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(54) Title: FABRICATING IONIC/POLYIMIDE MEMBRANES

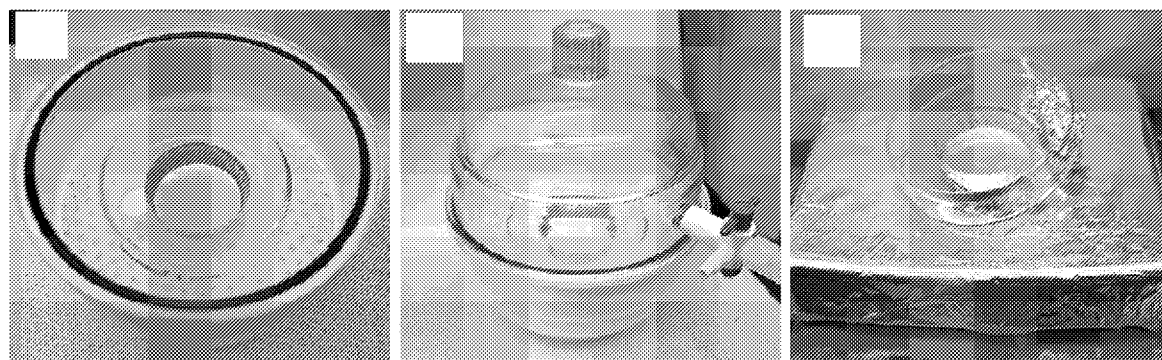


FIG. 1A

(57) Abstract: Disclosed are polyimide blends and methods of making and using same. The disclosed polyimide blends are prepared by first blending an ionic polymer and a poly(amic acid) to form a poly(amic acid) precursor, followed by cyclization. This abstract is intended as a scanning tool for purposes of searching in the particular art and is not intended to be limiting of the present invention.



FABRICATING IONIC/POLYIMIDE MEMBRANES

CROSS-REFERENCE TO RELATED APPLICATIONS

[0001] This Application claims the benefit of U.S. Provisional Application No. 62/371,622, filed on August 05, 2016, which is incorporated herein by reference in its entirety.

STATEMENT REGARDING FEDERALLY SPONSORED RESEARCH

[0002] This invention was made with Government support under Grant No. NNX13AN15A, awarded by the National Aeronautics and Space Administration (NASA). The Government has certain rights in the invention.

BACKGROUND

[0003] Ionic polymer-metal composite (IPMC) is a synthetic composite that typically consists of an ionomeric membrane (ion exchange membrane) plated with thin layers of noble metal electrode, such as platinum on both sides (Kim et al. (2014) *Robotics and Autonomous Systems* **62**: 53-60). IPMC is a unique active (smart) material which is a type of electroactive polymer (EAP). There are many types of EAPs such as ionic polymer gel (Terasawa et al. (2014) *Sensors and Actuators B* **202**: 382-387; Liu and Calvert (2000) *Adv. Mater.* **12**: 288-291; Shiga et al. (1993) *Journal of Applied Polymer Science* **47**: 113-291; Shahinpoor (1992) *Smart Mater. Struct.* **1**: 91-94), dielectric elastomer (Jung et al. (2008) *Sensors and Actuators A* **143**: 343-351; Pelrine et al. (2000) *Science* **287**: 836-839), carbon nanotube films (Jeon et al. (2004) *Journal of Applied Physics* **95**: 5736-5740; Kim et al. (2006) *Carbon* **44**: 1963-1968), ionic polymer-metal composites (IPMCs) (Shahinpoor and Kim (2001) *Smart Mater. Struct.* **10**: 819-833; Lee et al. (2005) *Smart Mater. Struct.* **14**: 1363-1368; Kim and Kim (2008) *Smart Mater. Struct.* **17**: 035011), etc. Among these EAPs, IPMCs have drawn enormous research interest over the past decades due to its flexibility since they use polymers as base materials, require low operating voltage (less than 5V), high strain rate, and have the ability to operate in water (Kim et al. (2014) *Robotics and Autonomous Systems* **62**: 53-60; Kim et al. (2011) *Sensors and Actuators B* **155**: 106-113). These properties make the IPMC an attractive research subject for use in underwater robotic applications (Shen et al. (2015) *Bioinspir. Biomim.* **10**: 055007; Palmre et al. (2013) *Smart Mater. Struct.* **22**: 014003), fluid flow sensor applications (Lee and Kim (2006) *Smart*

Mater. Struct. **15**: 1103-1109), biomedical and biomimetic application such as artificial muscles (Lu et al. (2008) *Adv. Func. Mater.* **18**: 1290-1298; Shahinpoor and Kim (2005) *Smart Mater. Struct.* **14**: 197-214; Jung et al. (2003) *Sensors and Actuators A* **107**: 183-192), space utilization (Krishen (2009) *Acta Astronautica* **64**: 1160-1166, and more.

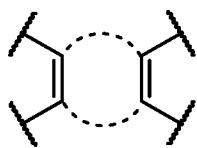
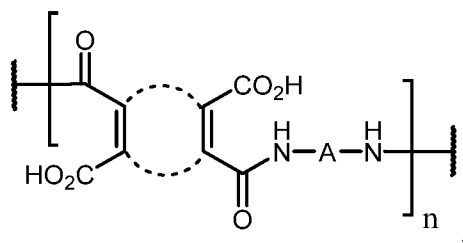
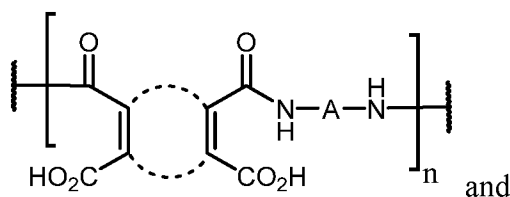
[0004] An ion exchange membrane is a fundamental base material for IPMC fabrication and an essential component that largely influences the performance of IPMCs. Among numerous commercially available ion exchange membranes, Nafion[®] has been and still is the most widely used ion exchange membrane material for IPMCs (Kim et al. (2014) *Robotics and Autonomous Systems* **62**: 53-60; Kim et al. (2011) *Sensors and Actuators B* **155**: 106-113; Kim and Shahinpoor (2002) *Polymer* **43**: 797-802; Lee et al. (2005) *Sensors and Actuators A* **118**: 98-106; Hwang et al. (2015) *Smart Mater. Struct.* **24**: 105011) owing to its advantages such as high proton conductivity, commercial availability, and good chemical stability (Ju et al. (2013) *Progress in Polymer Science* **38**: 1037-1066; Palmre et al. (2014) *Scientific Reports* **4**: 6176). Although Nafion-based IPMC actuators show good performance under low operating voltage, there are some drawbacks of Nafion that restrict its applications: reduced performance above 80 °C, high cost, and low storage modulus (Hickner et al. (2004) *Chem. Rev.* **104**: 4587-4612; Park et al. (2011) *SPE Plastics Research Online* DOI: 10.1002/spepro.003706). Many attempts have been done to lower the manufacturing cost by replacing Nafion (Hwang et al. (2015) *Smart Mater. Struct.* **24**: 105011; Kim et al. (2005) *Smart Mater. Struct.* **14**: 889-894), but they have only been partially successful. In addition, there have been some studies done with nanoparticles, such as layered silicates or carbon nanotubes, which can dramatically improve thermal stability and mechanical performance compared to Nafion-based IPMC actuators (Ajayan and Tour (2007) *Nature* **447**: 254-255; Kotov (2006) *Nature* **442**: 254-255; Giannelis (1996) *Adv. Mater.* **8**: 29-35). It is still imperative to continue to explore new ionic polymers with improved properties to be used in high performance IPMC actuators.

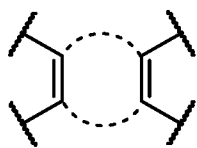
[0005] Despite the excellent electromechanical performance of Nafion, the high cost and physical properties of IPMC actuators prepared using Nafion leave much to be desired. Thus, there remains a need for ionic polymer-based IPMCs having improved thermal and mechanical properties. These needs and others are met by the present invention.

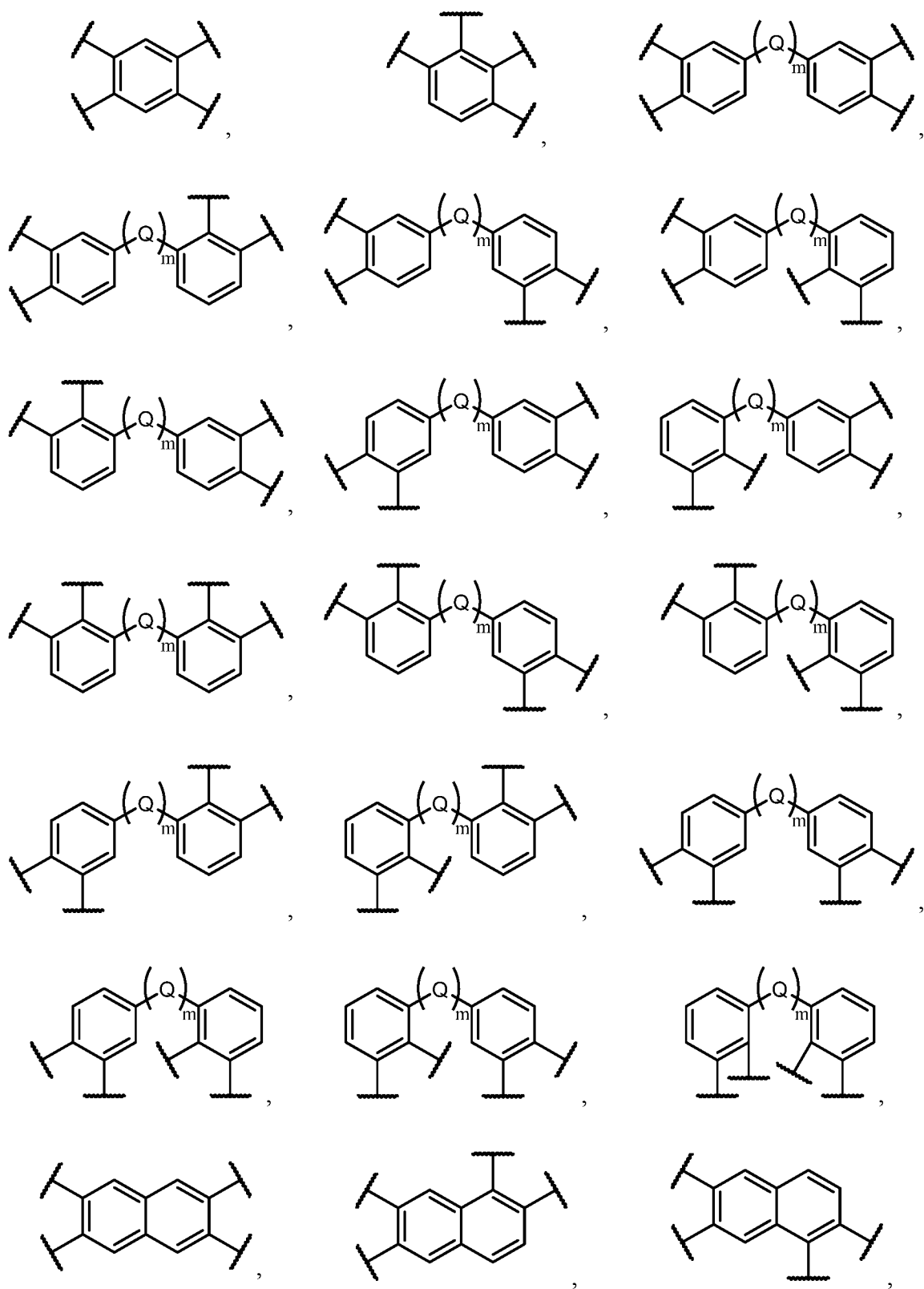
SUMMARY

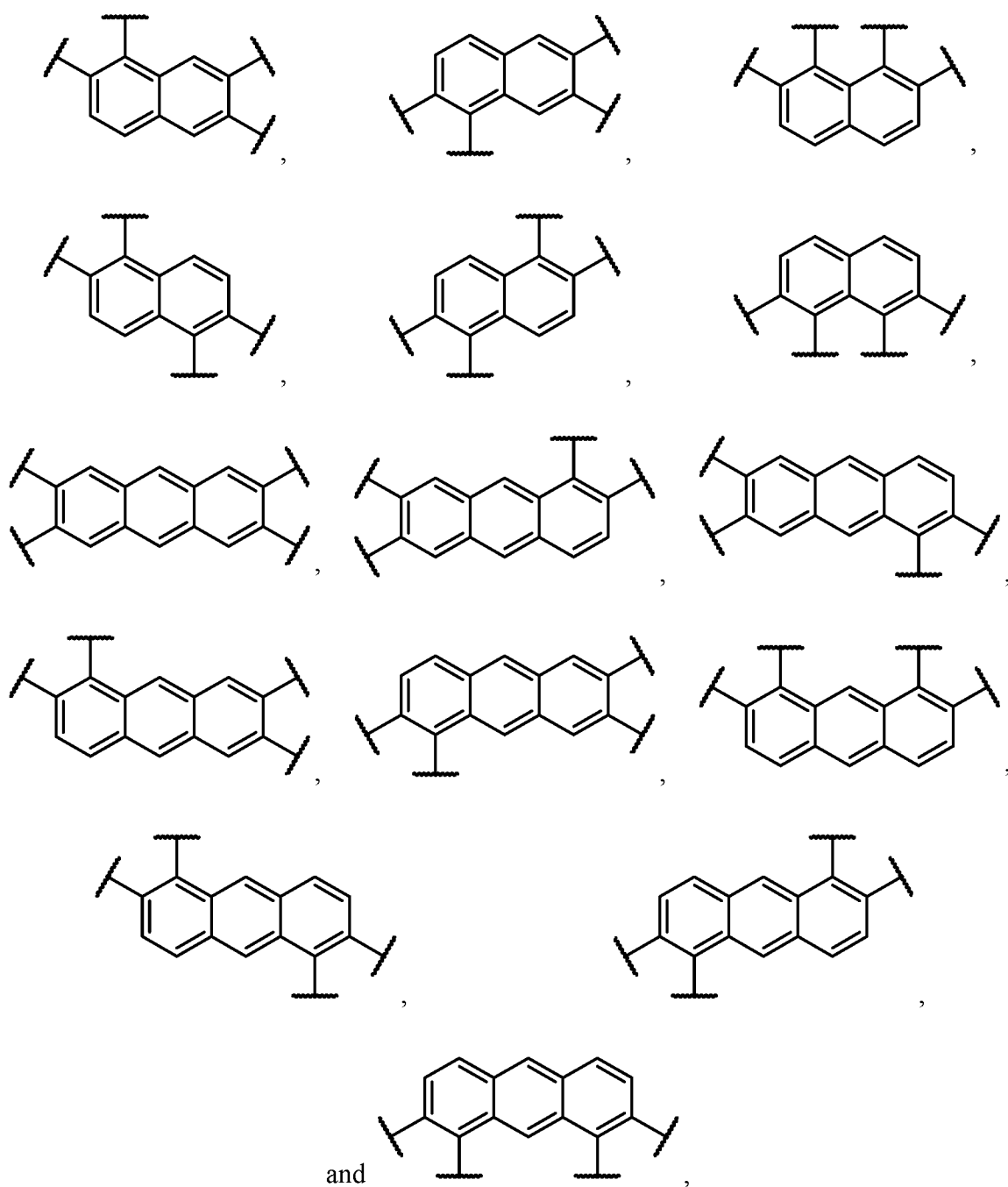
[0006] In accordance with the purpose(s) of the invention, as embodied and broadly described herein, the invention, in one aspect, relates to blend ion exchange membranes comprising an ionic polymer and a poly(amic acid) and their uses.

[0007] Disclosed are methods of making a polyimide blend, the method comprising: (a) mixing an ionic polymer selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion, and a poly(amic acid) comprising at least one residue having a structure represented by a formula selected from:

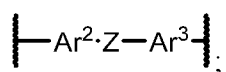


wherein  comprises a structure represented by a formula selected from:





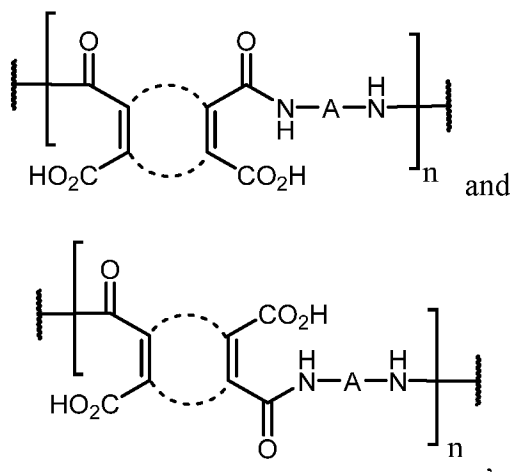
wherein n is an integer greater than 1; wherein m is 0 or 1; wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:

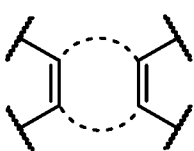


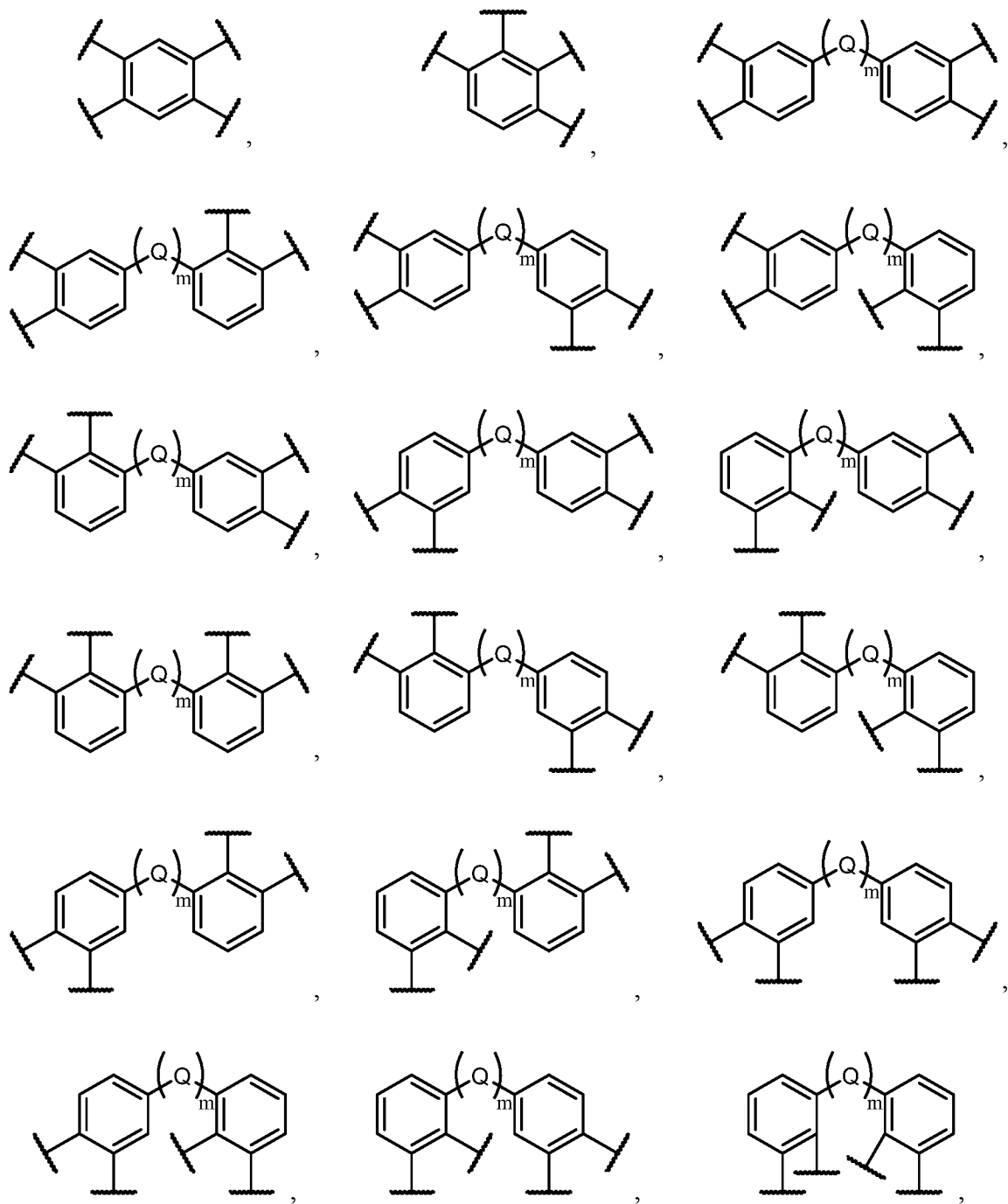
wherein Z , when present, is selected from O , NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO , and SO_2 ; wherein each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4

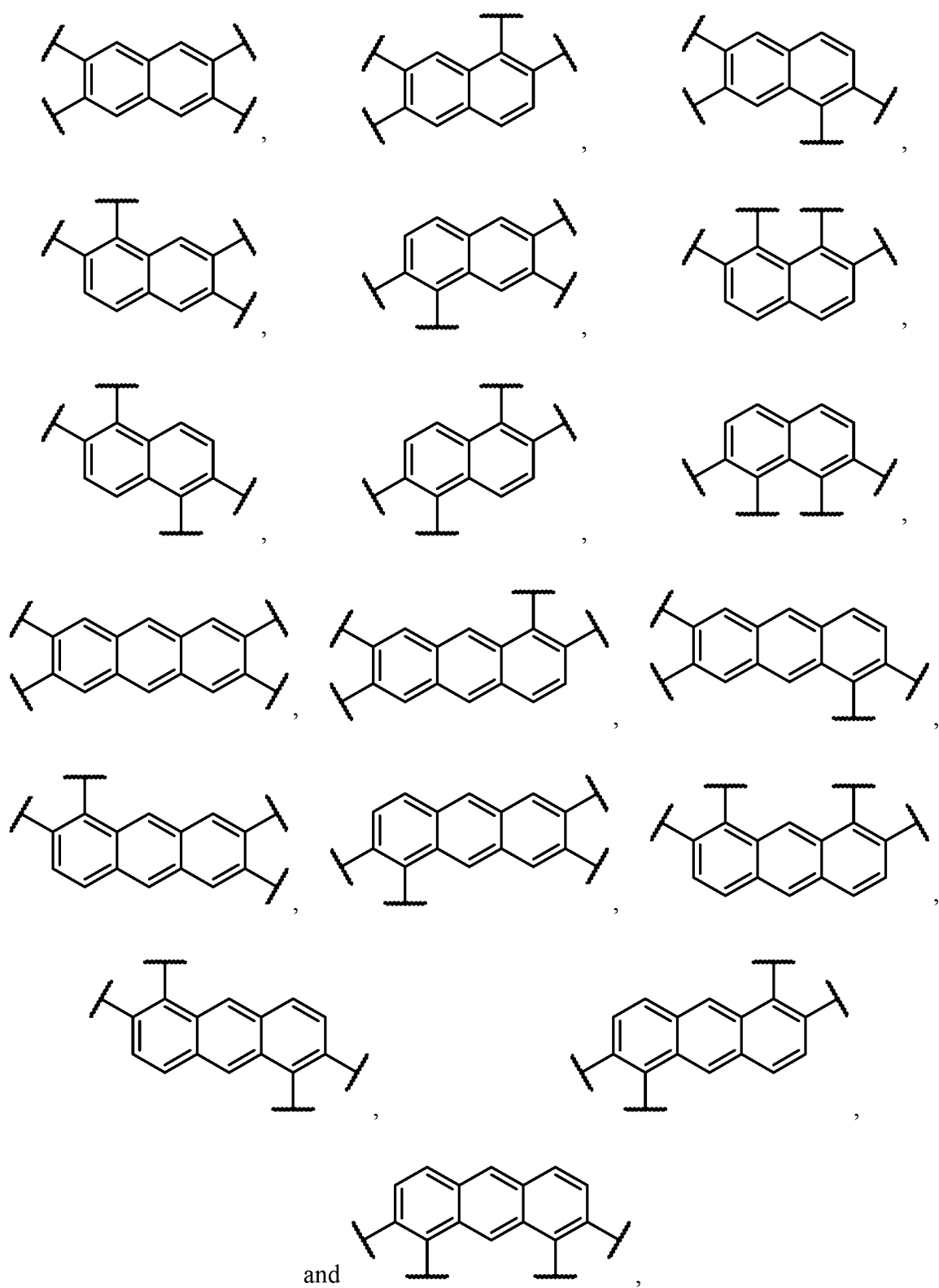
haloalkyl; wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein Q, when present, is selected from O, NR^1 , SO, SO_2 , $\text{C}(\text{O})$, and $\text{CR}^{2a}\text{R}^{2b}$; and wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl, thereby making a poly(amic acid) blend; and (b) cyclizing the poly(amic acid) blend.

[0008] Also disclosed are poly(amic acid) blends comprising: (a) an ionic polymer selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acrylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion; and (b) a poly(amic acid) comprising at least one residue having a structure represented by a formula selected from:

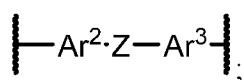


wherein  comprises a structure represented by a formula selected from:



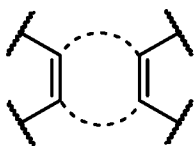
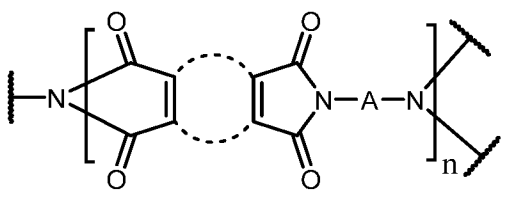


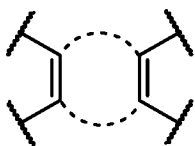
wherein n is an integer greater than 1; wherein m is 0 or 1; wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:

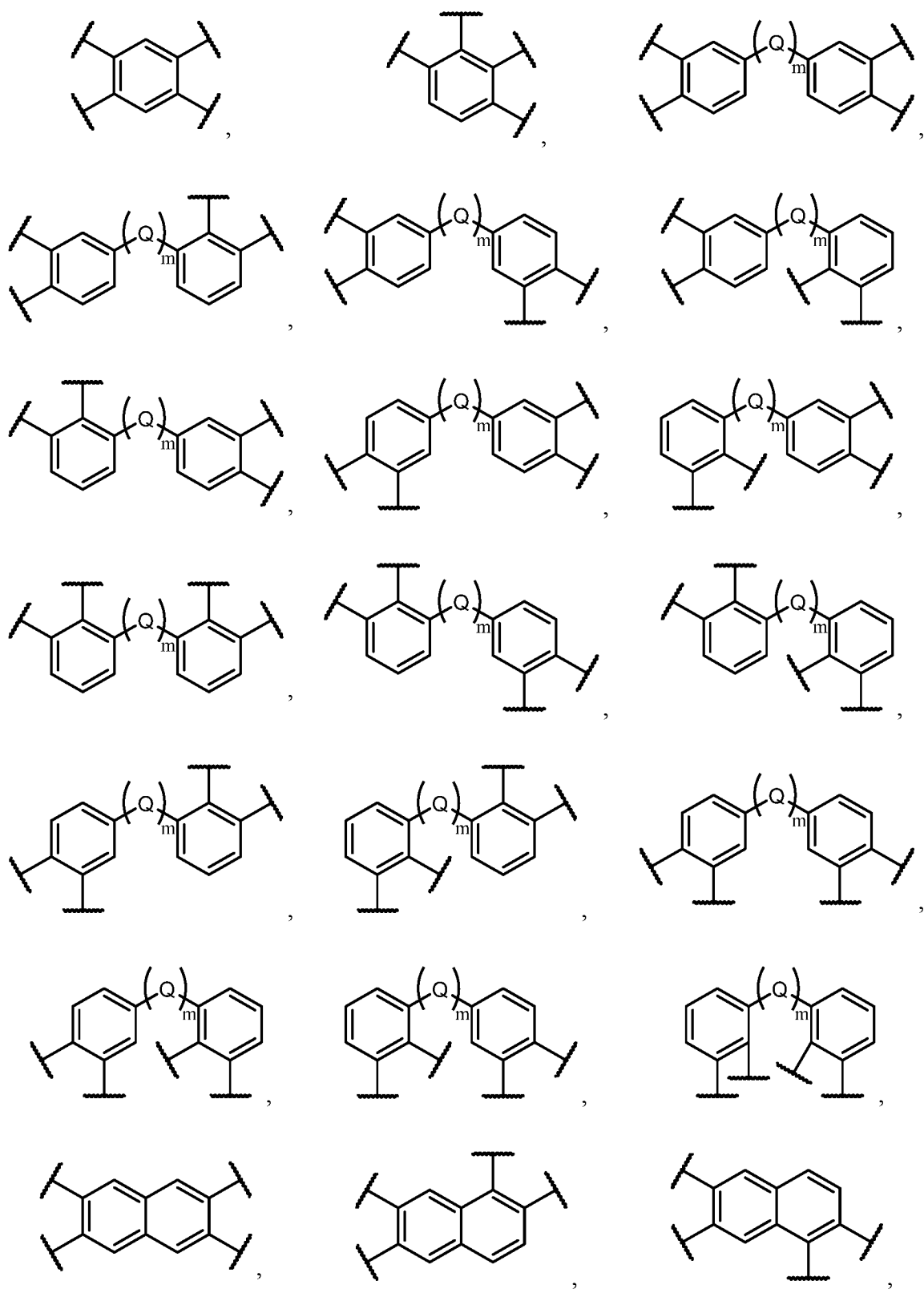


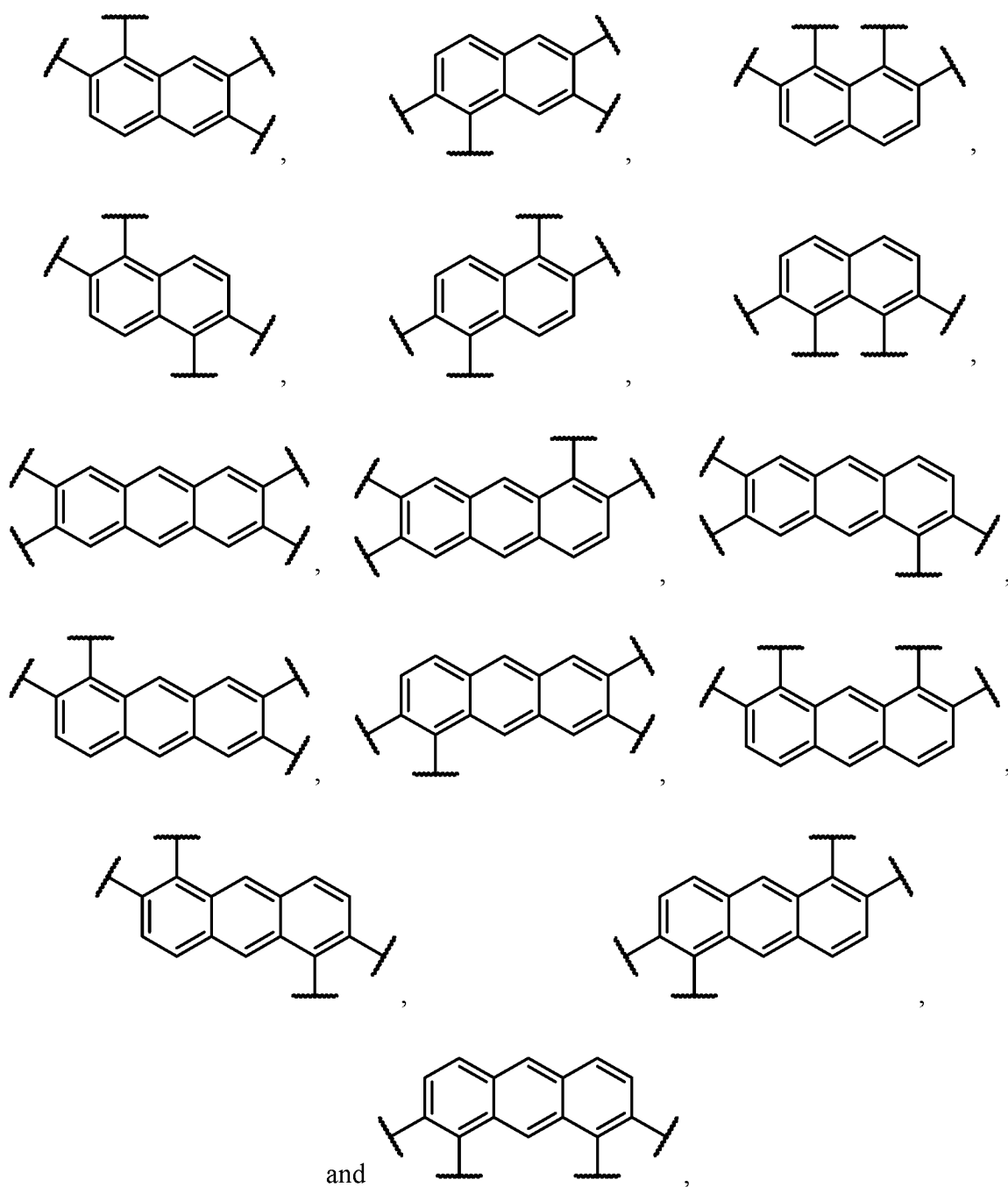
wherein Z, when present, is selected from O, NR³, CR^{4a}R^{4b}, CO, and SO₂; each of R³, R^{4a}, and R^{4b}, when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl; wherein Ar¹, when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, –OH, –CN, –NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein each of Ar² and Ar³, when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, –OH, –CN, –NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein Q, when present, is selected from O, NR¹, SO, SO₂, C(O), and CR^{2a}R^{2b}; and wherein each of R¹, R^{2a}, and R^{2b}, when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl.

[0009] Also disclosed are polyimide blends comprising: (a) an ionic polymer selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acrylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion; and (b) a polyimide comprising at least one residue having a structure represented by a formula:

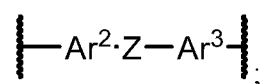


wherein  comprises a structure represented by a formula selected from:





wherein n is an integer greater than 1; wherein m is 0 or 1; wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:



wherein Z , when present, is selected from O , NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO , and SO_2 ; each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl;

wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein Q, when present, is selected from O, NR^1 , SO, SO_2 , $\text{C}(\text{O})$, and $\text{CR}^{2a}\text{R}^{2b}$; and wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl.

[0010] While aspects of the present invention can be described and claimed in a particular statutory class, such as the system statutory class, this is for convenience only and one of skill in the art will understand that each aspect of the present invention can be described and claimed in any statutory class. Unless otherwise expressly stated, it is in no way intended that any method or aspect set forth herein be construed as requiring that its steps be performed in a specific order. Accordingly, where a method claim does not specifically state in the claims or descriptions that the steps are to be limited to a specific order, it is no way intended that an order be inferred, in any respect. This holds for any possible non-express basis for interpretation, including matters of logic with respect to arrangement of steps or operational flow, plain meaning derived from grammatical organization or punctuation, or the number or type of aspects described in the specification.

BRIEF DESCRIPTION OF THE FIGURES

[0011] The accompanying figures, which are incorporated in and constitute a part of this specification, illustrate several aspects and together with the description serve to explain the principles of the invention.

[0012] **FIG. 1A** shows representative images of the sample preparation procedure.

[0013] **FIG. 1B** shows representative images of prepared membranes after thermal imidization (left to right: Nafion, NPI-6, NPI-12, NPI-18, and NPI-30; size = 1.0 x 1.0 cm).

[0014] **FIG. 2A-C** show representative images of fabricated IPMCs. Specifically, Nafion 117 (**2A**), NPI-18 (**2B**), and NPI-30 (**2C**) are shown.

[0015] **FIG. 3A** and **FIG. 3B** show representative FT-IR spectra of PAA film (untreated)

and PI film (treated) before and after thermal imidization for regions 4000-700 cm^{-1} (**3A**) and 2200-700 cm^{-1} (**3B**).

[0016] **FIG. 4A** and **FIG. 4B** show representative FT-IR spectra of Nafion, NPI-6, NPI-12, NPI-18, NPI-30, and polyimide for regions 4000-700 cm^{-1} (**4A**) and 2200-700 cm^{-1} (**4B**).

[0017] **FIG. 5A** and **FIG. 5B** show representative TGA (**4A**) and TGA derivative curve (**4B**) of the membranes using the Q500 (TA) increasing temperature 30-700 $^{\circ}\text{C}$, heating rate 10 $^{\circ}\text{C}/\text{min}$ in nitrogen environment.

[0018] **FIG. 6A-D** show representative DMA results of membranes Nafion 117, NPI-6, NPI-12, and polyimide. Specifically, storage modulus (**6A**), loss modulus (**6B**), and $\tan \delta$ (**6C**) with a frequency range from 0.01 to 20 Hz in tensile mode are shown. **FIG. 6D** shows representative storage modulus, loss modulus, and $\tan \delta$ of samples at 10 Hz.

[0019] **FIG. 7A-D** show representative SEM images of prepared IPMCs. Specifically, Nafion (**7A**), NPI-6 (**7B**), NPI-12 (**7C**), and NPI-18 (**7D**) are shown.

[0020] **FIG. 8A-C** show representative data pertaining to the actuation performance of the IPMC actuators (Nafion 117 and NPI-18). Specifically, **FIG. 8A** shows the measured voltage, current, displacement responses, and bending strain at ± 3 V, AC square-wave under 0.1 Hz together with a superimposed image of video captures of NPI-18 actuator at 0.1 Hz. **FIG. 8B** and **FIG. 8C** show the measured voltage, current, displacement responses, and bending strain at ± 3 V, AC square wave under 0.5 Hz and 1.0 Hz, respectively.

[0021] **FIG. 9A-C** show representative images of prepared IPMC actuators. Specifically, Nafion 117 (**9A**), NPI-18 (**9B**), and NPI-30 (**9C**) with/without applying voltage (± 3 V, AC) under varied frequency (0.1, 0.5, and 1.0 Hz) are shown.

[0022] **FIG. 10** shows representative blocking force responses in time at 3 V, DC for IPMC actuators comparing Nafion 117 and NPI-18.

[0023] Additional advantages of the invention will be set forth in part in the description which follows, and in part will be obvious from the description, or may be learned by practice of the invention. The advantages of the invention will be realized and attained by means of the elements and combinations particularly pointed out in the appended claims. It is to be

understood that both the foregoing general description and the following detailed description are exemplary and explanatory only and are not restrictive of the invention, as claimed.

DETAILED DESCRIPTION

[0024] The present invention can be understood more readily by reference to the following detailed description of the invention and the Examples included therein.

[0025] Before the present compounds, compositions, articles, devices, and/or methods are disclosed and described, it is to be understood that they are not limited to specific synthetic methods unless otherwise specified, or to particular reagents unless otherwise specified, as such may, of course, vary. It is also to be understood that the terminology used herein is for the purpose of describing particular aspects only and is not intended to be limiting. Although any methods and materials similar or equivalent to those described herein can be used in the practice or testing of the present invention, example methods and materials are now described.

[0026] Although any methods and materials similar or equivalent to those described herein can be used in the practice or testing of the present invention, example methods and materials are now described.

[0027] All publications mentioned herein are incorporated herein by reference to disclose and describe the methods and/or materials in connection with which the publications are cited. The publications discussed herein are provided solely for their disclosure prior to the filing date of the present application. Nothing herein is to be construed as an admission that the present invention is not entitled to antedate such publication by virtue of prior invention. Further, the dates of publication provided herein may be different from the actual publication dates, which can require independent confirmation.

A. DEFINITIONS

[0028] As used herein, nomenclature for compounds, including organic compounds, can be given using common names, IUPAC, IUBMB, or CAS recommendations for nomenclature. When one or more stereochemical features are present, Cahn-Ingold-Prelog rules for stereochemistry can be employed to designate stereochemical priority, *E/Z* specification, and the like. One of skill in the art can readily ascertain the structure of a compound if given a name,

either by systemic reduction of the compound structure using naming conventions, or by commercially available software, such as CHEMDRAWTM (Cambridgesoft Corporation, U.S.A.).

[0029] As used in the specification and the appended claims, the singular forms “a,” “an” and “the” include plural referents unless the context clearly dictates otherwise. Thus, for example, reference to “a component,” “a polymer,” or “a particle” includes mixtures of two or more such components, polymers, or particles, and the like.

[0030] Ranges can be expressed herein as from “about” one particular value, and/or to “about” another particular value. When such a range is expressed, another aspect includes from the one particular value and/or to the other particular value. Similarly, when values are expressed as approximations, by use of the antecedent “about,” it will be understood that the particular value forms another aspect. It will be further understood that the endpoints of each of the ranges are significant both in relation to the other endpoint, and independently of the other endpoint. It is also understood that there are a number of values disclosed herein, and that each value is also herein disclosed as “about” that particular value in addition to the value itself. For example, if the value “10” is disclosed, then “about 10” is also disclosed. It is also understood that when a value is disclosed that “less than or equal to” the value, “greater than or equal to the value” and possible ranges between values are also disclosed, as appropriately understood by the skilled artisan. For example, if the value “10” is disclosed the “less than or equal to 10” as well as “greater than or equal to 10” is also disclosed. It is also understood that throughout the application, data is provided in a number of different formats and that this data represents endpoints and starting points, and ranges for any combination of the data points. For example, if a particular data point “10” and a particular data point 15 are disclosed, it is understood that greater than, greater than or equal to, less than, less than or equal to, and equal to 10 and 15 are considered disclosed as well as between 10 and 15. It is also understood that each unit between two particular units are also disclosed. For example, if 10 and 15 are disclosed, then 11, 12, 13, and 14 are also disclosed.

[0031] References in the specification and concluding claims to parts by weight of a particular element or component in a composition denotes the weight relationship between the element or component and any other elements or components in the composition or article for

which a part by weight is expressed. Thus, in a compound containing 2 parts by weight of component X and 5 parts by weight component Y, X and Y are present at a weight ratio of 2:5, and are present in such ratio regardless of whether additional components are contained in the compound.

[0032] A weight percent (wt. %) of a component, unless specifically stated to the contrary, is based on the total weight of the formulation or composition in which the component is included.

[0033] As used herein, the terms “optional” or “optionally” means that the subsequently described event or circumstance may or may not occur, and that the description includes instances where said event or circumstance occurs and instances where it does not.

[0034] As used herein, the terms “effective amount” and “amount effective” refer to an amount that is sufficient to achieve the desired result or to have an effect on an undesired condition.

[0035] The term “stable,” as used herein, refers to compositions that are not substantially altered when subjected to conditions to allow for their production, detection, and, in certain aspects, their recovery, purification, and use for one or more of the purposes disclosed herein.

[0036] As used herein, the term “polymer” refers to a relatively high molecular weight organic compound, natural or synthetic, whose structure can be represented by a repeated small unit, the monomer (e.g., polyethylene, rubber, cellulose). Synthetic polymers are typically formed by addition or condensation polymerization of monomers.

[0037] As used herein, the term “homopolymer” refers to a polymer formed from a single type of repeating unit (monomer residue).

[0038] As used herein, the term “copolymer” refers to a polymer formed from two or more different repeating units (monomer residues). By way of example and without limitation, a copolymer can be an alternating copolymer, a random copolymer, a block copolymer, or a graft copolymer. It is also contemplated that, in certain aspects, various block segments of a block copolymer can themselves comprise copolymers.

[0039] As used herein, the term “oligomer” refers to a relatively low molecular weight polymer in which the number of repeating units is between two and ten, for example, from two to eight, from two to six, or from two to four. In one aspect, a collection of oligomers can have

an average number of repeating units of from about two to about ten, for example, from about two to about eight, from about two to about six, or from about two to about four.

[0040] As used herein, the term “cross-linked polymer” refers to a polymer having bonds linking one polymer chain to another.

[0041] The term “alkyl” as used herein is a branched or unbranched saturated hydrocarbon group of 1 to 24 carbon atoms, such as methyl, ethyl, *n*-propyl, isopropyl, *n*-butyl, isobutyl, *s*-butyl, *t*-butyl, *n*-pentyl, isopentyl, *s*-pentyl, neopentyl, hexyl, heptyl, octyl, nonyl, decyl, dodecyl, tetradecyl, hexadecyl, eicosyl, tetracosyl, and the like. The alkyl group can be cyclic or acyclic. The alkyl group can be branched or unbranched. The alkyl group can also be substituted or unsubstituted. For example, the alkyl group can be substituted with one or more groups including, but not limited to, alkyl, cycloalkyl, alkoxy, amino, ether, halide, hydroxy, nitro, silyl, sulfo-oxo, or thiol, as described herein. A “lower alkyl” group is an alkyl group containing from one to six (e.g., from one to four) carbon atoms. Non-limiting examples of alkyls include C1-18 alkyl, C1-C12 alkyl, C1-C8 alkyl, C1-C6 alkyl, C1-C3 alkyl, and C1 alkyl.

[0042] Throughout the specification “alkyl” is generally used to refer to both unsubstituted alkyl groups and substituted alkyl groups; however, substituted alkyl groups are also specifically referred to herein by identifying the specific substituent(s) on the alkyl group. For example, the term “halogenated alkyl” or “haloalkyl” specifically refers to an alkyl group that is substituted with one or more halide, e.g., fluorine, chlorine, bromine, or iodine. The term “alkoxyalkyl” specifically refers to an alkyl group that is substituted with one or more alkoxy groups, as described below. The term “alkylamino” specifically refers to an alkyl group that is substituted with one or more amino groups, as described below, and the like. When “alkyl” is used in one instance and a specific term such as “alkylalcohol” is used in another, it is not meant to imply that the term “alkyl” does not also refer to specific terms such as “alkylalcohol” and the like.

[0043] The term “alkenyl” as used herein is a hydrocarbon group of 2 to 24 carbon atoms with a structural formula containing at least one carbon-carbon double bond. The alkenyl group can be unsubstituted or substituted with one or more groups including, but not limited to, alkyl, cycloalkyl, alkoxy, alkenyl, cycloalkenyl, alkynyl, cycloalkynyl, aryl, heteroaryl, aldehyde, amino, carboxylic acid, ester, ether, halide, hydroxy, ketone, azide, nitro, silyl, sulfo-oxo, or thiol, as described herein. Non-limiting examples of alkenyls include C2-18 alkenyl, C2-12

alkenyl, C2-8 alkenyl, C2-6 alkenyl, and C2-3 alkenyl.

[0044] The term “alkynyl” as used herein is a hydrocarbon group of 2 to 24 carbon atoms with a structural formula containing at least one carbon-carbon triple bond. The alkynyl group can be unsubstituted or substituted with one or more groups including, but not limited to, alkyl, cycloalkyl, alkoxy, alkenyl, cycloalkenyl, alkynyl, cycloalkynyl, aryl, heteroaryl, aldehyde, amino, carboxylic acid, ester, ether, halide, hydroxy, ketone, azide, nitro, silyl, sulfo-oxo, or thiol, as described herein. Non-limiting examples of alkynyls include C2-18 alkynyl, C2-12 alkynyl, C2-8 alkynyl, C2-6 alkynyl, and C2-3 alkynyl.

[0045] The terms “amine” or “amino” as used herein are represented by the formula $\text{—NA}^1\text{A}^2$, where A^1 and A^2 can be, independently, hydrogen or alkyl, cycloalkyl, alkenyl, cycloalkenyl, alkynyl, cycloalkynyl, aryl, or heteroaryl group as described herein.

[0046] The term “ester” as used herein is represented by the formula —OC(O)A^1 or —C(O)OA^1 , where A^1 can be alkyl, cycloalkyl, alkenyl, cycloalkenyl, alkynyl, cycloalkynyl, aryl, or heteroaryl group as described herein. The term “polyester” as used herein is represented by the formula $\text{—(A}^1\text{O(O)C—A}^2\text{—C(O)O)}_a\text{—}$ or $\text{—(A}^1\text{O(O)C—A}^2\text{—OC(O))}_a\text{—}$, where A^1 and A^2 can be, independently, an alkyl, cycloalkyl, alkenyl, cycloalkenyl, alkynyl, cycloalkynyl, aryl, or heteroaryl group described herein and “a” is an integer from 1 to 500. “Polyester” is used to describe a group that is produced by the reaction between a compound having at least two carboxylic acid groups with a compound having at least two hydroxyl groups.

[0047] The term “ether” as used herein is represented by the formula A^1OA^2 , where A^1 and A^2 can be, independently, an alkyl, cycloalkyl, alkenyl, cycloalkenyl, alkynyl, cycloalkynyl, aryl, or heteroaryl group described herein. The term “polyether” as used herein is represented by the formula $\text{—(A}^1\text{O—A}^2\text{O)}_a\text{—}$, where A^1 and A^2 can be, independently, an alkyl, cycloalkyl, alkenyl, cycloalkenyl, alkynyl, cycloalkynyl, aryl, or heteroaryl group described herein and “a” is an integer of from 1 to 500. Examples of polyether groups include polyethylene oxide, polypropylene oxide, and polybutylene oxide.

[0048] The term “azide” as used herein is represented by the formula —N_3 .

[0049] The term “thiol” as used herein is represented by the formula —SH .

[0050] Compounds described herein can contain one or more double bonds and, thus,

potentially give rise to cis/trans (E/Z) isomers, as well as other conformational isomers. Unless stated to the contrary, the invention includes all such possible isomers, as well as mixtures of such isomers.

[0051] Certain materials, compounds, compositions, and components disclosed herein can be obtained commercially or readily synthesized using techniques generally known to those of skill in the art. For example, the starting materials and reagents used in preparing the disclosed compounds and compositions are either available from commercial suppliers such as Aldrich Chemical Co., (Milwaukee, Wis.), Acros Organics (Morris Plains, N.J.), Fisher Scientific (Pittsburgh, Pa.), or Sigma (St. Louis, Mo.) or are prepared by methods known to those skilled in the art following procedures set forth in references such as Fieser and Fieser's Reagents for Organic Synthesis, Volumes 1-17 (John Wiley and Sons, 1991); Rodd's Chemistry of Carbon Compounds, Volumes 1-5 and Supplemental volumes (Elsevier Science Publishers, 1989); Organic Reactions, Volumes 1-40 (John Wiley and Sons, 1991); March's Advanced Organic Chemistry, (John Wiley and Sons, 4th Edition); and Larock's Comprehensive Organic Transformations (VCH Publishers Inc., 1989).

[0052] Unless otherwise expressly stated, it is in no way intended that any method set forth herein be construed as requiring that its steps be performed in a specific order. Accordingly, where a method claim does not actually recite an order to be followed by its steps or it is not otherwise specifically stated in the claims or descriptions that the steps are to be limited to a specific order, it is no way intended that an order be inferred, in any respect. This holds for any possible non-express basis for interpretation, including: matters of logic with respect to arrangement of steps or operational flow; plain meaning derived from grammatical organization or punctuation; and the number or type of embodiments described in the specification.

[0053] Disclosed are the components to be used to prepare the compositions of the invention as well as the compositions themselves to be used within the methods disclosed herein. These and other materials are disclosed herein, and it is understood that when combinations, subsets, interactions, groups, etc. of these materials are disclosed that while specific reference of each various individual and collective combinations and permutation of these compounds may not be explicitly disclosed, each is specifically contemplated and described herein. For example, if a particular compound is disclosed and discussed and a number of modifications that can be made

to a number of molecules including the compounds are discussed, specifically contemplated is each and every combination and permutation of the compound and the modifications that are possible unless specifically indicated to the contrary. Thus, if a class of molecules A, B, and C are disclosed as well as a class of molecules D, E, and F and an example of a combination molecule, A-D is disclosed, then even if each is not individually recited each is individually and collectively contemplated meaning combinations, A-E, A-F, B-D, B-E, B-F, C-D, C-E, and C-F are considered disclosed. Likewise, any subset or combination of these is also disclosed. Thus, for example, the sub-group of A-E, B-F, and C-E would be considered disclosed. This concept applies to all aspects of this application including, but not limited to, steps in methods of making and using the compositions of the invention. Thus, if there are a variety of additional steps that can be performed it is understood that each of these additional steps can be performed with any specific aspect or combination of aspects of the methods of the invention.

[0054] It is understood that the compositions disclosed herein have certain functions. Disclosed herein are certain structural requirements for performing the disclosed functions, and it is understood that there are a variety of structures that can perform the same function that are related to the disclosed structures, and that these structures will typically achieve the same result.

B. IONIC-POLYMER METAL COMPOSITES (IPMCs)

[0055] Ionic electroactive polymers (EAPs) are polymers that show change in size or shape when electrical stimulation is applied. These EAPs form a composite with metal on the surface which is electrically conductive, undergoing large amounts of bending deformation while sustaining large forces when electrically stimulated. Examples of EAPs include, but are not limited to, ionic polymer gels, dielectric elastomers, carbon nanotube films, and ionic polymer-metal composites (IPMCs).

[0056] IPMCs are composed of two parts: ionic polymer membrane and metal electrode. Ionic polymer membranes such as Nafion or Flemion are electrochemically plated on the surface of the membrane with metals such as gold or platinum. When an IPMC is fabricated, it contains cations, anions, and water molecules inside. When a small voltage is applied to it (generally less than 5V), hydrated mobile ions (either cations or anions) in the ion exchange membrane move toward the anode or cathode, respectively, forming a volumetric gradient or a pressure gradient

between the electrodes on both sides. This gradient is responsible for the deformation of the IPMC.

[0057] Ion exchange membranes are fundamental materials used to fabricate IPMCs and a very significant factor that largely influences the performance of IPMCs. Without wishing to be bound by theory, the term ion exchange membrane may refer to a membrane that is designed to transport ions selectively across the polymeric membrane owing to ionic groups present in the membrane. Depending on the type of ionic groups attached, there are two types of ion exchange membranes: (1) cation exchange membranes; and (2) anion exchange membranes. Cation exchange membranes contain fixed cationic groups that allow the passage of cations and block anions. Conversely, anionic exchange membranes contain fixed anionic groups that allow the passage of anions and block cations.

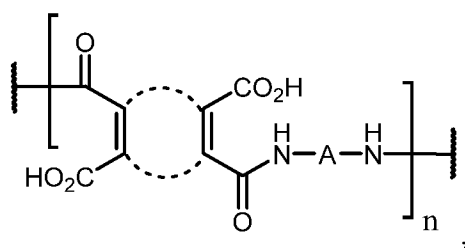
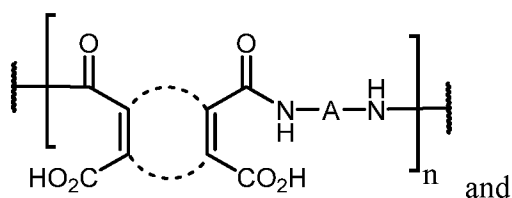
[0058] The most commonly used commercially available material for fabricating IPMCs is Nafion (31, 32). Nafion is a perfluorinated polymer known for its flexibility, light weight, immediate bending response, softness, low actuating voltage (<5 V), large bending deformation, commercial availability, appropriate mechanical robustness, good chemical stability, and high proton conductivity (36). Moreover, Nafion has high ion conductivity of around 0.1 S cm^{-1} in $1 \text{ M H}_2\text{SO}_4$ at 20°C measured using a DC current pulse (37).

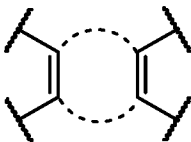
[0059] Here, IPMC actuators using blend ion exchange membranes comprising an ionic polymer and a polyimide are disclosed. In various aspects, these IPMC actuators may have comparable electromechanical properties to Nafion-only based actuators. In a further aspect, the disclosed IPMC actuators may have improved electromechanical properties to Nafion-only based actuators. In a still further aspect, the disclosed IPMC actuators may have comparable thermal properties to Nafion-only based actuators. In yet a further aspect, the disclosed IPMC actuators may have improved thermal properties to Nafion-only based actuators. In an even further aspect, the disclosed IPMC actuators may have comparable mechanical properties to Nafion-only based actuators. In a still further aspect, the disclosed IPMC actuators may have improved mechanical properties to Nafion-only based actuators.

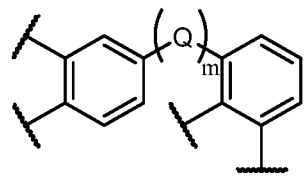
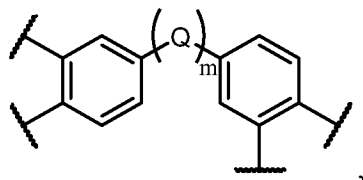
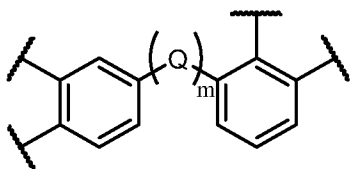
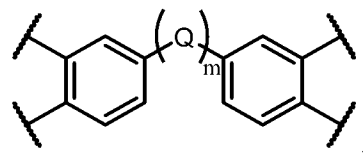
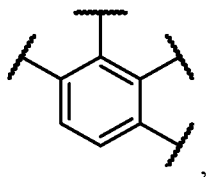
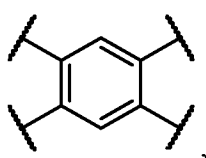
C. POLY(AMIC ACID) BLENDS

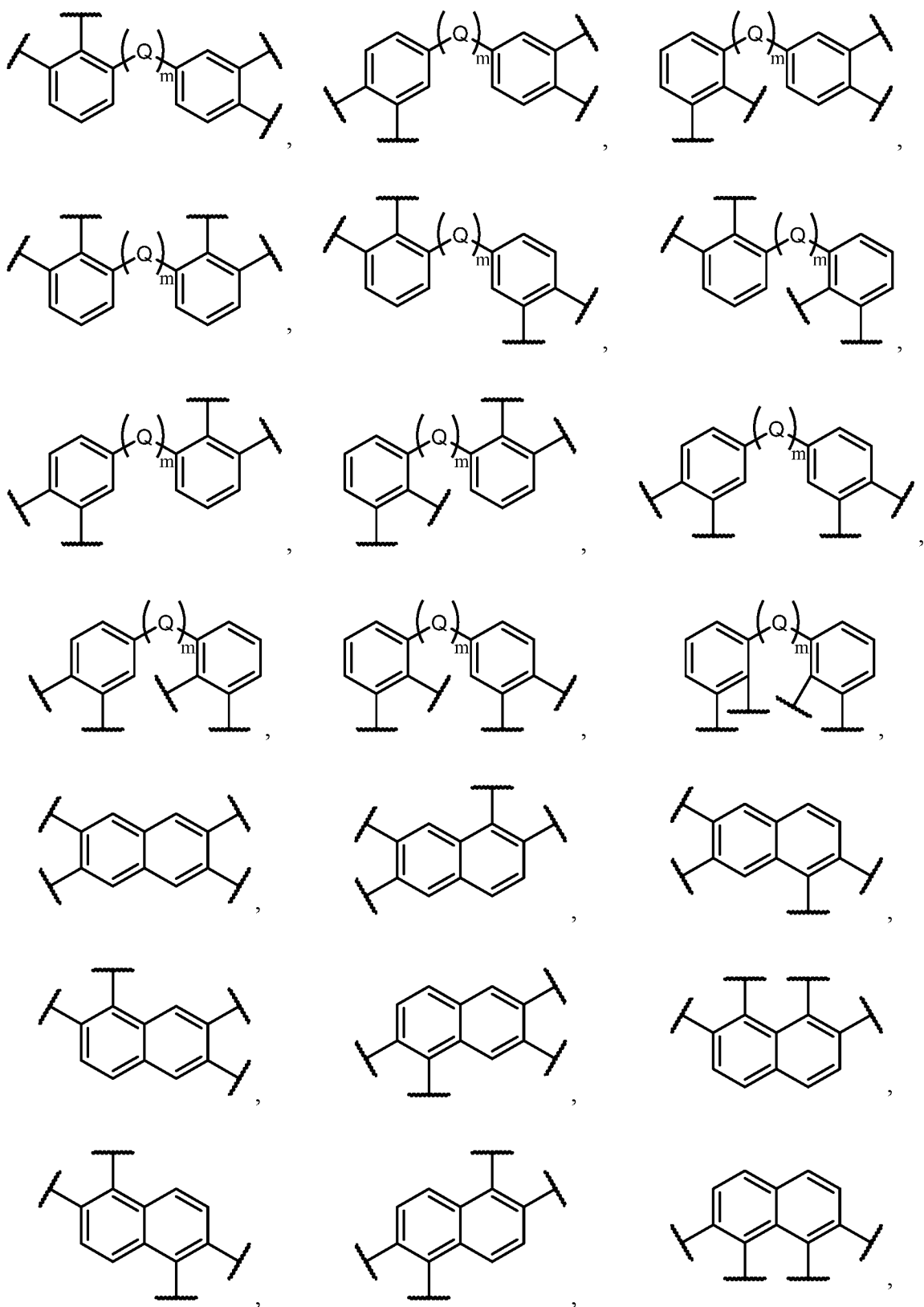
[0060] In one aspect, disclosed are poly(amic acid) blends comprising: (a) an ionic polymer

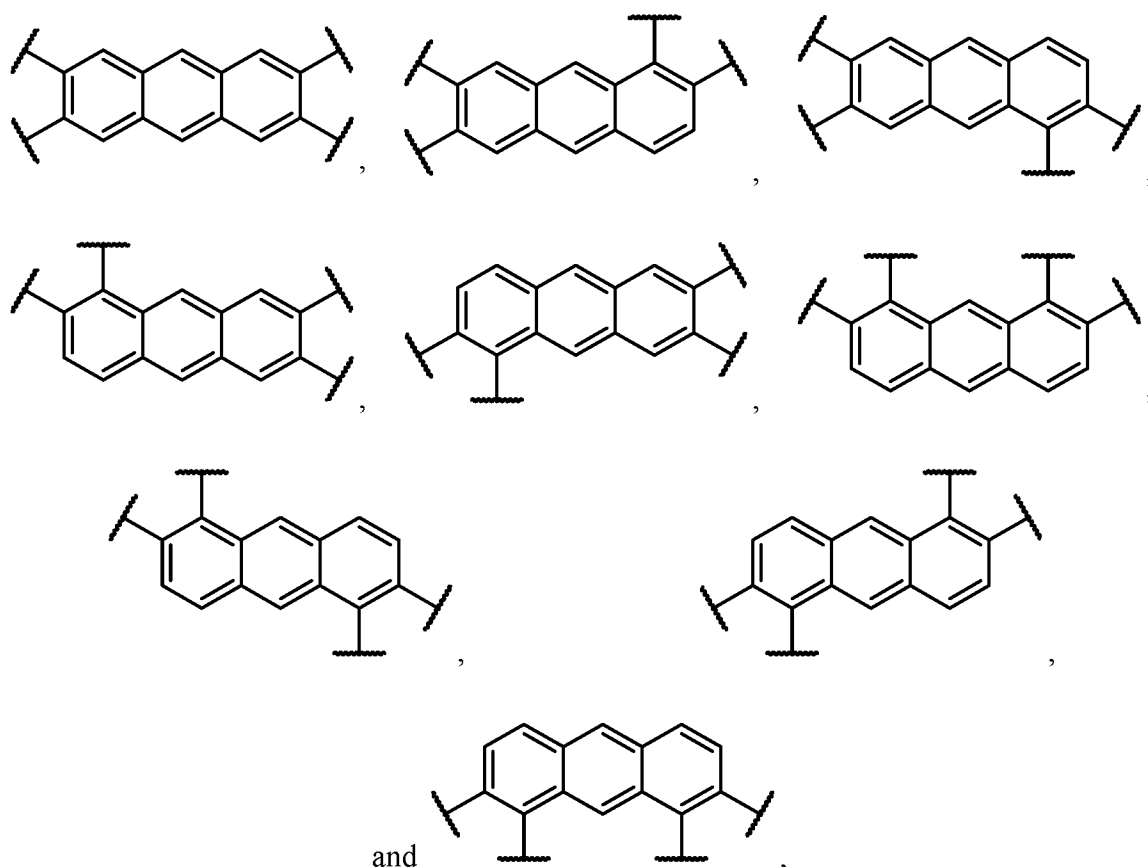
selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion; and (b) a poly(amic acid) comprising at least one residue having a structure represented by a formula selected from:



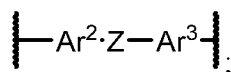
wherein  comprises a structure represented by a formula selected from:







wherein n is an integer greater than 1; wherein m is 0 or 1; wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:



wherein Z , when present, is selected from O , NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO , and SO_2 ; each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl; wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein Q , when present, is selected from O , NR^1 , SO , SO_2 , $\text{C}(\text{O})$, and $\text{CR}^{2a}\text{R}^{2b}$; and wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl.

[0061] Due to the rigidity of polymer backbone and strong interchain interactions, most polyimides are insoluble in organic solvents and intractable in their imide forms. Therefore, to make a blend ion exchange membrane of polyimide and ionic polymer, a blend membrane of poly(amic acid) (PAA), the precursor of polyimide (PI), and ionic polymer should be prepared first. This is due to the fact that PAA is soluble in organic solvents such as, for example, N-methyl-2-pyrrolidone (NMP) while PI is not. Once a PAA/ionic polymer membranes has been prepared, the PAA can be transformed to PI, resulting in a blend membrane of PI and ionic polymer.

[0062] In a further aspect, the poly(amic acid) is present in an amount of from about 1.0 wt% to about 30 wt% of the pol(amic acid) blend. In a still further aspect, the poly(amic acid) is present in an amount of from about 1.0 wt% to about 25 wt% of the pol(amic acid) blend. In yet a further aspect, the poly(amic acid) is present in an amount of from about 1.0 wt% to about 20 wt% of the pol(amic acid) blend. In an even further aspect, the poly(amic acid) is present in an amount of from about 1.0 wt% to about 15 wt% of the pol(amic acid) blend. In a still further aspect, the poly(amic acid) is present in an amount of from about 1.0 wt% to about 10 wt% of the pol(amic acid) blend. In yet a further aspect, the poly(amic acid) is present in an amount of from about 1.0 wt% to about 5.0 wt% of the pol(amic acid) blend. In an even further aspect, the poly(amic acid) is present in an amount of from about 5.0 wt% to about 30 wt% of the pol(amic acid) blend. In a still further aspect, the poly(amic acid) is present in an amount of from about 10 wt% to about 30 wt% of the pol(amic acid) blend. In yet a further aspect, the poly(amic acid) is present in an amount of from about 15 wt% to about 30 wt% of the pol(amic acid) blend. In an even further aspect, the poly(amic acid) is present in an amount of from about 20 wt% to about 30 wt% of the pol(amic acid) blend. In a still further aspect, the poly(amic acid) is present in an amount of from about 25 wt% to about 30 wt% of the pol(amic acid) blend. In yet a further aspect, the poly(amic acid) is present in an amount of from about 5.0 wt% to about 25 wt% of the pol(amic acid) blend. In an even further aspect, the poly(amic acid) is present in an amount of from about 10 wt% to about 20 wt% of the pol(amic acid) blend. In a still further aspect, the poly(amic acid) is present in an amount of from about 15 wt% to about 20 wt% of the pol(amic acid) blend. In yet a further aspect, the poly(amic acid) is present in an amount of from about 18 wt% to about 20 wt% of the poly(amic acid) blend.

[0063] In a further aspect, the poly(amic acid) blend comprises a solvent. Examples of

solvents include, but are not limited to, N,N-dimethylformamide, N,N-dimethylacetamide, N,N-diethylacetamide, N-methyl-2-pyrrolidone, N-ethyl-2-pyrrolidone, 1,3-dimethyl-2-imidazolidinone, N-methylcaprolactam, hexamethylphosphorotriamide, 1,2-dimethoxyethane, bis(2-methoxyethyl) ether, 1,2-bis(2-methoxyethoxy)ethane, tetrahydrofuran, bis[2-(2-methoxyethoxy)ethyl] ether, 1,4-dioxane, dimethylsulfoxide, dimethylsulfone, diphenyl ether, sulfolane, diphenylsulfone, tetramethylurea, and anisole. In a still further aspect, the solvent is selected from N,N-dimethylformamide and N-methyl-2-pyrrolidone.

[0064] In a further aspect, the solvent is present in amount of from about 10 volume% to about 50 volume% of the poly(amic acid) blend. In a still further aspect, the solvent is present in amount of from about 10 volume% to about 45 volume% of the poly(amic acid) blend. In yet a further aspect, the solvent is present in amount of from about 10 volume% to about 40 volume% of the poly(amic acid) blend. In an even further aspect, the solvent is present in amount of from about 10 volume% to about 35 volume% of the poly(amic acid) blend. In a still further aspect, the solvent is present in amount of from about 10 volume% to about 30 volume% of the poly(amic acid) blend. In yet a further aspect, the solvent is present in amount of from about 10 volume% to about 25 volume% of the poly(amic acid) blend. In an even further aspect, the solvent is present in amount of from about 10 volume% to about 20 volume% of the poly(amic acid) blend. In a still further aspect, the solvent is present in amount of from about 15 volume% to about 50 volume% of the poly(amic acid) blend. In yet a further aspect, the solvent is present in amount of from about 20 volume% to about 50 volume% of the poly(amic acid) blend. In an even further aspect, the solvent is present in amount of from about 25 volume% to about 50 volume% of the poly(amic acid) blend. In a still further aspect, the solvent is present in amount of from about 30 volume% to about 50 volume% of the poly(amic acid) blend. In yet a further aspect, the solvent is present in amount of from about 35 volume% to about 50 volume% of the poly(amic acid) blend. In an even further aspect, the solvent is present in amount of from about 40 volume% to about 50 volume% of the poly(amic acid) blend. In a still further aspect, the solvent is present in amount of from about 15 volume% to about 45 volume% of the poly(amic acid) blend. In yet a further aspect, the solvent is present in amount of from about 18 volume% to about 42 volume% of the poly(amic acid) blend. In an even further aspect, the solvent is present in amount of from about 20 volume% to about 40 volume% of the poly(amic acid) blend. In a still further aspect, the solvent is present in amount of from about 25 volume% to about 35

volume% of the poly(amic acid) blend.

[0065] In a further aspect, the poly(amic acid) blend further comprises a co-solvent. Examples of co-solvents include, but are not limited to, water, an alcohol, and other polar solvents.

[0066] In a further aspect, the co-solvent is present in amount of from about 50 volume% to about 90 volume% of the poly(amic acid) blend. In a still further aspect, the co-solvent is present in amount of from about 50 volume% to about 80 volume% of the poly(amic acid) blend. In yet a further aspect, the co-solvent is present in amount of from about 50 volume% to about 70 volume% of the poly(amic acid) blend. In an even further aspect, the co-solvent is present in amount of from about 50 volume% to about 60 volume% of the poly(amic acid) blend. In a still further aspect, the co-solvent is present in amount of from about 60 volume% to about 90 volume% of the poly(amic acid) blend. In yet a further aspect, the co-solvent is present in amount of from about 70 volume% to about 90 volume% of the poly(amic acid) blend. In an even further aspect, the co-solvent is present in amount of from about 80 volume% to about 90 volume% of the poly(amic acid) blend. In a still further aspect, the co-solvent is present in amount of from about 55 volume% to about 85 volume% of the poly(amic acid) blend. In yet a further aspect, the co-solvent is present in amount of from about 58 volume% to about 82 volume% of the poly(amic acid) blend. In an even further aspect, the co-solvent is present in amount of from about 60 volume% to about 80 volume% of the poly(amic acid) blend. In a still further aspect, the co-solvent is present in amount of from about 65 volume% to about 75 volume% of the poly(amic acid) blend.

1. IONIC POLYMERS

[0067] In one aspect, the disclosed poly(amic acid) blends comprise an ionic polymer selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-

hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion.

[0068] In various aspects, an ionic polymer can refer to a polymer that comprises at least one charged residue. An ionic polymer can comprise both electrically neutral residues and charged residues. For example, in a further aspect, an ionic polymer can comprise less than 99 mol% charged residues. In a still further aspect, an ionic polymer can comprise less than 90 mol% charged residues. In yet a further aspect, an ionic polymer can comprise less than 75 mol% charged residues. In an even further aspect, an ionic polymer can comprise less than 50 mol% charged residues. In a still further aspect, an ionic polymer can comprise less than 25 mol% charged residues. In yet a further aspect, an ionic polymer can comprise less than 10 mol% charged residues. In an even further aspect, an ionic polymer can comprise less than 5 mol% charged residues. In a still further aspect, an ionic polymer can comprise less than 1 mol% charged residues. In yet a further aspect, an ionic polymer can comprise less than 0.1 mol% charged residues.

[0069] Alternatively, an ionic polymer can comprise less than 99 mol% uncharged residues. In a still further aspect, an ionic polymer can comprise less than 90 mol% uncharged residues. In yet a further aspect, an ionic polymer can comprise less than 75 mol% uncharged residues. In an even further aspect, an ionic polymer can comprise less than 50 mol% uncharged residues. In a still further aspect, an ionic polymer can comprise less than 25 mol% uncharged residues. In yet a further aspect, an ionic polymer can comprise less than 10 mol% uncharged residues. In an even further aspect, an ionic polymer can comprise less than 5 mol% uncharged residues. In a still further aspect, an ionic polymer can comprise less than 1 mol% uncharged residues. In yet a further aspect, an ionic polymer can comprise less than 0.1 mol% uncharged residues.

[0070] In various aspects, an ionic polymer is selected from a polycation and a polyanion. In a further aspect, the ionic polymer is a polycation. In a still further aspect, the ionic polymer is a polyanion. In yet a further aspect, the ionic polymer can comprise both cationic and anionic repeat groups.

[0071] In various aspects, the ionic groups can be covalently attached to the polymer backbone. Alternatively, the ionic group can be incorporated into the polymer backbone.

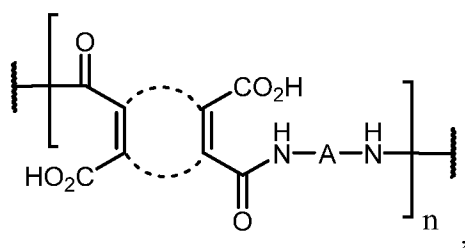
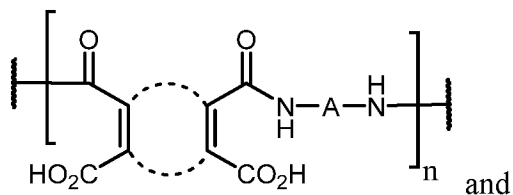
[0072] In various aspects, the ionic polymer can have excellent thermal and mechanical properties such as, for example, highly ion-conductive, highly permeable to water, a super-acid

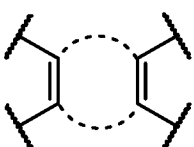
catalyst, temperature resistance, and chemical resistance.

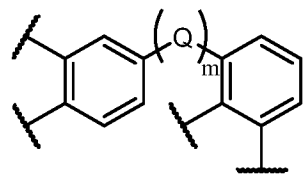
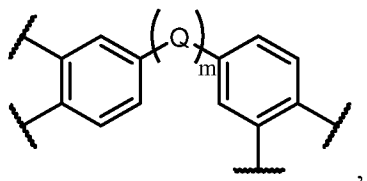
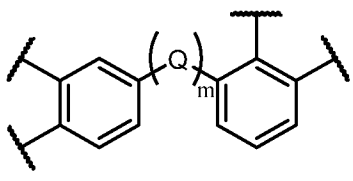
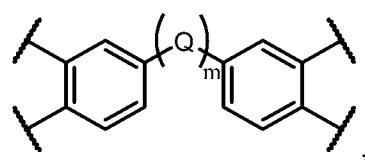
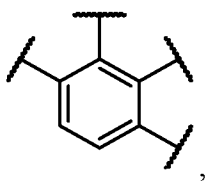
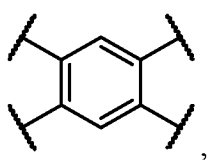
[0073] In a further aspect, the ionic polymer is Nafion. In a still further aspect, the ionic polymer is Flemion.

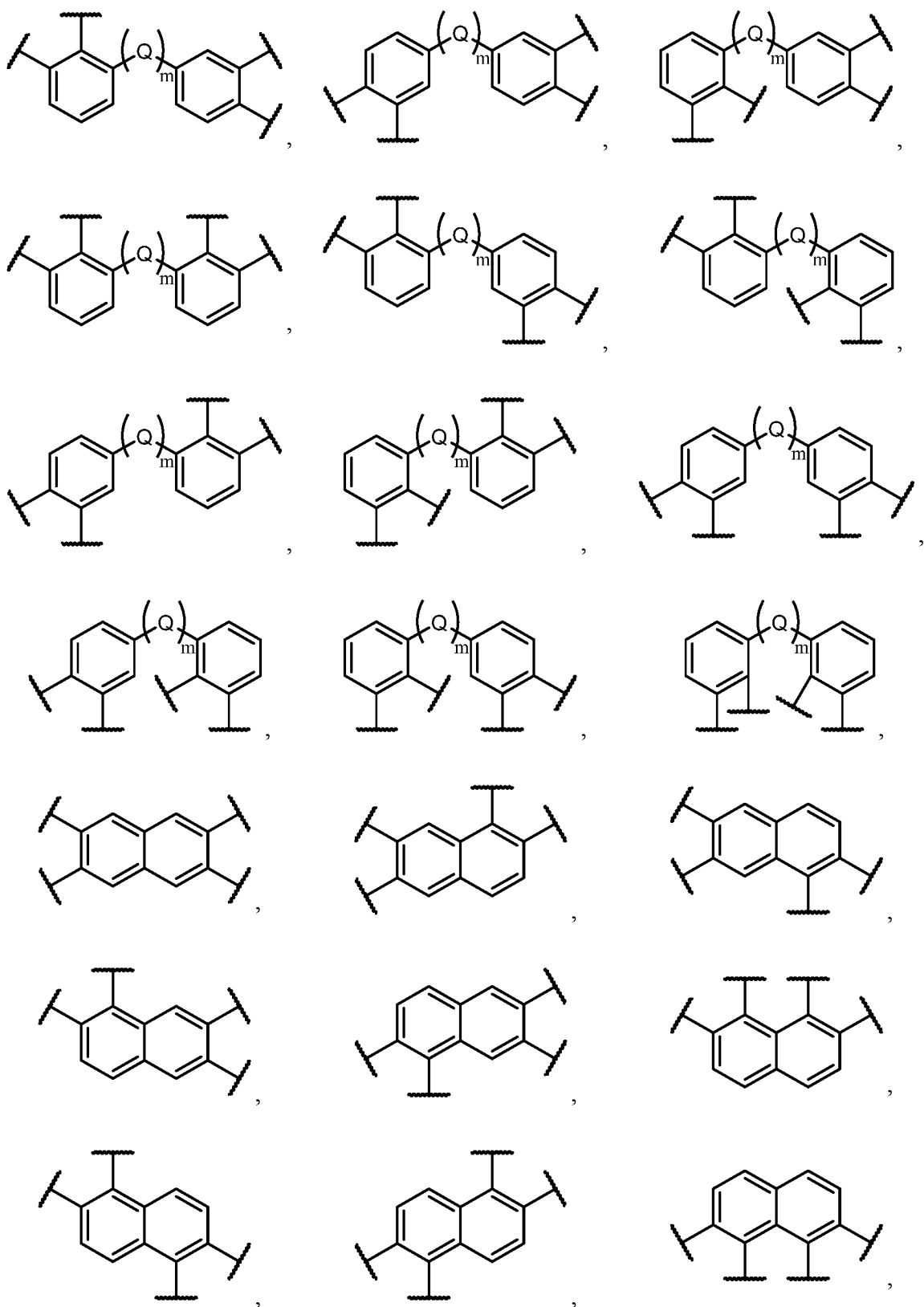
2. POLY(AMIC ACIDS)

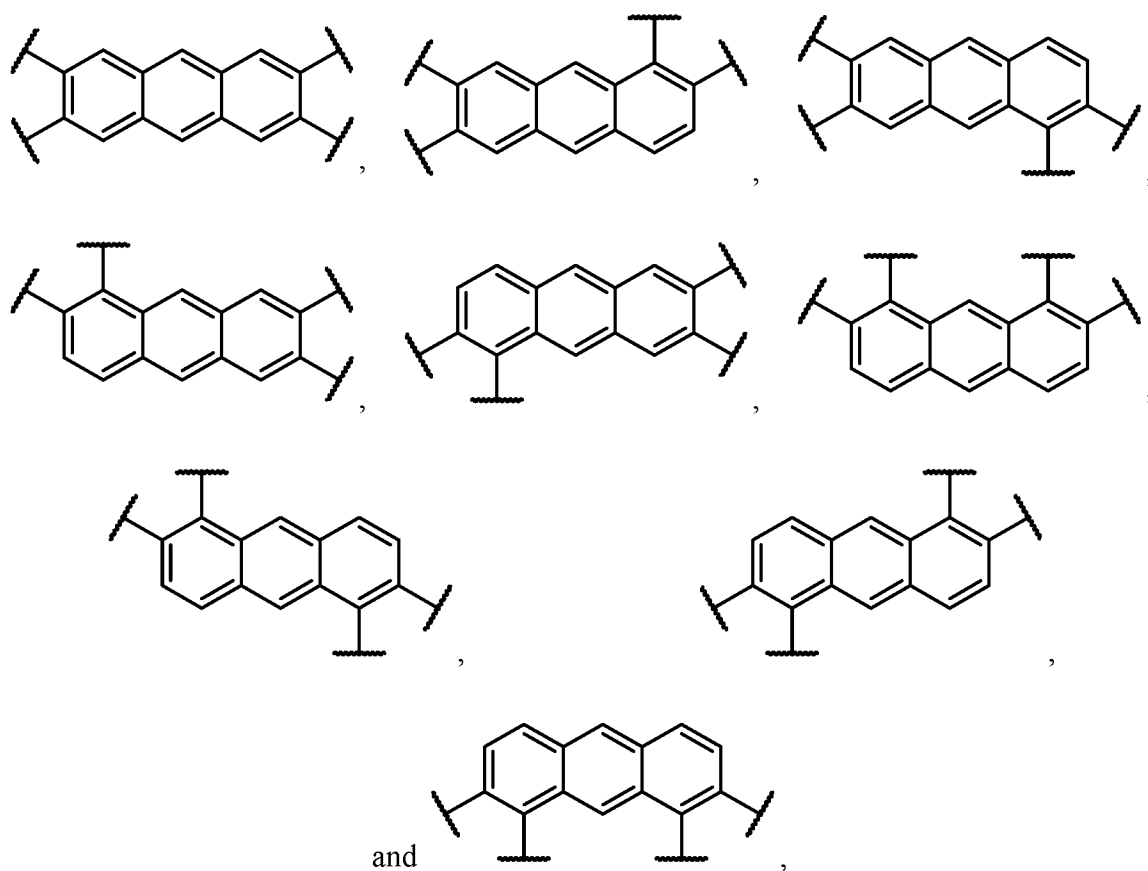
[0074] In one aspect, the disclosed poly(amic acid) blends comprise a poly(amic acid) comprising at least one residue having a structure represented by a formula selected from:



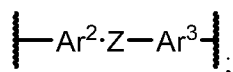
wherein  comprises a structure represented by a formula selected from:





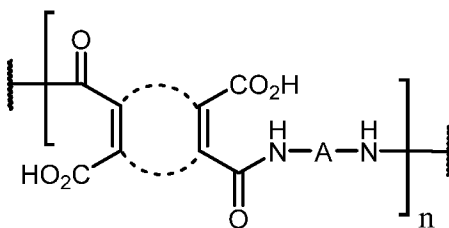


wherein n is an integer greater than 1; wherein m is 0 or 1; wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:

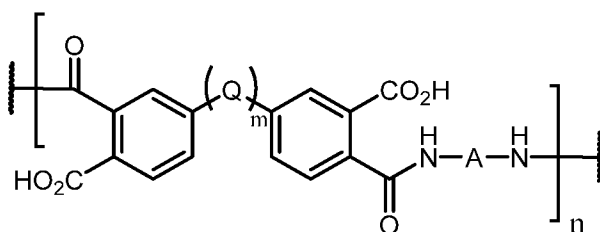


wherein Z , when present, is selected from O , NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO , and SO_2 ; wherein each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl; wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein Q , when present, is selected from O , NR^1 , SO , SO_2 , C(O) , and $\text{CR}^{2a}\text{R}^{2b}$; and wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl.

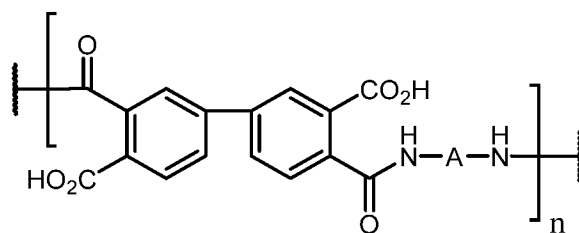
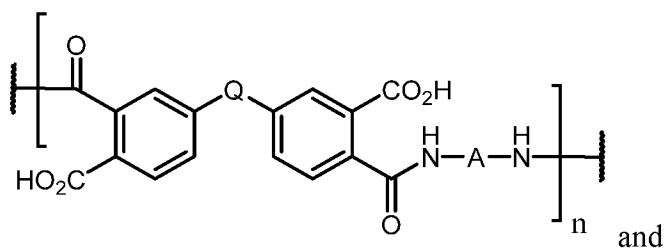
[0075] In a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



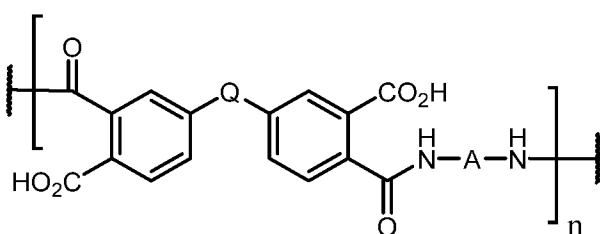
[0076] In a still further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



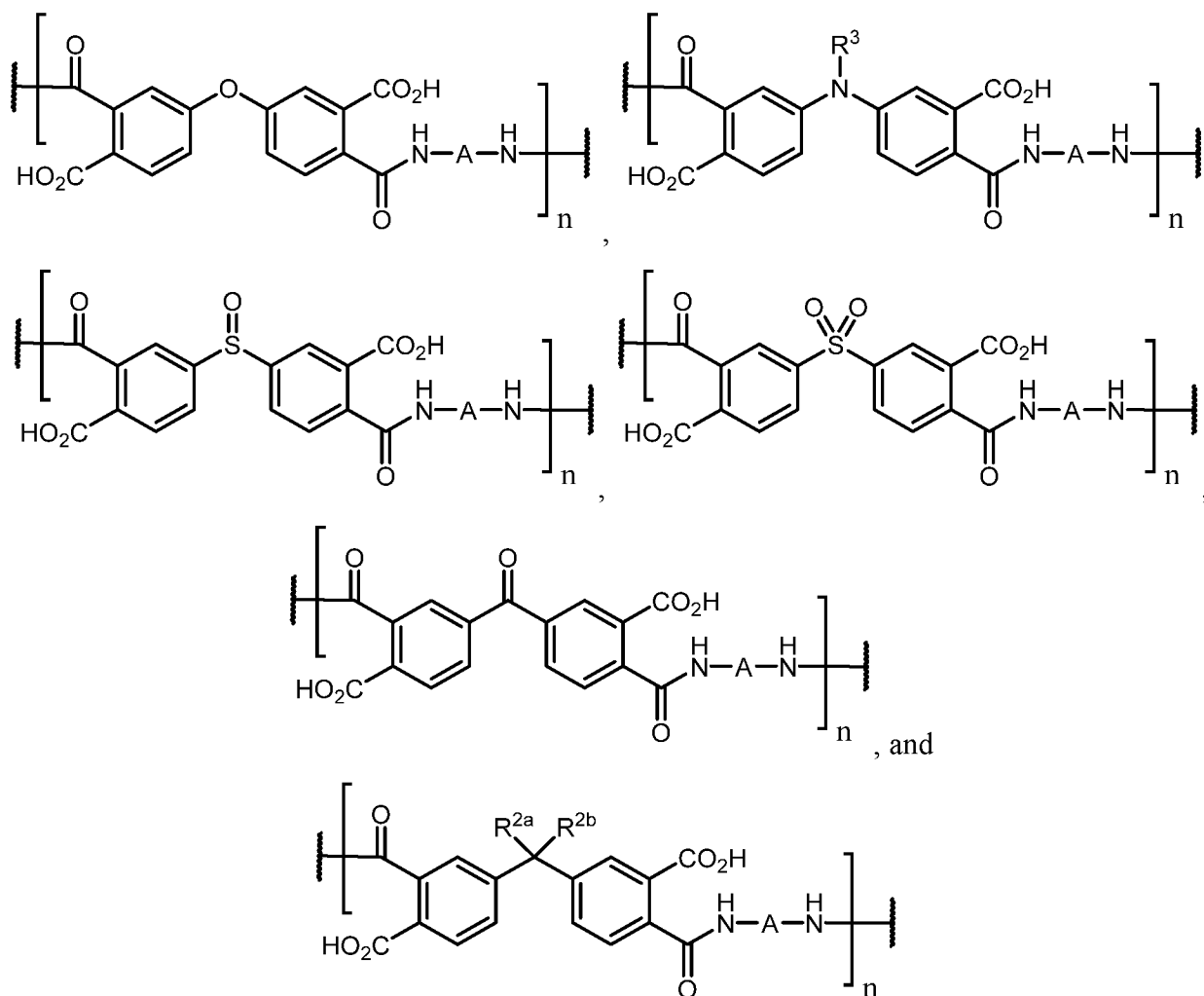
[0077] In yet a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula selected from:



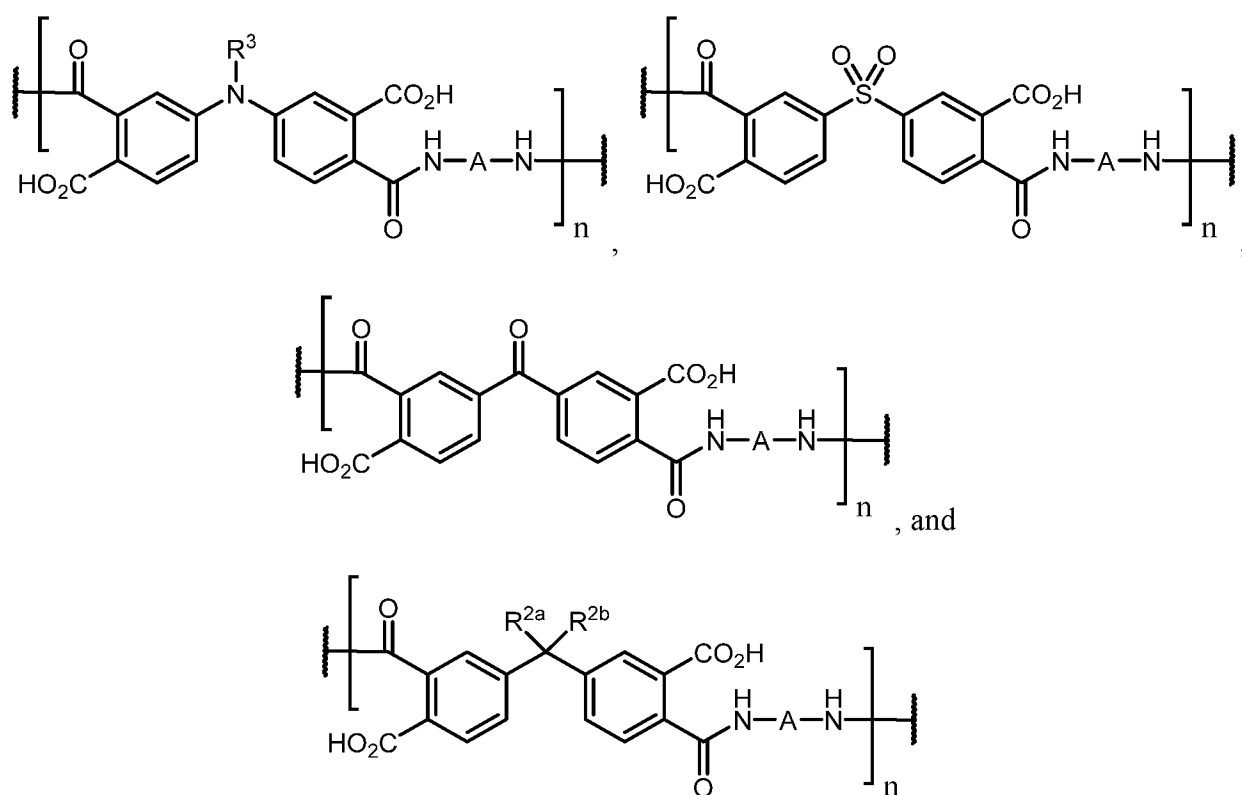
[0078] In an even further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



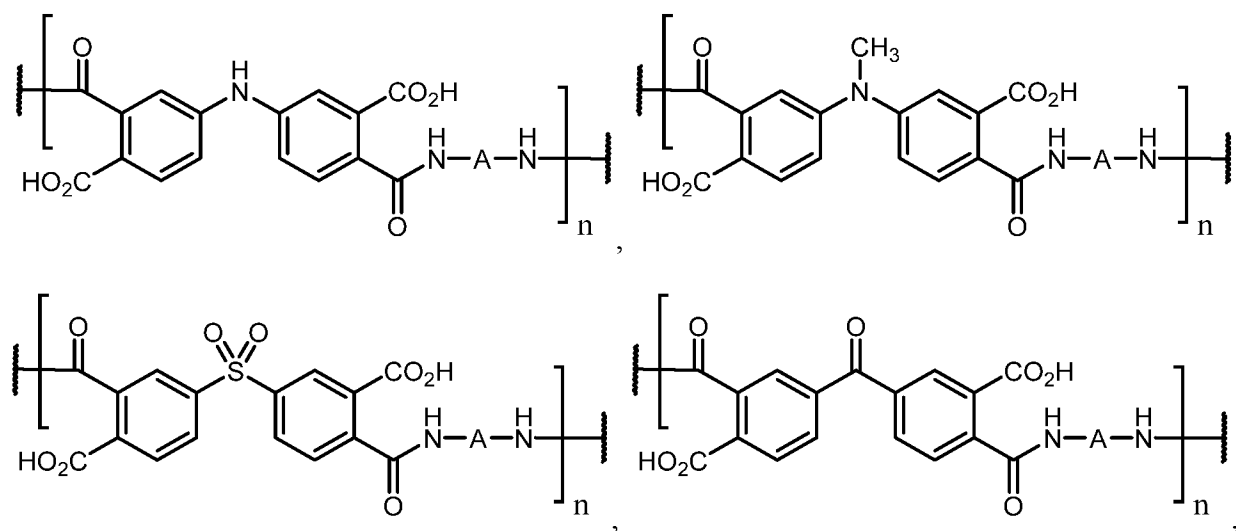
[0079] In a still further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula selected from:

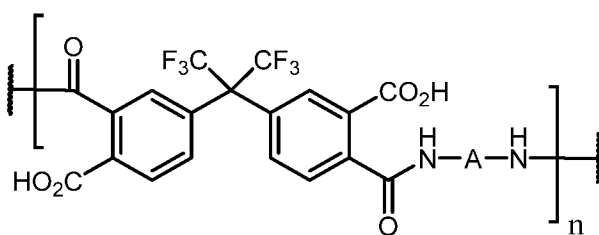
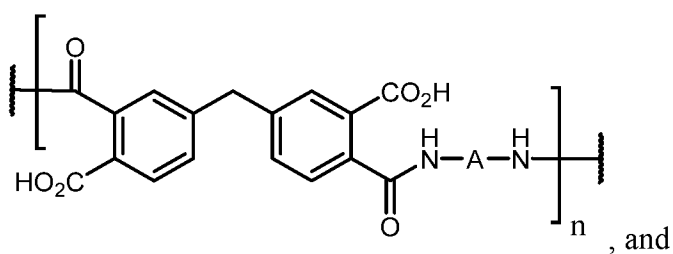


[0080] In yet a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula selected from:

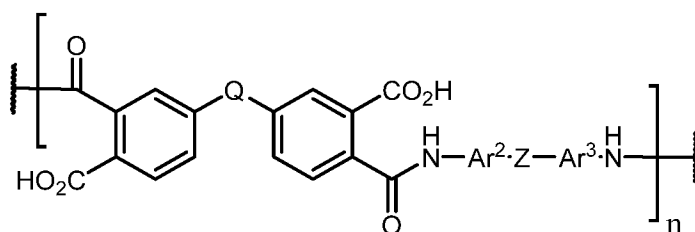


[0081] In an even further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula selected from:

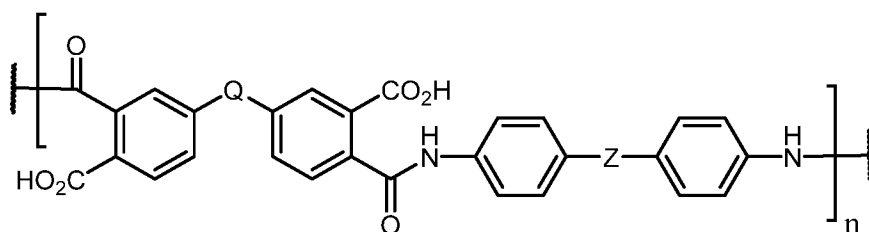




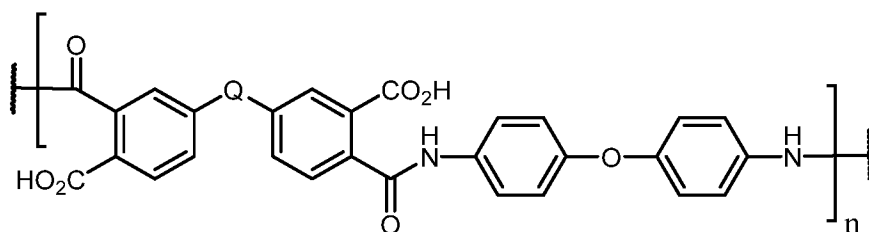
[0082] In a still further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



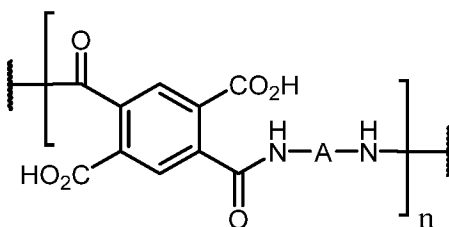
[0083] In yet a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



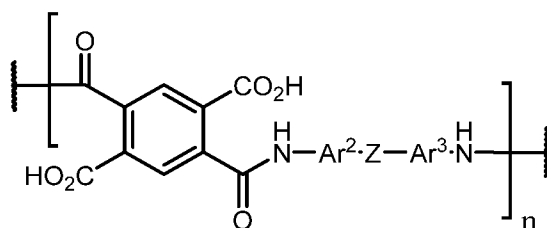
[0084] In an even further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



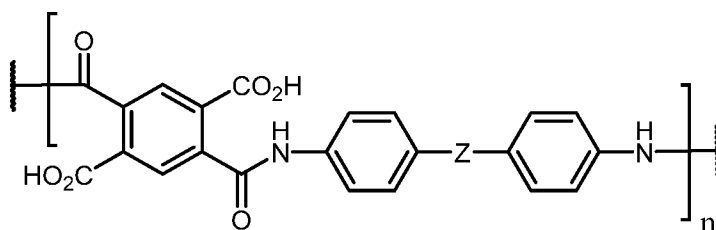
[0085] In a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



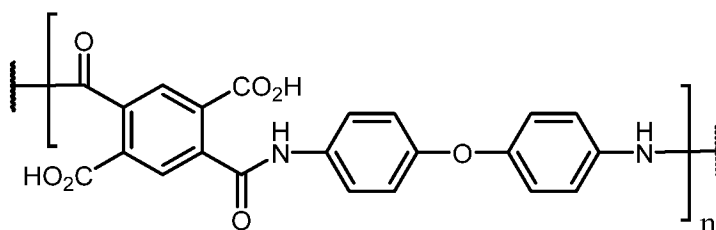
[0086] In yet a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



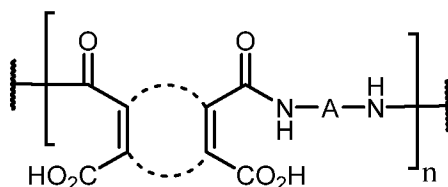
[0087] In an even further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



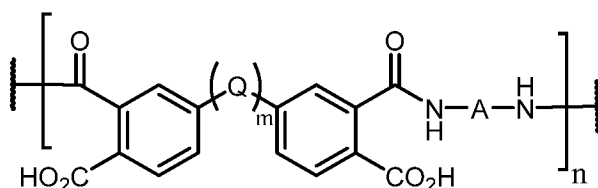
[0088] In a still further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



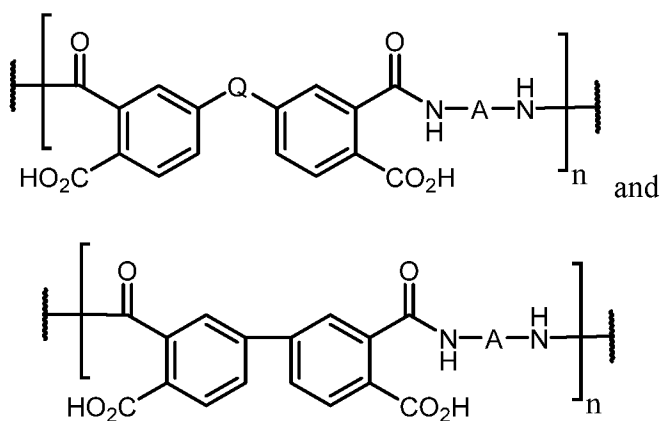
[0089] In a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



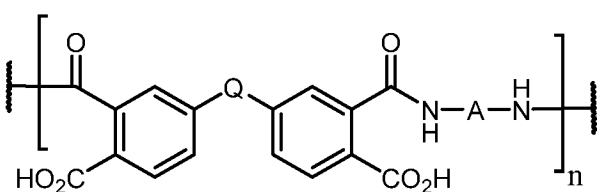
[0090] In a still further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



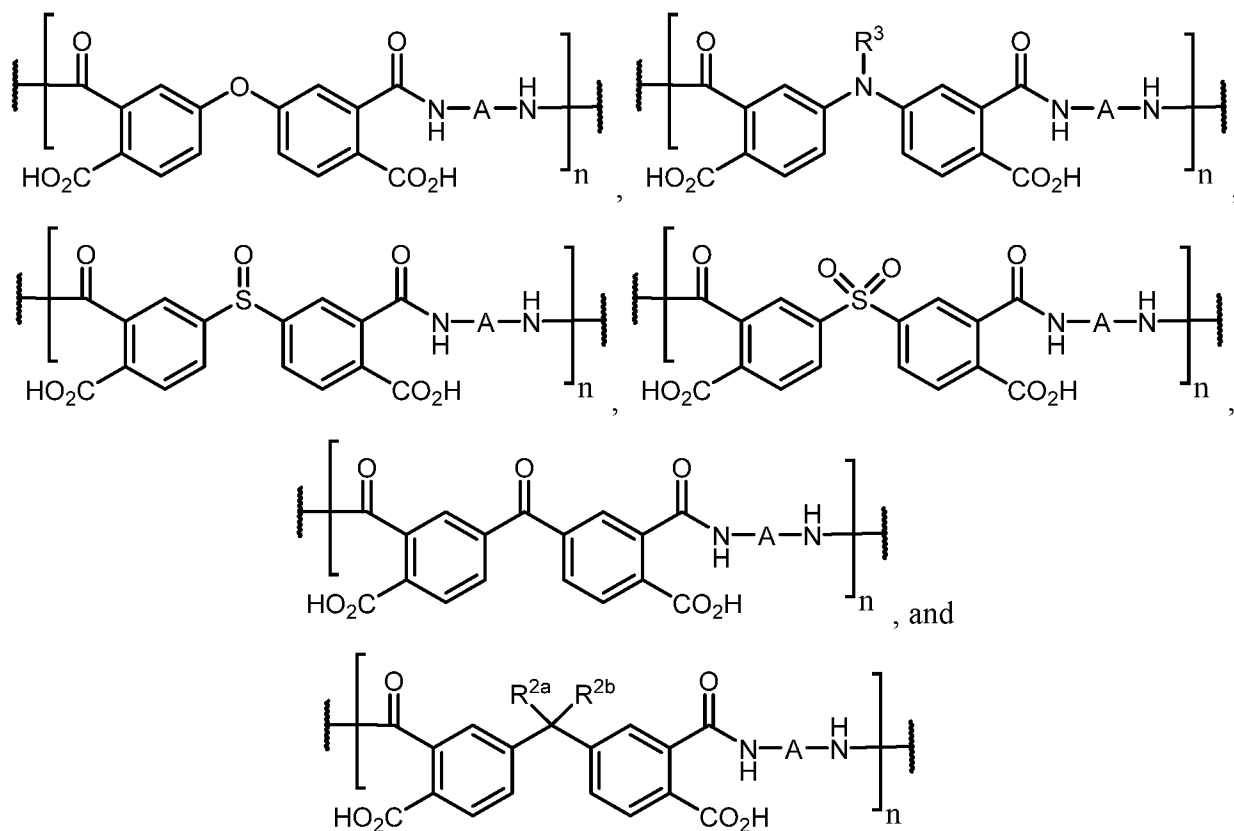
[0091] In yet a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula selected from:



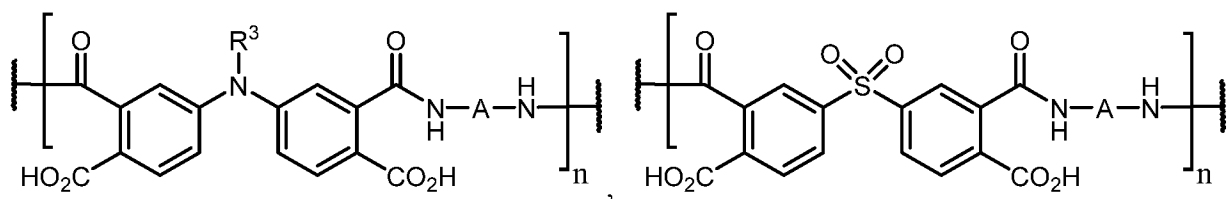
[0092] In an even further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:

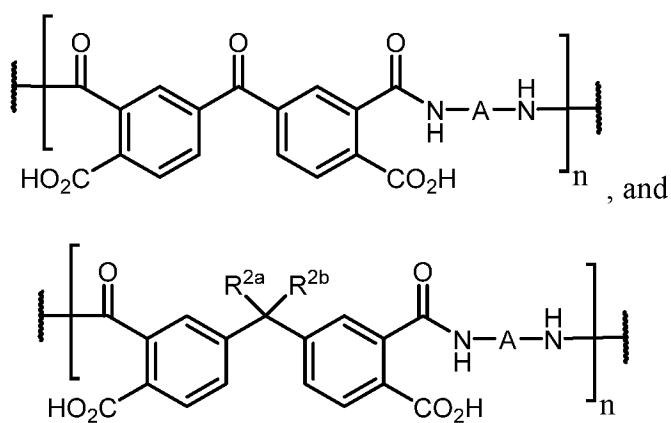


[0093] In a still further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula selected from:

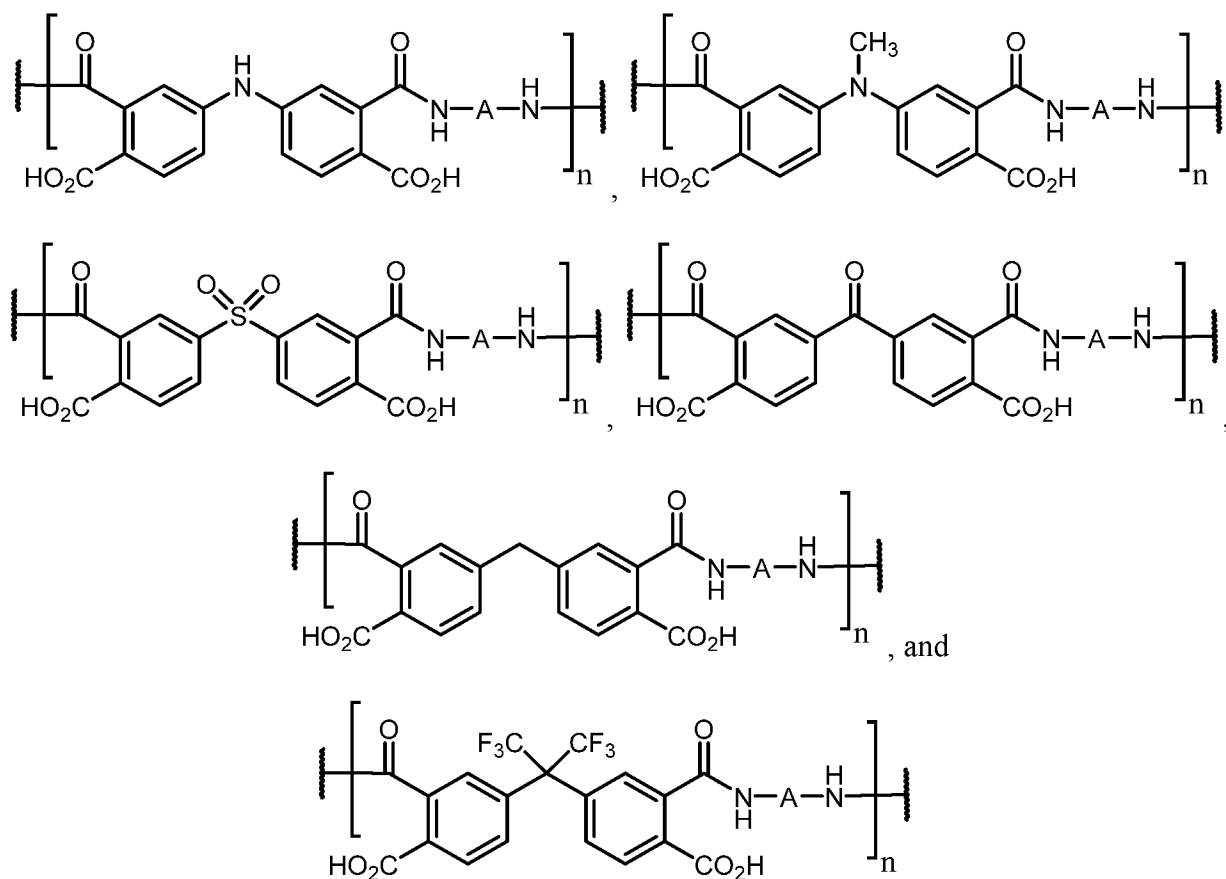


[0094] In yet a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula selected from:

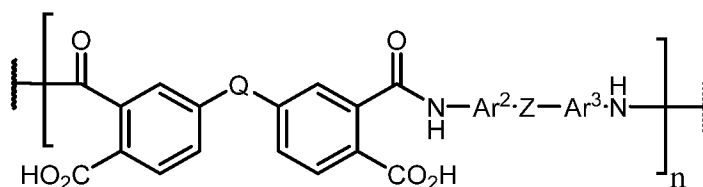




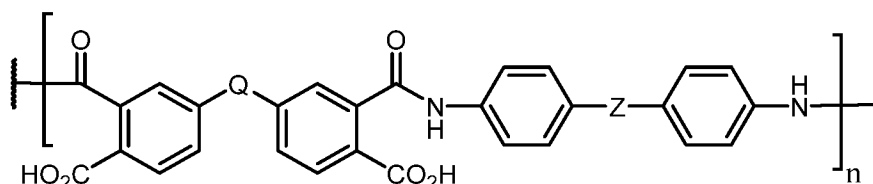
[0095] In an even further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula selected from:



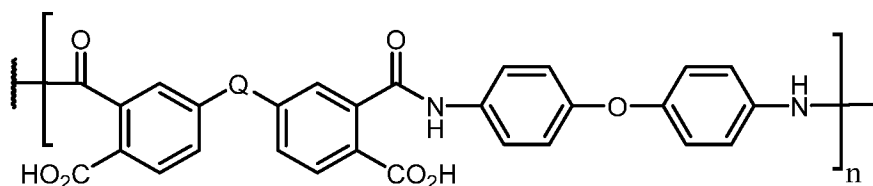
[0096] In a still further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



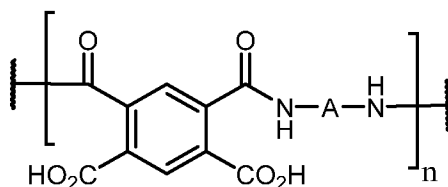
[0097] In yet a further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



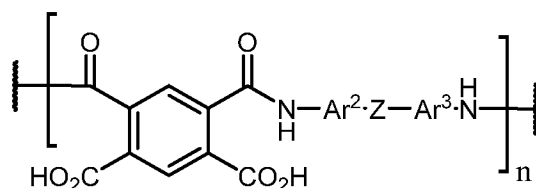
[0098] In an even further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:



[0099] In a still further aspect, the poly(amic acid) comprises at least one residue having a structure represented by a formula:

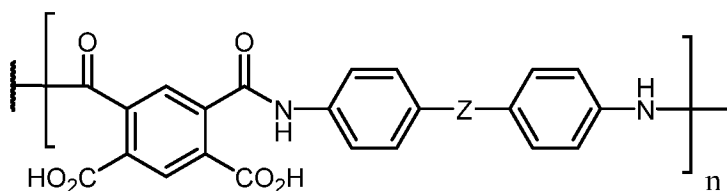


[00100] In yet a further aspect, the poly(amic acid) comprises at least one residue having a structure:

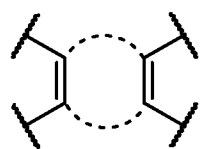
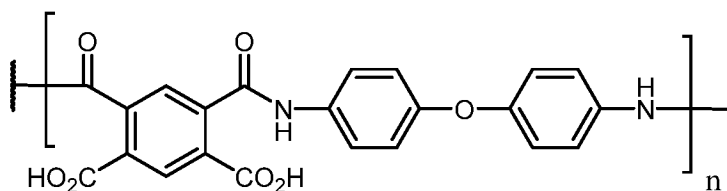


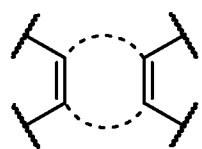
[00101] In an even further aspect, the poly(amic acid) comprises at least one residue having a

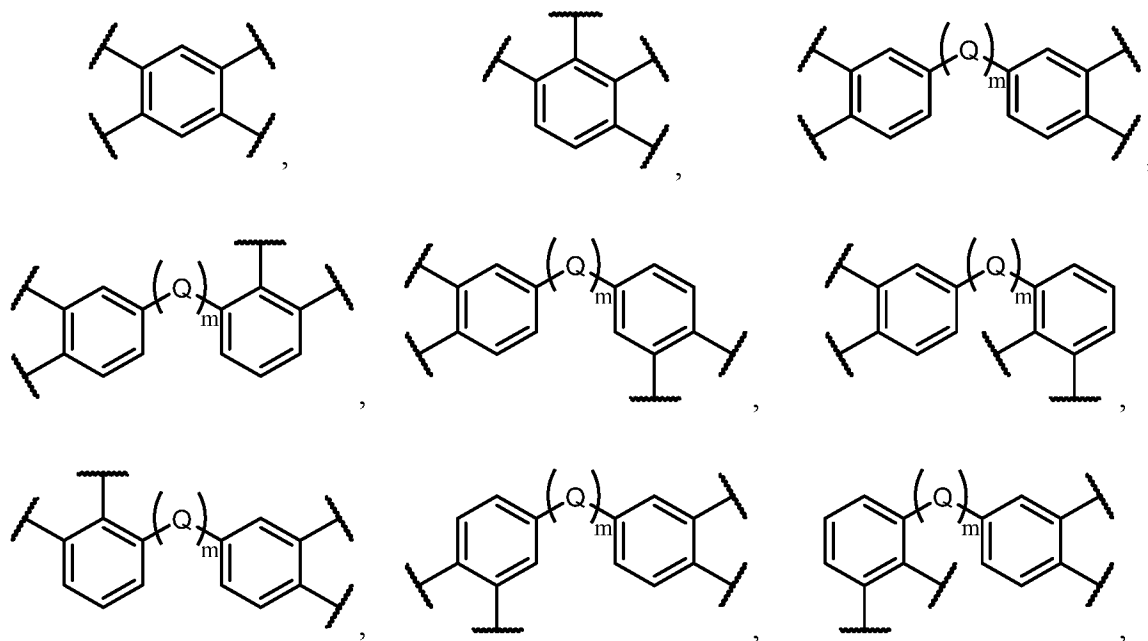
structure:

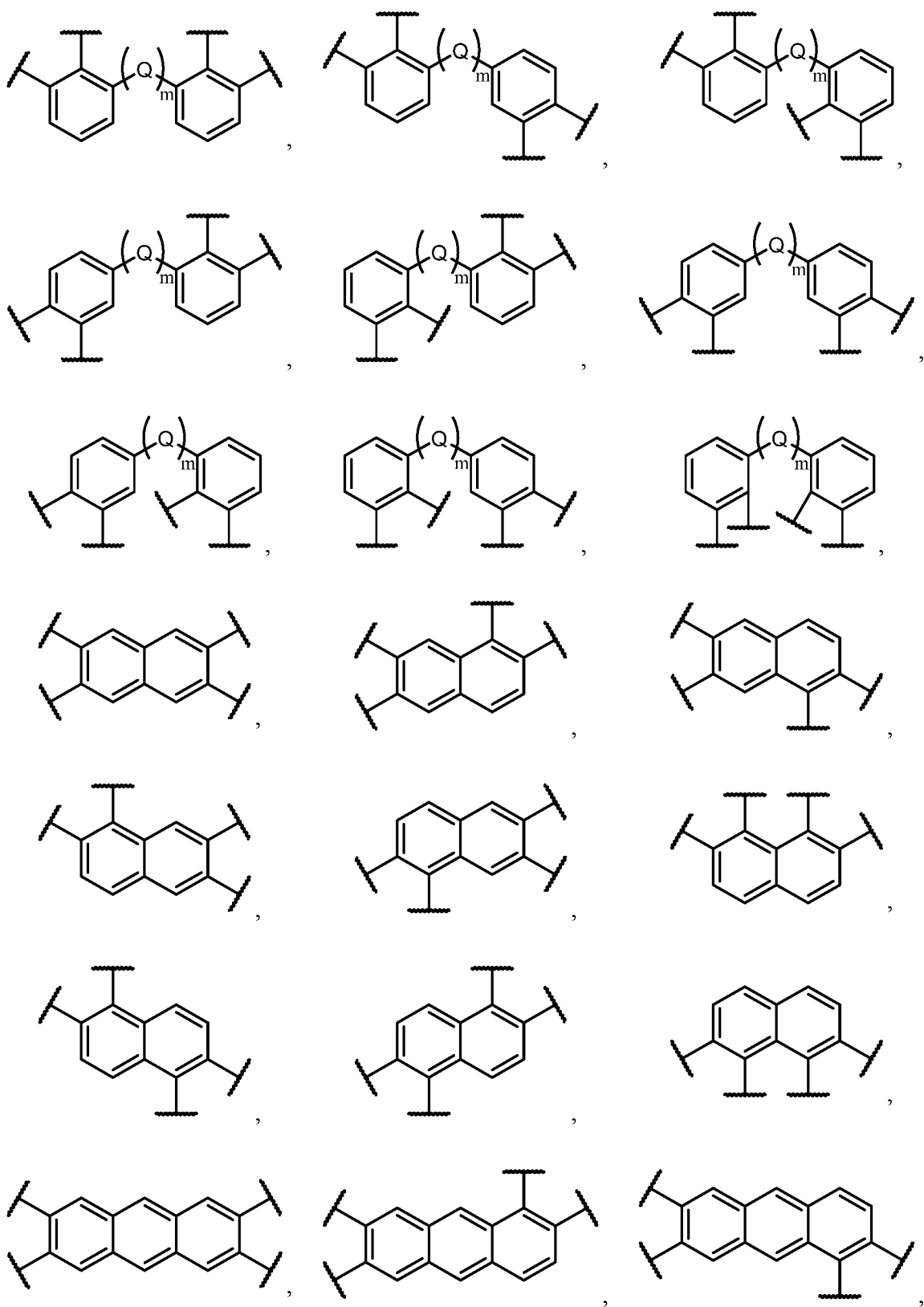


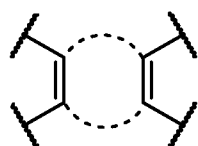
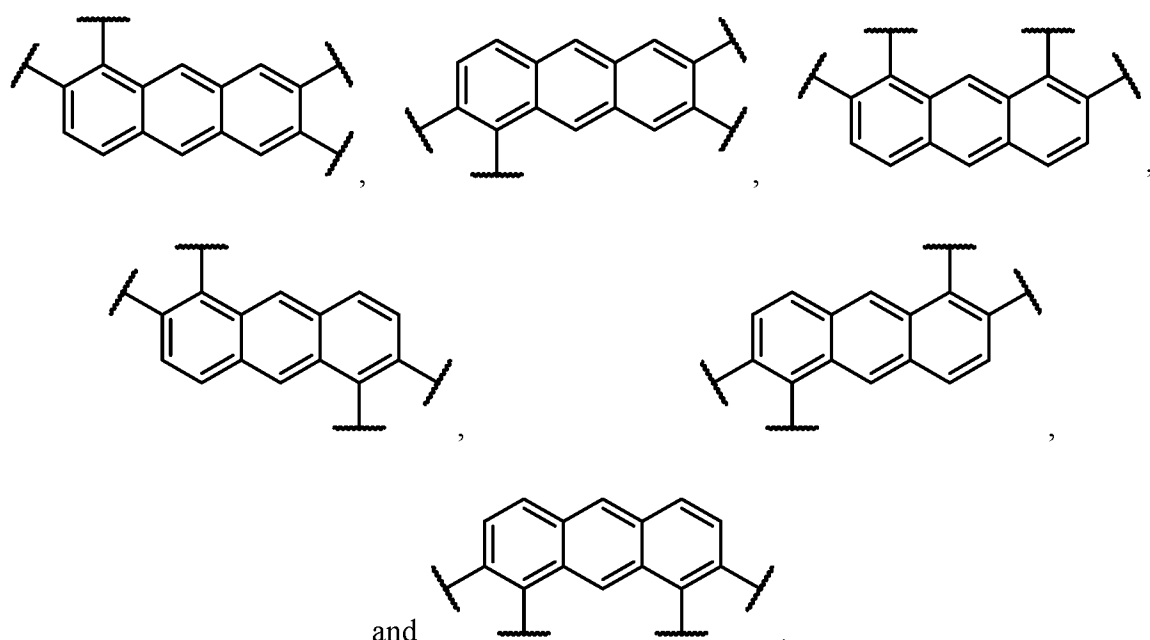
[00102] In a still further aspect, the poly(amic acid) comprises at least one residue having a structure:



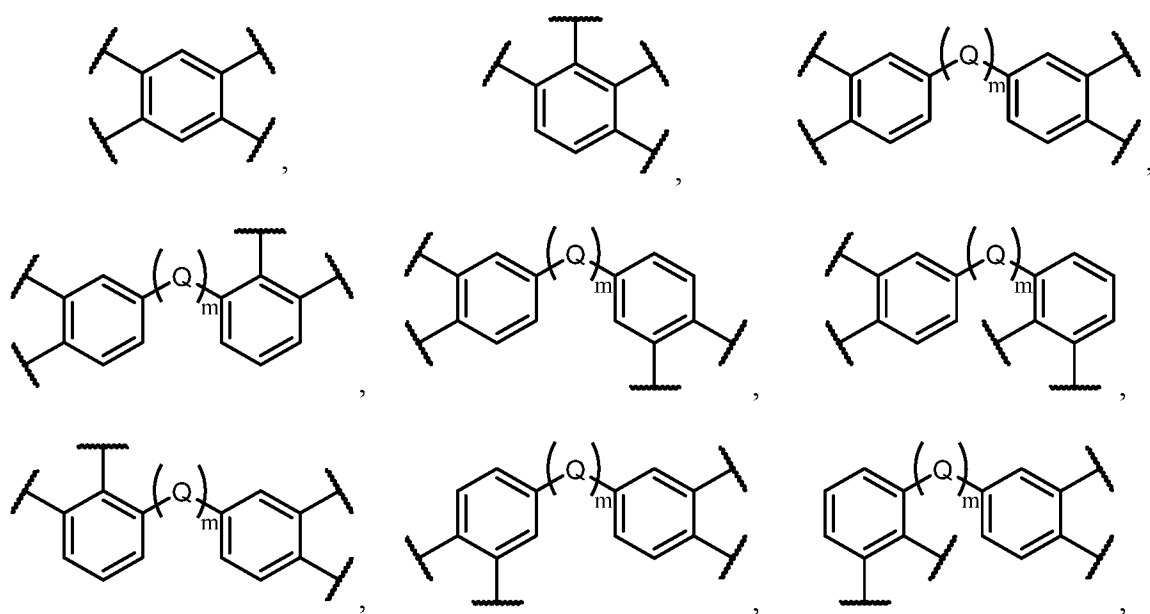
[00103] In one aspect,  comprises a structure represented by a formula selected from:

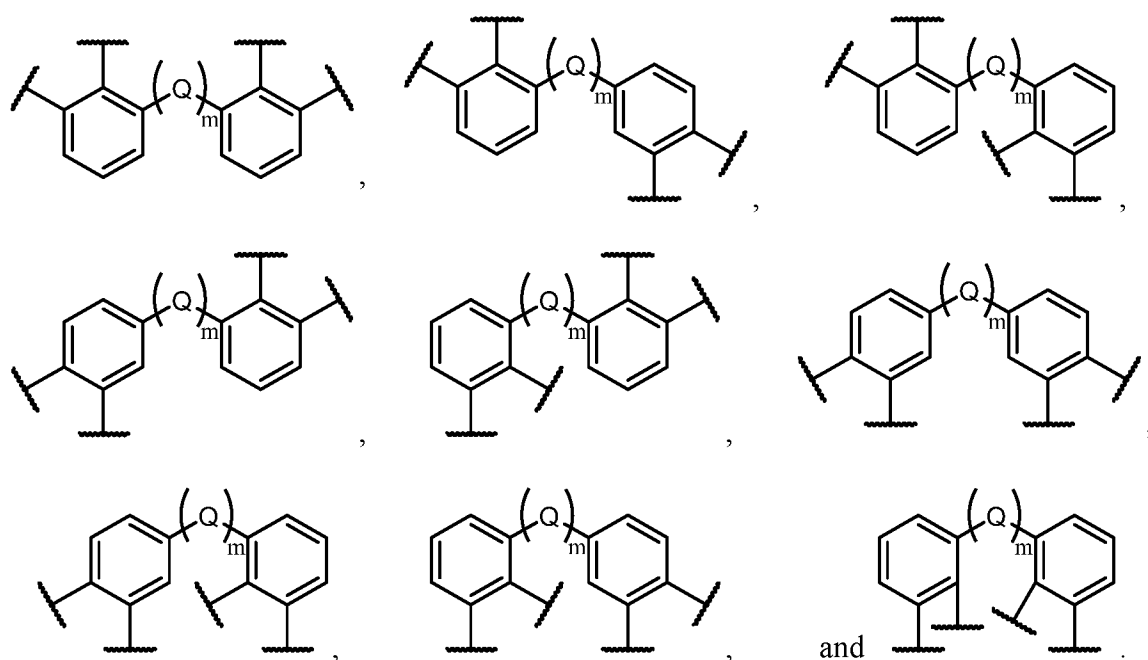




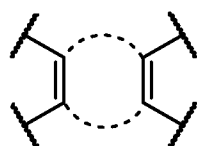


[00104] In a further aspect, comprises a structure represented by a formula selected from:

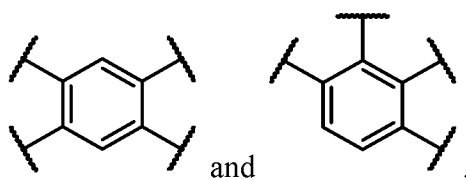




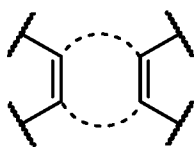
[00105] In a further aspect,
selected from:



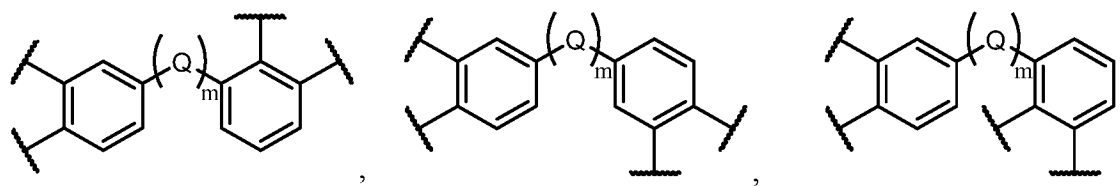
comprises a structure represented by a formula

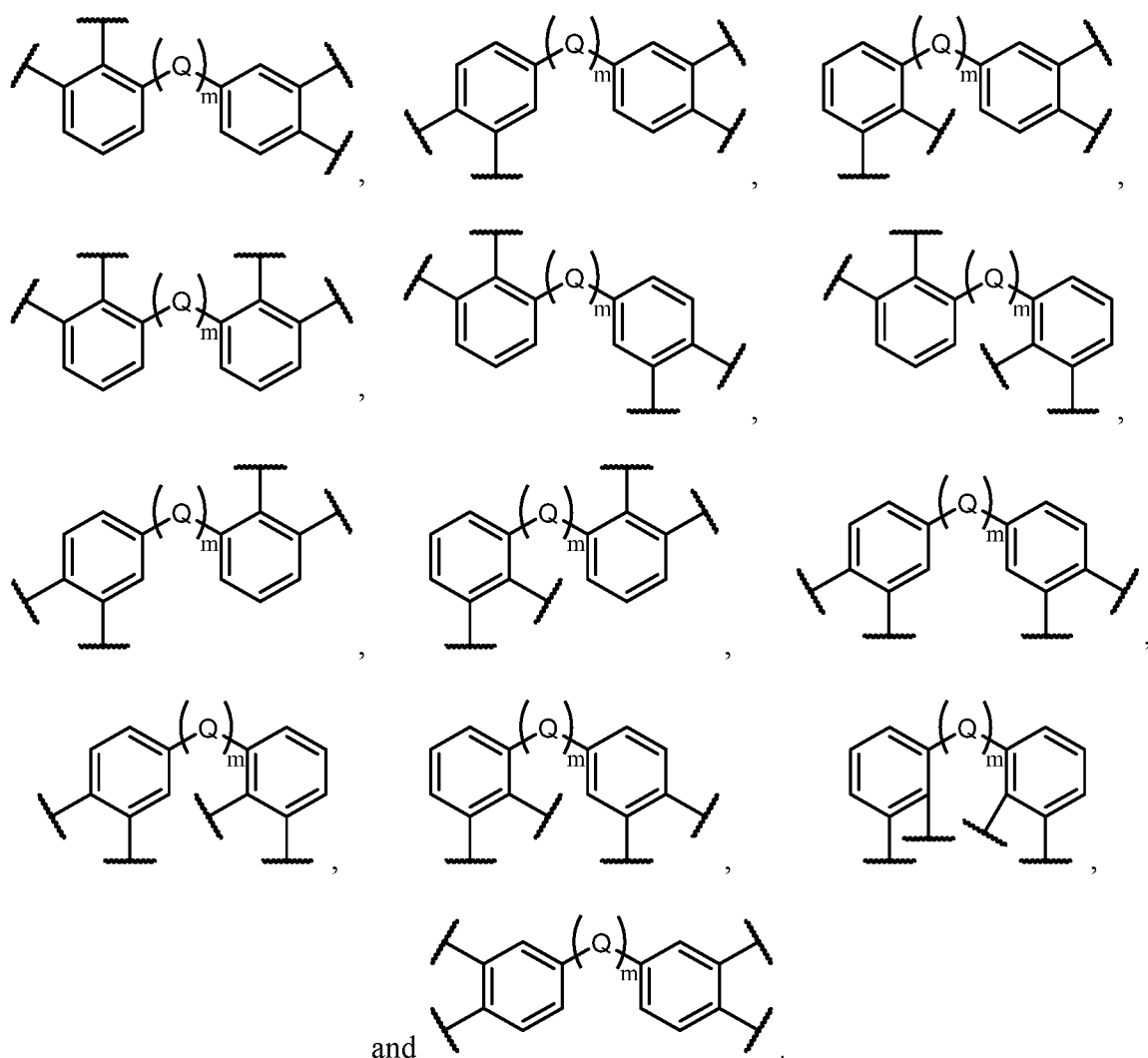


and

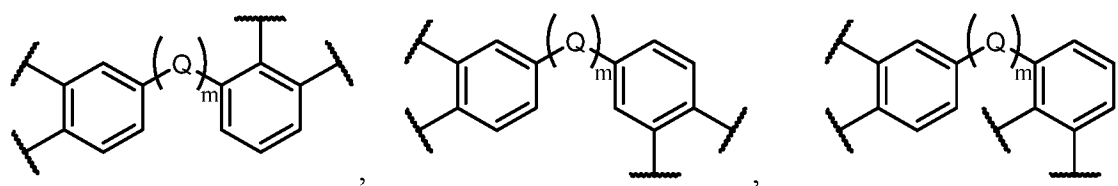


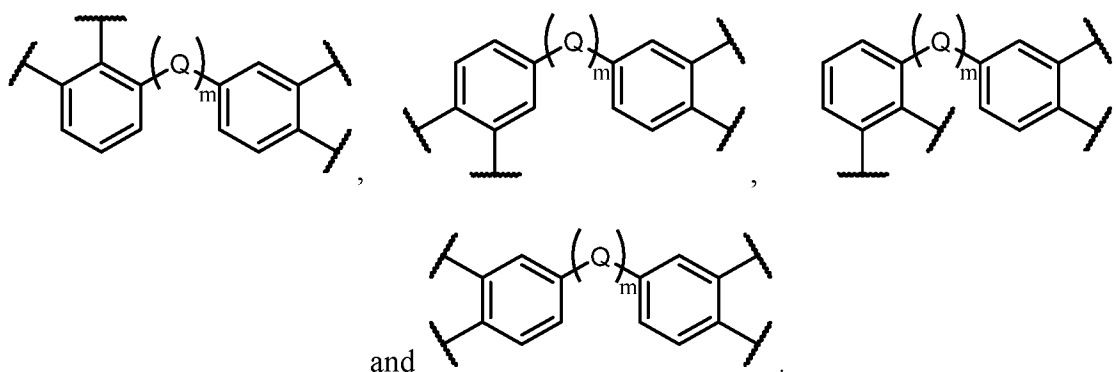
[00106] In a still further aspect,
formula selected from:



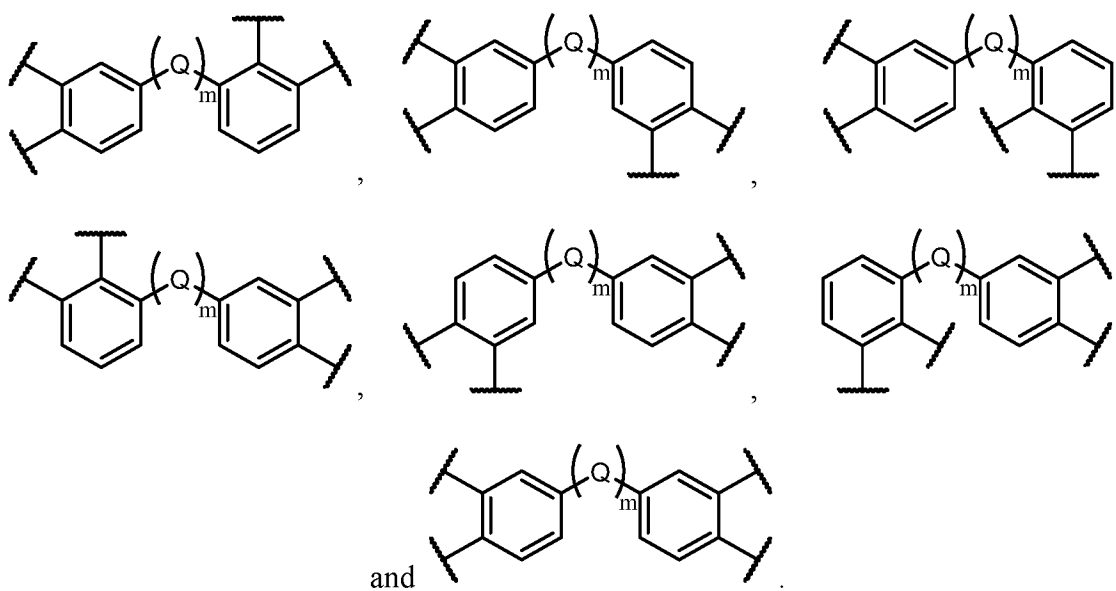


[00107] In yet a further aspect,
formula selected from:

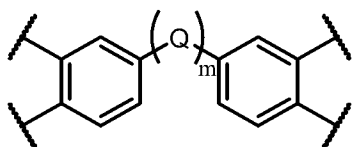




[00108] In an even further aspect,  comprises a structure represented by a formula selected from:



[00109] In a still further aspect,  comprises a structure represented by a formula:

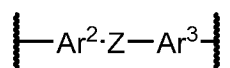


[00110] In one aspect, n is an integer greater than 1. In a further aspect, n is an integer greater than 10. In a still further aspect, n is an integer greater than 100. In yet a further aspect, n is an integer greater than 1000. In an even further aspect, n is an integer greater than 10,000. In a still further aspect, n is an integer greater than 100,000.

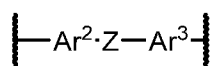
[00111] In one aspect, m is 0 or 1. In a further aspect, m is 0. In a still further aspect, m is 1.

a. A GROUPS

[00112] In one aspect, A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:



[00113] In a further aspect, A is $-\text{Ar}^1-$. In a still further aspect, A is a structure represented by a formula:



b. Q GROUPS

[00114] In one aspect, Q, when present, is selected from O, NR^1 , SO, SO_2 , C(O), and $\text{CR}^{2a}\text{R}^{2b}$.

[00115] In a further aspect, Q, when present, is selected from O, NR^1 , and $\text{CR}^{2a}\text{R}^{2b}$. In a still further aspect, Q, when present, is selected from NR^1 and $\text{CR}^{2a}\text{R}^{2b}$. In yet a further aspect, Q, when present, is selected from O and NR^1 . In an even further aspect, Q, when present, is selected from O and $\text{CR}^{2a}\text{R}^{2b}$. In a still further aspect, Q, when present, is O. In yet a further aspect, Q, when present, is NR^1 . In an even further aspect, Q, when present, is $\text{CR}^{2a}\text{R}^{2b}$.

[00116] In a further aspect, Q, when present, is selected from SO, SO_2 , and C(O). In a still further aspect, Q, when present, is selected from SO and SO_2 . In yet a further aspect, Q, when present, is selected from SO and C(O). In an even further aspect, Q, when present, is selected from SO_2 and C(O). In a still further aspect, Q, when present, is SO. In yet a further aspect, Q, when present, is SO_2 . In an even further aspect, Q, when present, is C(O).

c. Z GROUPS

[00117] In one aspect, Z, when present, is selected from O, NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO, and SO_2 .

[00118] In a further aspect, Z, when present, is selected from O, NR^3 , and $\text{CR}^{4a}\text{R}^{4b}$. In a still further aspect, Z, when present, is selected from NR^3 and $\text{CR}^{4a}\text{R}^{4b}$. In yet a further aspect, Z, when present, is selected from O and NR^3 . In an even further aspect, Z, when present, is selected from O and $\text{CR}^{4a}\text{R}^{4b}$. In a still further aspect, Z, when present, is O. In yet a further aspect, Z, when present, is NR^3 . In an even further aspect, Z, when present, is $\text{CR}^{4a}\text{R}^{4b}$.

[00119] In a further aspect, Z, when present, is selected from O, NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, and CO. In a still further aspect, Z, when present, is selected from NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, and CO. In yet a further aspect, Z, when present, is selected from $\text{CR}^{4a}\text{R}^{4b}$ and CO.

[00120] In a further aspect, Z, when present, is selected from CO and SO_2 . In a still further aspect, Z, when present, is CO. In yet a further aspect, Z, when present is SO_2 .

d. R^1 , R^{2a} , AND R^{2b} GROUPS

[00121] In one aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl. In a further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is hydrogen.

[00122] In a further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, methyl, ethyl, *i*-propyl, *n*-propyl, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CH}_2\text{CH}_2\text{F}$, $-\text{CH}_2\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{CH}_2\text{Br}$, $-(\text{CH}_2)_2\text{CH}_2\text{F}$, $-(\text{CH}_2)_2\text{CH}_2\text{Cl}$, $-(\text{CH}_2)_2\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, $-\text{CBr}_3$, $-\text{CH}_2\text{CHF}_2$, $-\text{CH}_2\text{CF}_3$, $-\text{CH}_2\text{CHCl}_2$, $-\text{CH}_2\text{CCl}_3$, $-\text{CH}_2\text{CHBr}_2$, $-\text{CH}_2\text{CBr}_3$, $-(\text{CH}_2)_2\text{CHF}_2$, $-(\text{CH}_2)_2\text{CF}_3$, $-(\text{CH}_2)_2\text{CHCl}_2$, $-(\text{CH}_2)_2\text{CCl}_3$, $-(\text{CH}_2)_2\text{CHBr}_2$, and $-(\text{CH}_2)_2\text{CBr}_3$. In a still further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, methyl, ethyl, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CH}_2\text{CH}_2\text{F}$, $-\text{CH}_2\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, $-\text{CBr}_3$, $-\text{CH}_2\text{CHF}_2$, $-\text{CH}_2\text{CF}_3$, $-\text{CH}_2\text{CHCl}_2$, $-\text{CH}_2\text{CCl}_3$, $-\text{CH}_2\text{CHBr}_2$, and $-\text{CH}_2\text{CBr}_3$. In yet a further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, methyl, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, and $-\text{CBr}_3$.

[00123] In a further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen and C1-C4 alkyl. In a still further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, methyl, ethyl, *i*-propyl, *n*-propyl, *n*-butyl, *i*-butyl, *s*-butyl, and *t*-butyl. In yet a further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is

independently selected from hydrogen, methyl, ethyl, *i*-propyl, and *n*-propyl. In an even further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, methyl, and ethyl. In a still further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen and ethyl. In yet a further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen and methyl.

[00124] In a further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen and C1-C4 haloalkyl. In a still further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CH}_2\text{CH}_2\text{F}$, $-\text{CH}_2\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{CH}_2\text{Br}$, $-(\text{CH}_2)_2\text{CH}_2\text{F}$, $-(\text{CH}_2)_2\text{CH}_2\text{Cl}$, $-(\text{CH}_2)_2\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, $-\text{CBr}_3$, $-\text{CH}_2\text{CHF}_2$, $-\text{CH}_2\text{CF}_3$, $-\text{CH}_2\text{CHCl}_2$, $-\text{CH}_2\text{CCl}_3$, $-\text{CH}_2\text{CHBr}_2$, $-\text{CH}_2\text{CBr}_3$, $-(\text{CH}_2)_2\text{CHF}_2$, $-(\text{CH}_2)_2\text{CF}_3$, $-(\text{CH}_2)_2\text{CHCl}_2$, $-(\text{CH}_2)_2\text{CCl}_3$, $-(\text{CH}_2)_2\text{CHBr}_2$, and $-(\text{CH}_2)_2\text{CBr}_3$. In yet a further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CH}_2\text{CH}_2\text{F}$, $-\text{CH}_2\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, $-\text{CBr}_3$, $-\text{CH}_2\text{CHF}_2$, $-\text{CH}_2\text{CF}_3$, $-\text{CH}_2\text{CHCl}_2$, $-\text{CH}_2\text{CCl}_3$, $-\text{CH}_2\text{CHBr}_2$, and $-\text{CH}_2\text{CBr}_3$. In an even further aspect, each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, and $-\text{CBr}_3$.

e. R^3 , R^{4a} , AND R^{4b} GROUPS

[00125] In one aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl. In a further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is hydrogen.

[00126] In a further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, methyl, ethyl, *i*-propyl, *n*-propyl, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CH}_2\text{CH}_2\text{F}$, $-\text{CH}_2\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{CH}_2\text{Br}$, $-(\text{CH}_2)_2\text{CH}_2\text{F}$, $-(\text{CH}_2)_2\text{CH}_2\text{Cl}$, $-(\text{CH}_2)_2\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, $-\text{CBr}_3$, $-\text{CH}_2\text{CHF}_2$, $-\text{CH}_2\text{CF}_3$, $-\text{CH}_2\text{CHCl}_2$, $-\text{CH}_2\text{CCl}_3$, $-\text{CH}_2\text{CHBr}_2$, $-\text{CH}_2\text{CBr}_3$, $-(\text{CH}_2)_2\text{CHF}_2$, $-(\text{CH}_2)_2\text{CF}_3$, $-(\text{CH}_2)_2\text{CHCl}_2$, $-(\text{CH}_2)_2\text{CCl}_3$, $-(\text{CH}_2)_2\text{CHBr}_2$, and $-(\text{CH}_2)_2\text{CBr}_3$. In a still further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, methyl, ethyl, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CH}_2\text{CH}_2\text{F}$, $-\text{CH}_2\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, $-\text{CBr}_3$, $-\text{CH}_2\text{CHF}_2$, $-\text{CH}_2\text{CF}_3$, $-\text{CH}_2\text{CHCl}_2$, $-\text{CH}_2\text{CCl}_3$, $-\text{CH}_2\text{CHBr}_2$, and $-\text{CH}_2\text{CBr}_3$. In yet a further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is

independently selected from hydrogen, methyl, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, and $-\text{CBr}_3$.

[00127] In a further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen and C1-C4 alkyl. In a still further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, methyl, ethyl, *i*-propyl, *n*-propyl, *n*-butyl, *i*-butyl, *s*-butyl, and *t*-butyl. In yet a further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, methyl, ethyl, *i*-propyl, and *n*-propyl. In an even further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, methyl, and ethyl. In a still further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen and ethyl. In yet a further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen and methyl.

[00128] In a further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen and C1-C4 haloalkyl. In a still further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CH}_2\text{CH}_2\text{F}$, $-\text{CH}_2\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{CH}_2\text{Br}$, $-(\text{CH}_2)_2\text{CH}_2\text{F}$, $-(\text{CH}_2)_2\text{CH}_2\text{Cl}$, $-(\text{CH}_2)_2\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, $-\text{CBr}_3$, $-\text{CH}_2\text{CHF}_2$, $-\text{CH}_2\text{CF}_3$, $-\text{CH}_2\text{CHCl}_2$, $-\text{CH}_2\text{CCl}_3$, $-\text{CH}_2\text{CHBr}_2$, $-\text{CH}_2\text{CBr}_3$, $-(\text{CH}_2)_2\text{CHF}_2$, $-(\text{CH}_2)_2\text{CF}_3$, $-(\text{CH}_2)_2\text{CHCl}_2$, $-(\text{CH}_2)_2\text{CCl}_3$, $-(\text{CH}_2)_2\text{CHBr}_2$, and $-(\text{CH}_2)_2\text{CBr}_3$. In yet a further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CH}_2\text{CH}_2\text{F}$, $-\text{CH}_2\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, $-\text{CBr}_3$, $-\text{CH}_2\text{CHF}_2$, $-\text{CH}_2\text{CF}_3$, $-\text{CH}_2\text{CHCl}_2$, $-\text{CH}_2\text{CCl}_3$, $-\text{CH}_2\text{CHBr}_2$, and $-\text{CH}_2\text{CBr}_3$. In an even further aspect, each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, $-\text{CH}_2\text{F}$, $-\text{CH}_2\text{Cl}$, $-\text{CH}_2\text{Br}$, $-\text{CHF}_2$, $-\text{CF}_3$, $-\text{CHCl}_2$, $-\text{CCl}_3$, $-\text{CHBr}_2$, and $-\text{CBr}_3$.

f. Ar^1 GROUPS

[00129] In one aspect, Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a further aspect, Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, or 2 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar^1 , when

present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, Ar¹, when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, Ar¹, when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and unsubstituted.

[00130] In a further aspect, Ar¹, when present, is aryl substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is aryl substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, Ar¹, when present, is aryl substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, Ar¹, when present, is aryl monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is unsubstituted aryl.

[00131] In a further aspect, Ar¹, when present, is phenyl substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is phenyl substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, Ar¹, when present, is phenyl substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, Ar¹, when present, is phenyl monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is unsubstituted phenyl.

[00132] In a further aspect, Ar¹, when present, is selected from 5-membered heteroaryl and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is selected from 5-membered heteroaryl and 6-membered heteroaryl and substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂,

C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, Ar¹, when present, is selected from 5-membered heteroaryl and 6-membered heteroaryl and substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, Ar¹, when present, is selected from 5-membered heteroaryl and 6-membered heteroaryl and monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is selected from 5-membered heteroaryl and 6-membered heteroaryl and unsubstituted.

[00133] In a further aspect, Ar¹, when present, is 5-membered heteroaryl substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is 5-membered heteroaryl substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, Ar¹, when present, is 5-membered heteroaryl substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, Ar¹, when present, is 5-membered heteroaryl monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is unsubstituted 5-membered heteroaryl.

[00134] In a further aspect, Ar¹, when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, Ar¹, when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, Ar¹, when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and unsubstituted.

[00135] In a further aspect, Ar¹, when present, is 6-membered heteroaryl substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is 6-membered heteroaryl substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, Ar¹, when present, is 6-membered heteroaryl substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, Ar¹, when present, is 6-membered heteroaryl monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is unsubstituted 6-membered heteroaryl.

[00136] In a further aspect, Ar¹, when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, Ar¹, when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, Ar¹, when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, Ar¹, when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and unsubstituted.

g. AR² AND AR³ GROUPS

[00137] In one aspect, each of Ar² and Ar³, when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a further aspect, each of Ar² and Ar³, when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl,

and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, each of Ar² and Ar³, when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, each of Ar² and Ar³, when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and unsubstituted.

[00138] In a further aspect, each of Ar² and Ar³, when present, is aryl substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is aryl substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, each of Ar² and Ar³, when present, is aryl substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, each of Ar² and Ar³, when present, is aryl monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is unsubstituted aryl.

[00139] In a further aspect, each of Ar² and Ar³, when present, is phenyl substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is phenyl substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, each of Ar² and Ar³, when present, is phenyl substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, each of Ar² and Ar³, when present, is phenyl monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is unsubstituted phenyl.

[00140] In a further aspect, each of Ar² and Ar³, when present, is independently selected from 5-membered heteroaryl and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups

independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is independently selected from 5-membered heteroaryl and 6-membered heteroaryl and substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, each of Ar² and Ar³, when present, is independently selected from 5-membered heteroaryl and 6-membered heteroaryl and substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, each of Ar² and Ar³, when present, is independently selected from 5-membered heteroaryl and 6-membered heteroaryl and monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is independently selected from 5-membered heteroaryl and 6-membered heteroaryl and unsubstituted.

[00141] In a further aspect, each of Ar² and Ar³, when present, is 5-membered heteroaryl substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is 5-membered heteroaryl substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, each of Ar² and Ar³, when present, is 5-membered heteroaryl substituted with 0 or 1 group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, each of Ar² and Ar³, when present, is 5-membered heteroaryl monosubstituted with a group selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is unsubstituted 5-membered heteroaryl.

[00142] In a further aspect, each of Ar² and Ar³, when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar² and Ar³, when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and substituted with 0, 1, or 2 groups independently selected from halogen, -OH, -CN, -NH₂, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, each of Ar² and Ar³, when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and substituted with 0 or 1 group

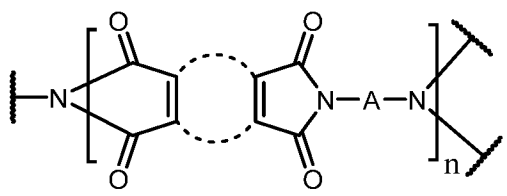
selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, each of Ar^2 and Ar^3 , when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and monosubstituted with a group selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar^2 and Ar^3 , when present, is selected from furanyl, thiophenyl, pyrrolyl, imidazolyl, pyrazolyl, and triazolyl and unsubstituted.

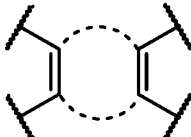
[00143] In a further aspect, each of Ar^2 and Ar^3 , when present, is 6-membered heteroaryl substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar^2 and Ar^3 , when present, is 6-membered heteroaryl substituted with 0, 1, or 2 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, each of Ar^2 and Ar^3 , when present, is 6-membered heteroaryl substituted with 0 or 1 group selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, each of Ar^2 and Ar^3 , when present, is 6-membered heteroaryl monosubstituted with a group selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar^2 and Ar^3 , when present, is unsubstituted 6-membered heteroaryl.

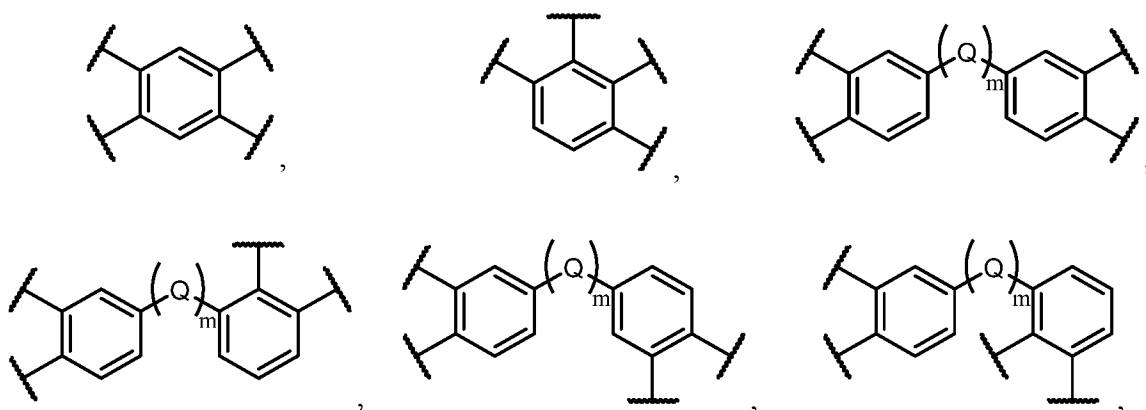
[00144] In a further aspect, each of Ar^2 and Ar^3 , when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar^2 and Ar^3 , when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and substituted with 0, 1, or 2 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In yet a further aspect, each of Ar^2 and Ar^3 , when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and substituted with 0 or 1 group selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In an even further aspect, each of Ar^2 and Ar^3 , when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and monosubstituted with a group selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy. In a still further aspect, each of Ar^2 and Ar^3 , when present, is selected from pyridinyl, pyridazinyl, pyrimidinyl, pyrazinyl, and triazinyl and unsubstituted.

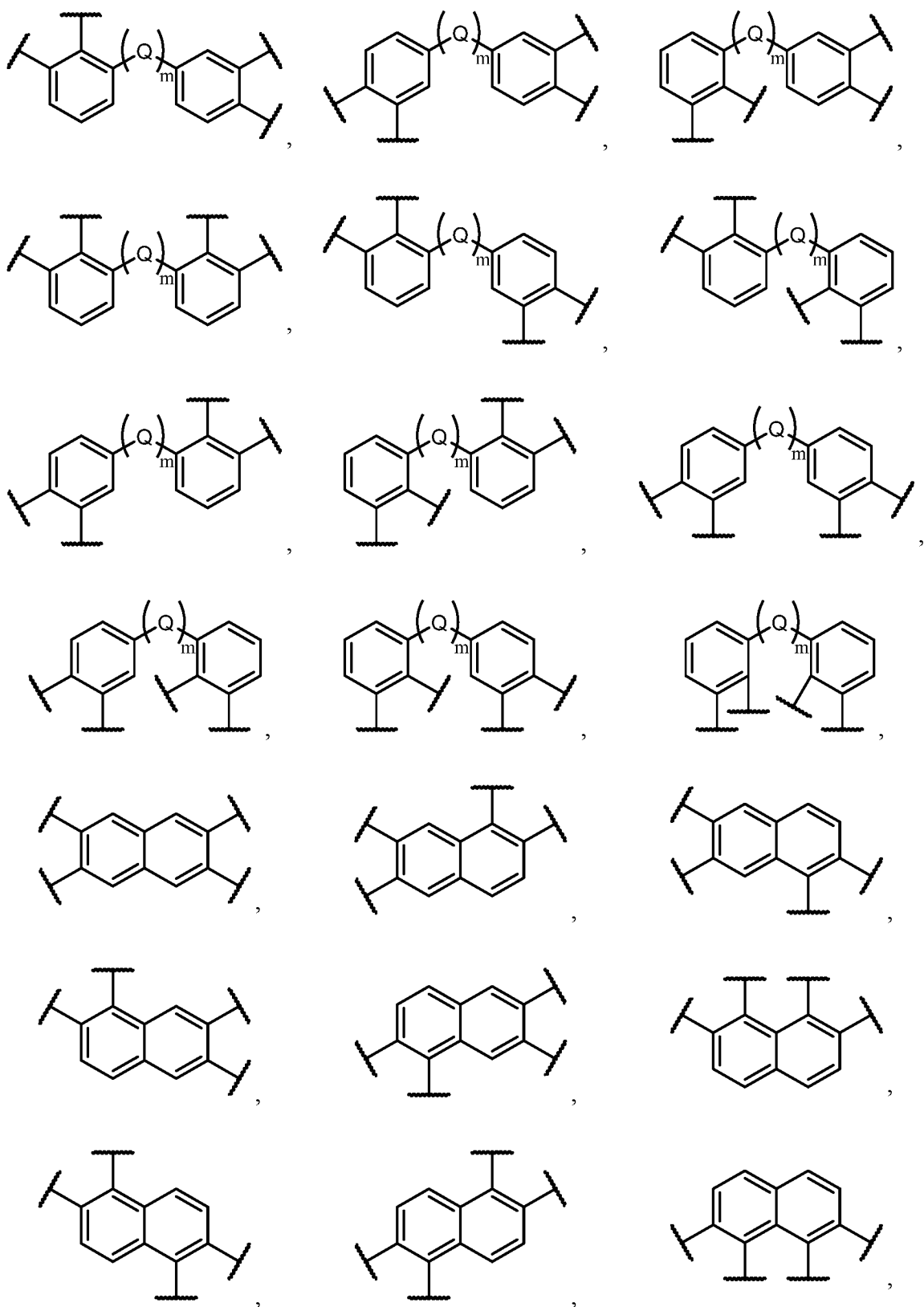
D. POLYIMIDE BLENDS

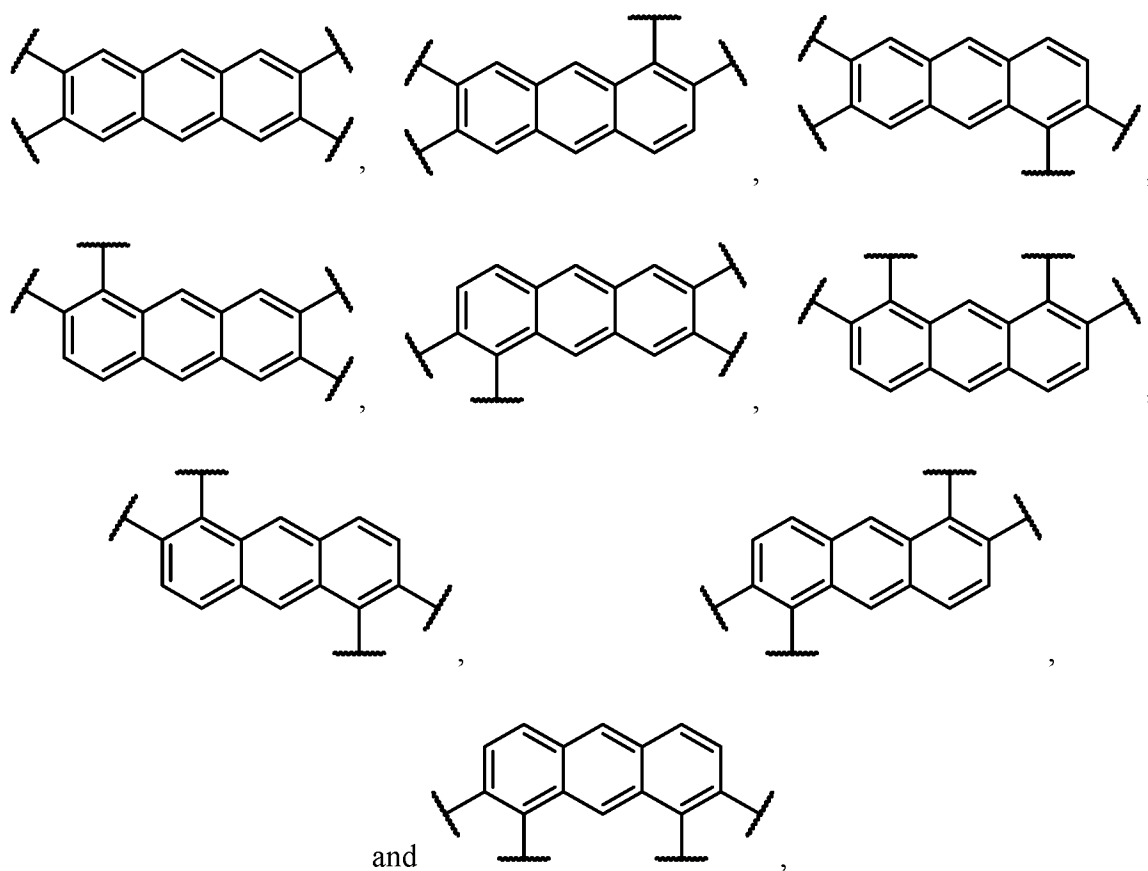
[00145] In one aspect, disclosed are polyimide blends comprising: (a) an ionic polymer selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acrylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion; and (b) a polyimide comprising at least one residue having a structure represented by a formula:



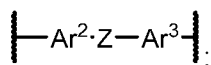
wherein  comprises a structure represented by a formula selected from:







wherein n is an integer greater than 1; wherein m is 0 or 1; wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:

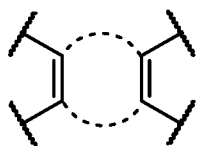
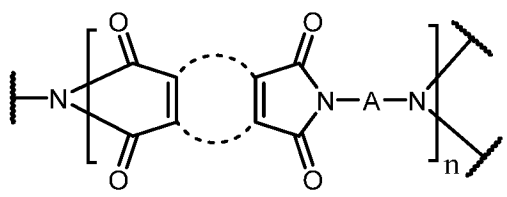


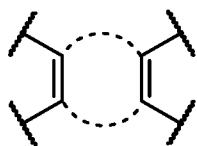
wherein Z , when present, is selected from O , NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO , and SO_2 ; wherein each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl; wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein Q , when present, is selected from O , NR^1 , SO , SO_2 , $\text{C}(\text{O})$, and $\text{CR}^{2a}\text{R}^{2b}$; and wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl.

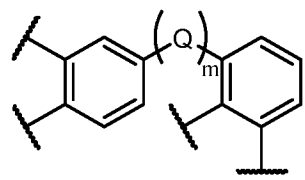
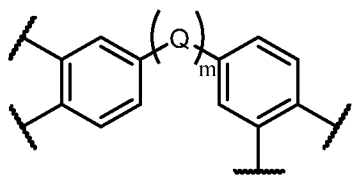
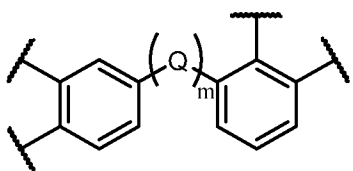
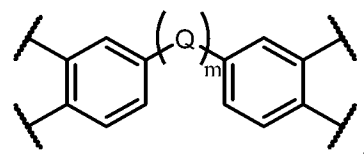
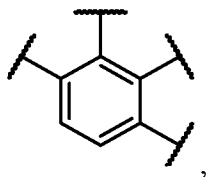
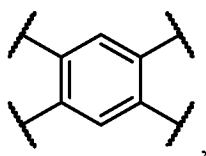
[00146] Aromatic polyimides are a class of high-performance polymers most widely used as coatings for microelectronic devices and high-temperature materials for the aerospace industry (59). Without wishing to be bound by theory, a blend comprising an ionic polymer and a disclosed polyimide may offer improved thermal properties, dimensional stability, and mechanical properties. There have been some reports on developing high-performance fuel cell applications (62-67) with sulfonated polyimide polyelectrolytes. However, only limited examples are available for electromechanical applications of sulfonated PIs (68, 69). These examples utilize the lengthy chemical synthesis for sulfonated PI. Here, physical blends comprising a polyimide and an ionic polymer are described. Without wishing to be bound by theory, these blends may offer improved properties compared to ion exchange membranes comprising the ionic polymer alone.

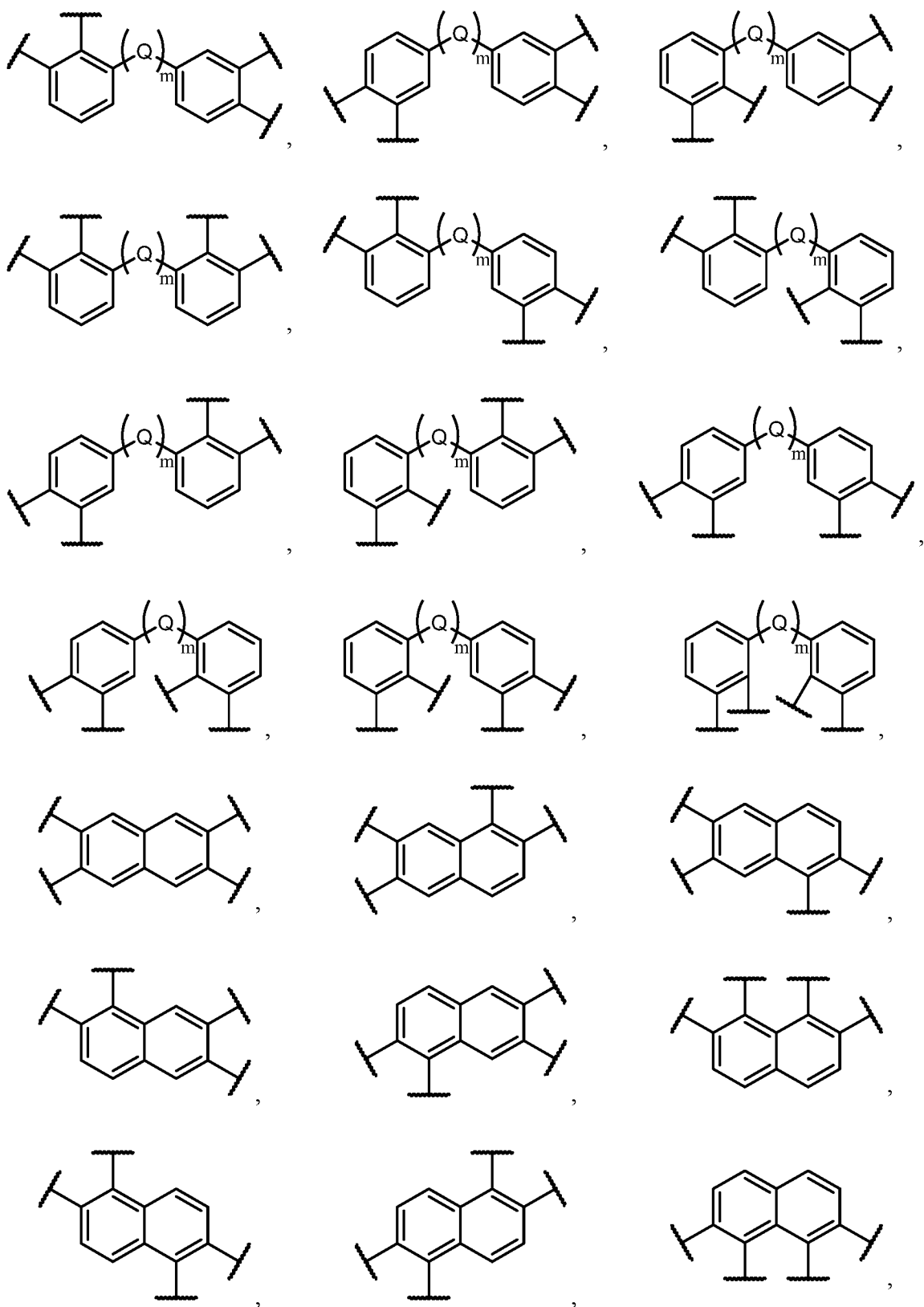
1. POLYIMIDES

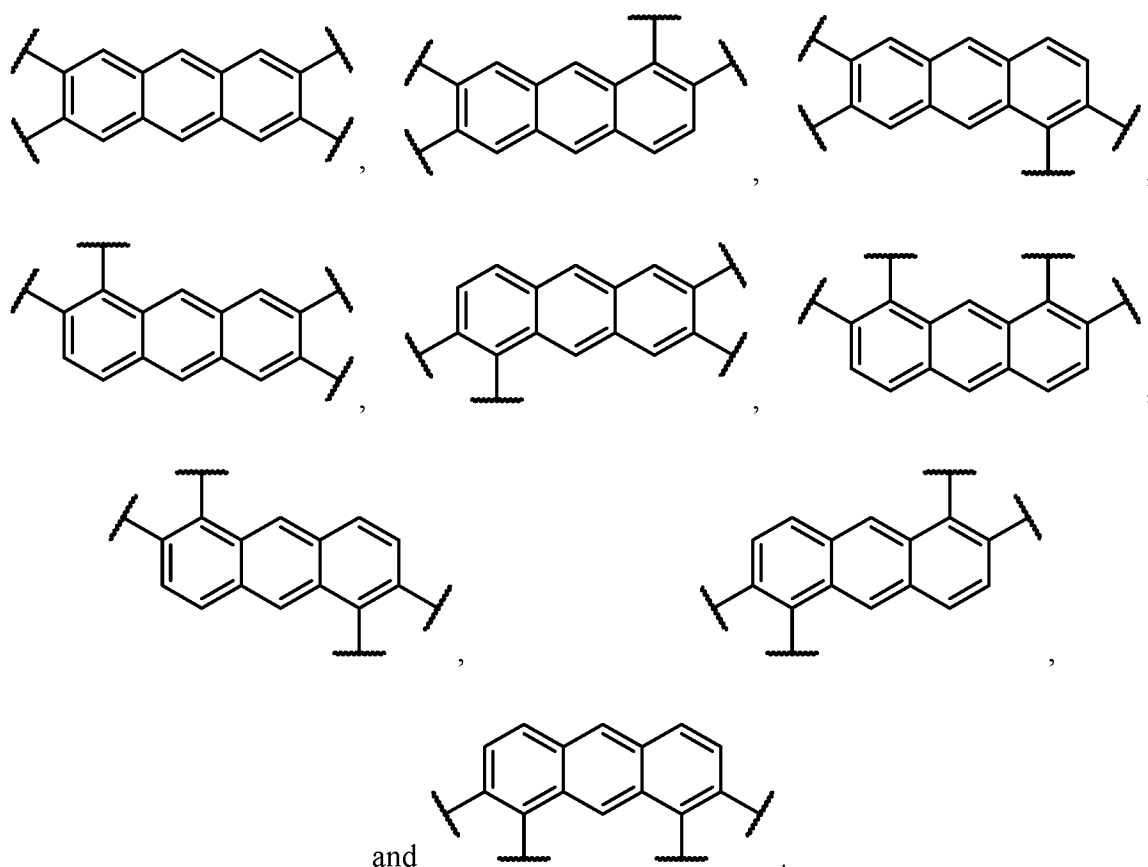
[00147] In one aspect, the disclosed polyimide blends comprise a polyimide comprising at least one residue having a structure represented by a formula:



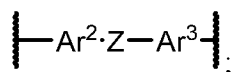
wherein  comprises a structure represented by a formula selected from:





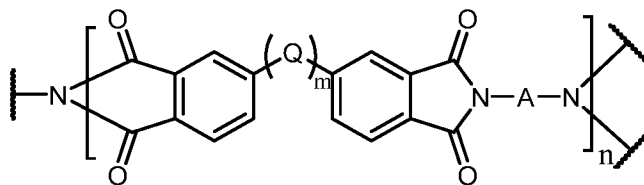


wherein n is an integer greater than 1; wherein m is 0 or 1; wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:

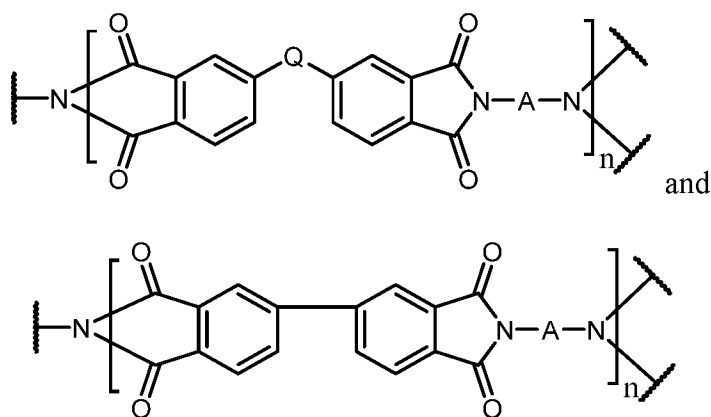


wherein Z , when present, is selected from O , NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO , and SO_2 ; wherein each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl; wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein Q , when present, is selected from O , NR^1 , SO , SO_2 , C(O) , and $\text{CR}^{2a}\text{R}^{2b}$; and wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl.

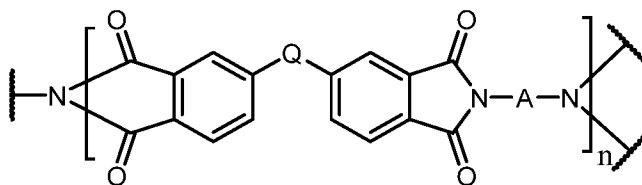
[00148] In a further aspect, the polyimide comprises at least one residue having a structure represented by a formula:



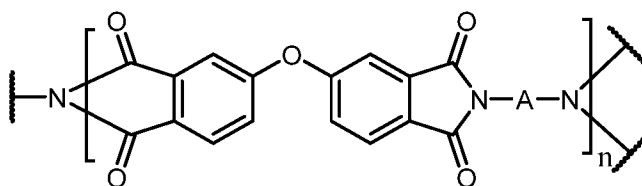
[00149] In a still further aspect, the polyimide comprises at least one residue having a structure represented by a formula selected from:

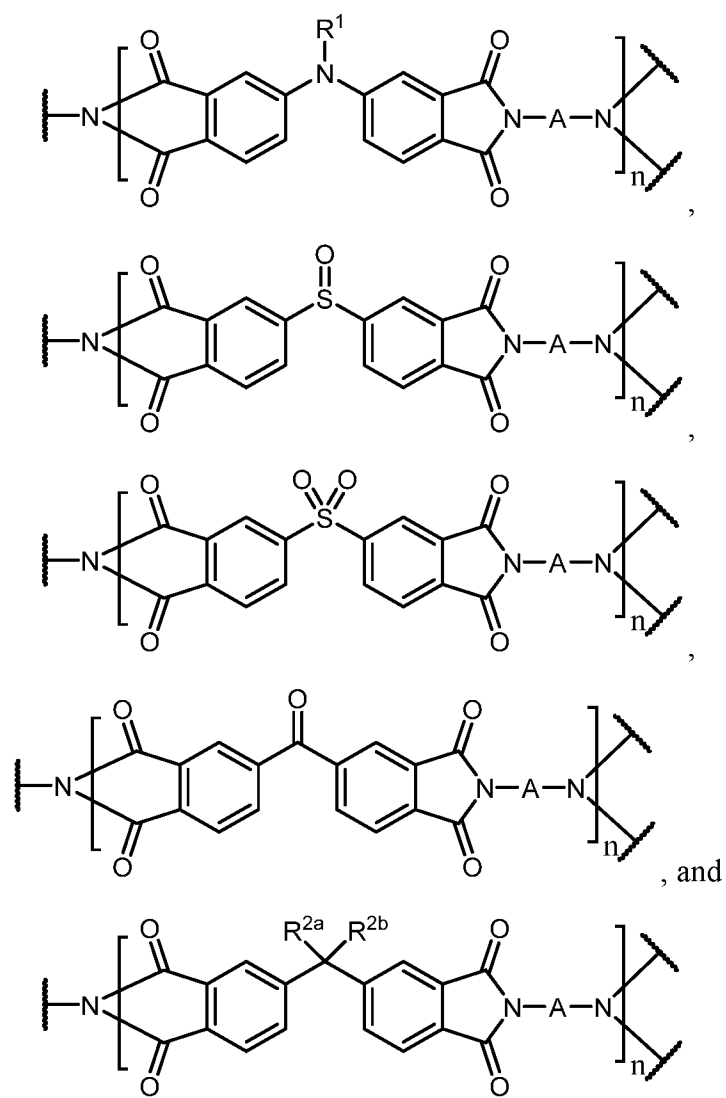


[00150] In yet a further aspect, the polyimide comprises at least one residue having a structure represented by a formula:

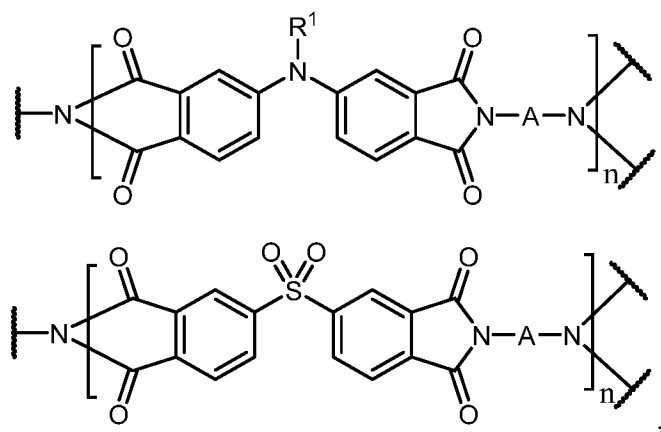


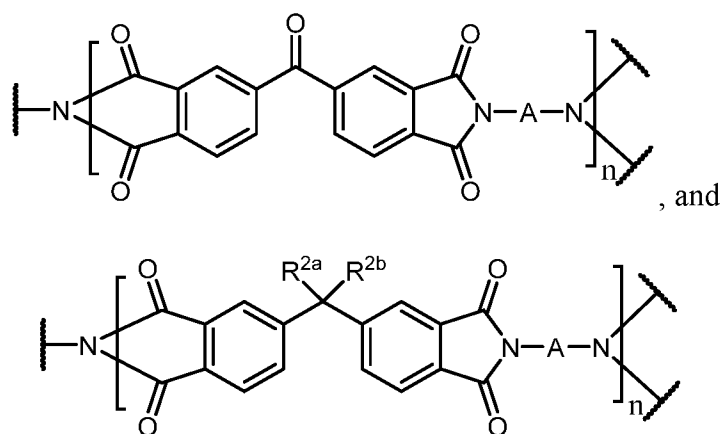
[00151] In an even further aspect, the polyimide comprises at least one residue having a structure represented by a formula selected from:



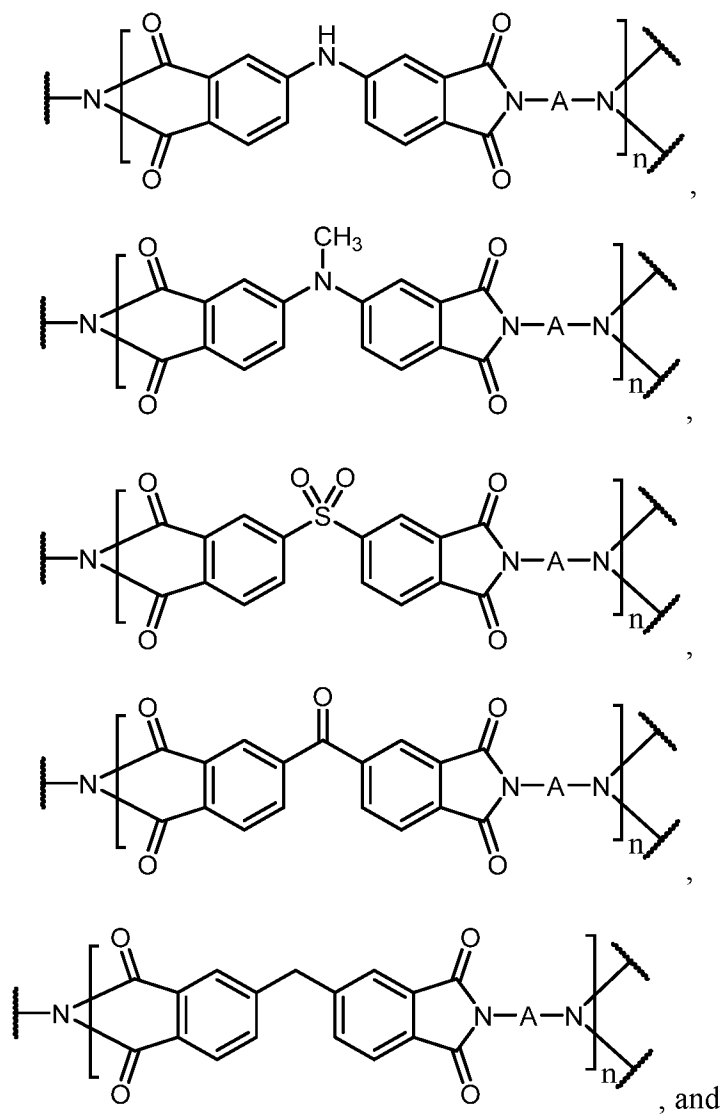


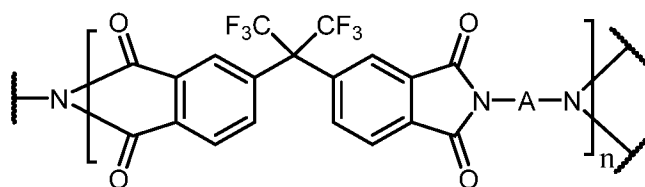
[00152] In a still further aspect, the polyimide comprises at least one residue having a structure represented by a formula selected from:



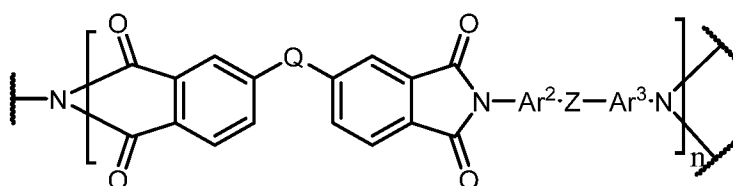


[00153] In yet a further aspect, the polyimide comprises at least one residue having a structure represented by a formula selected from:

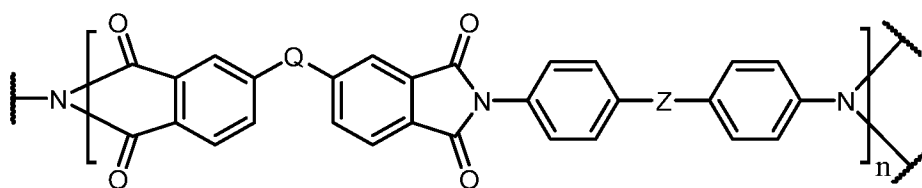




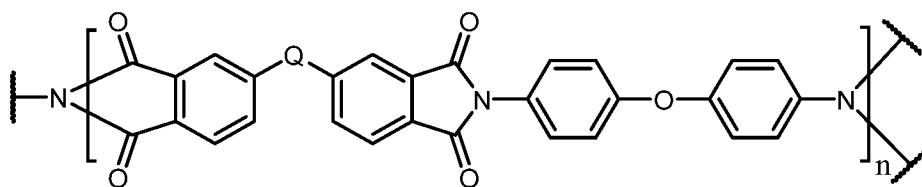
[00154] In an even further aspect, the polyimide comprises at least one residue having a structure represented by a formula:



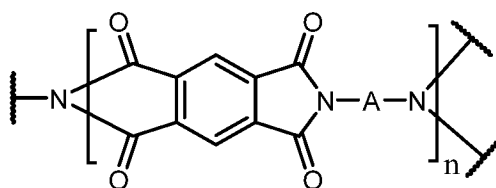
[00155] In a still further aspect, the polyimide comprises at least one residue having a structure represented by a formula:



[00156] In yet a further aspect, the polyimide comprises at least one residue having a structure represented by a formula:

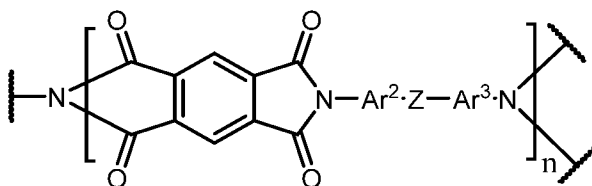


[00157] In a further aspect, the polyimide comprises at least one residue having a structure represented by a formula:

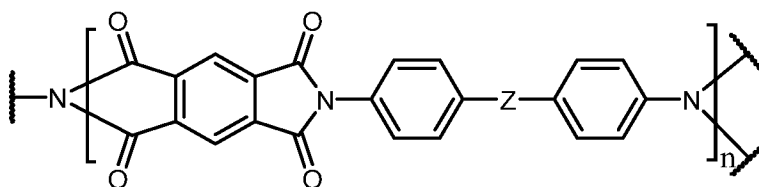


[00158] In a still further aspect, the polyimide comprises at least one residue having a

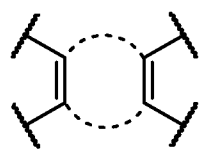
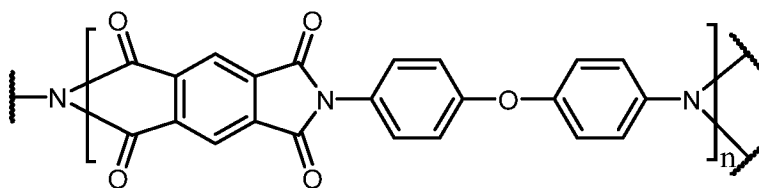
structure represented by a formula:



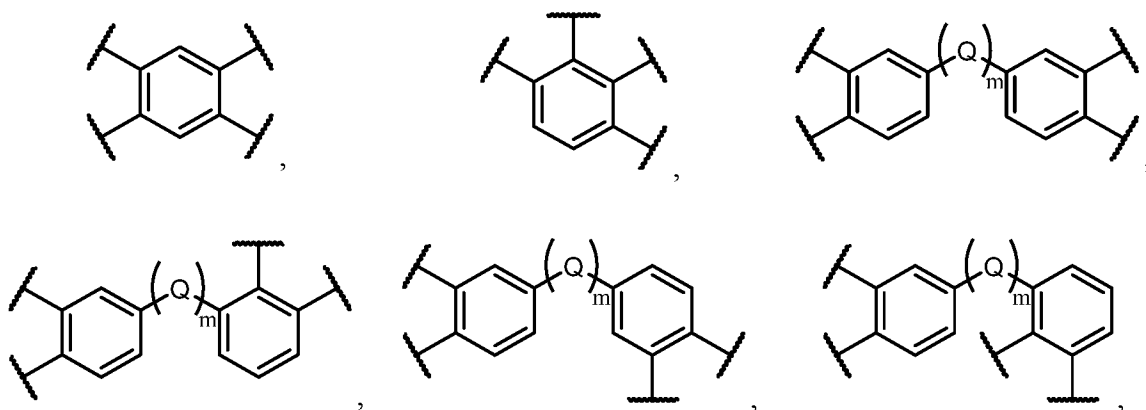
[00159] In yet a further aspect, the polyimide comprises at least one residue having a structure represented by a formula:

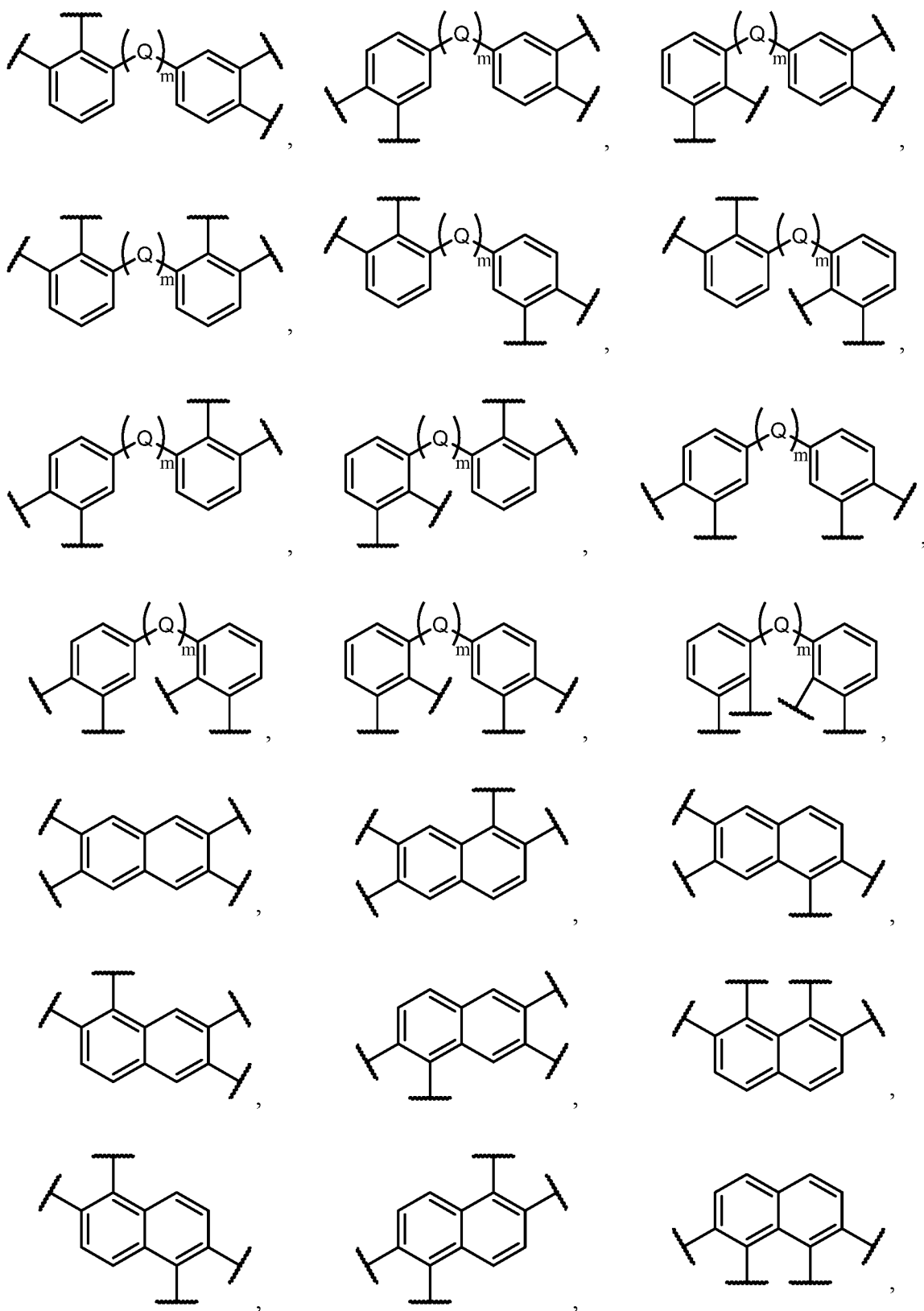


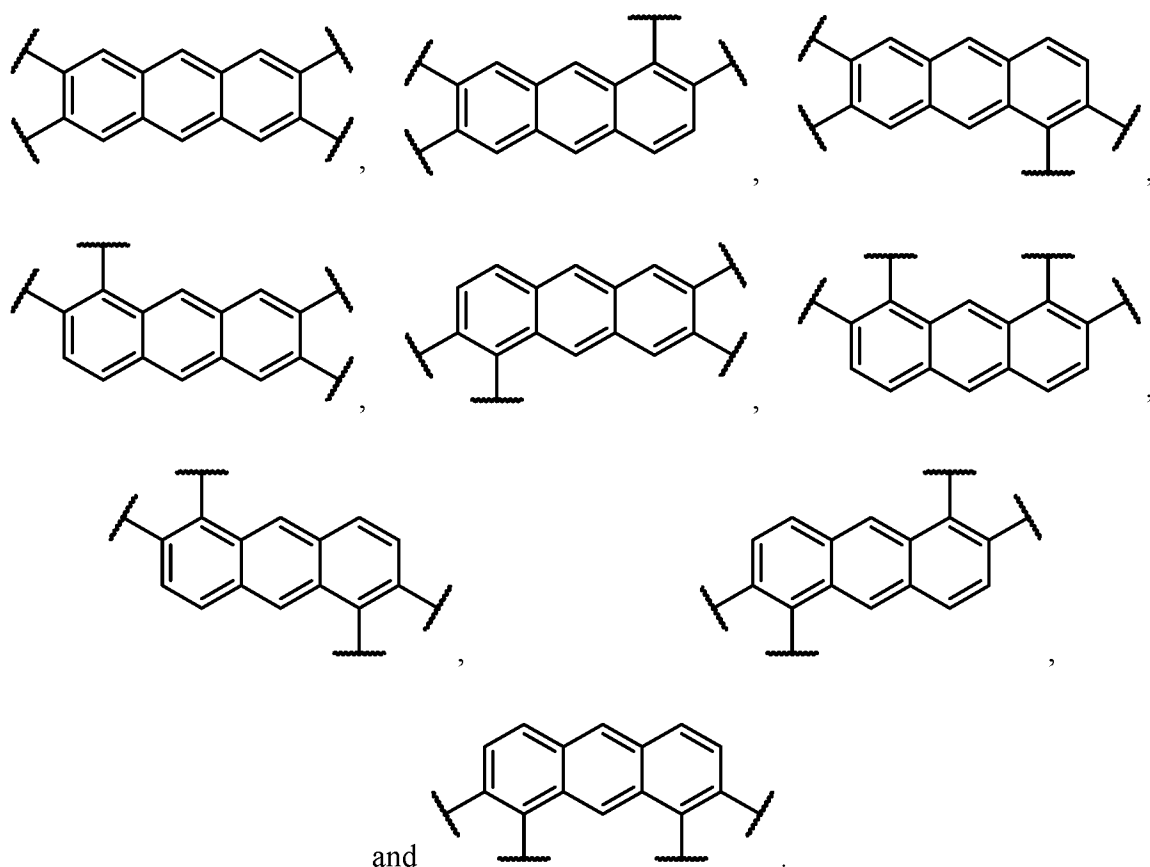
[00160] In an even further aspect, the polyimide comprises at least one residue having a structure represented by a formula:



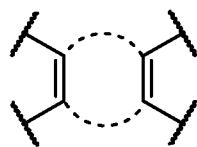
[00161] In one aspect, comprises a structure represented by a formula selected from:



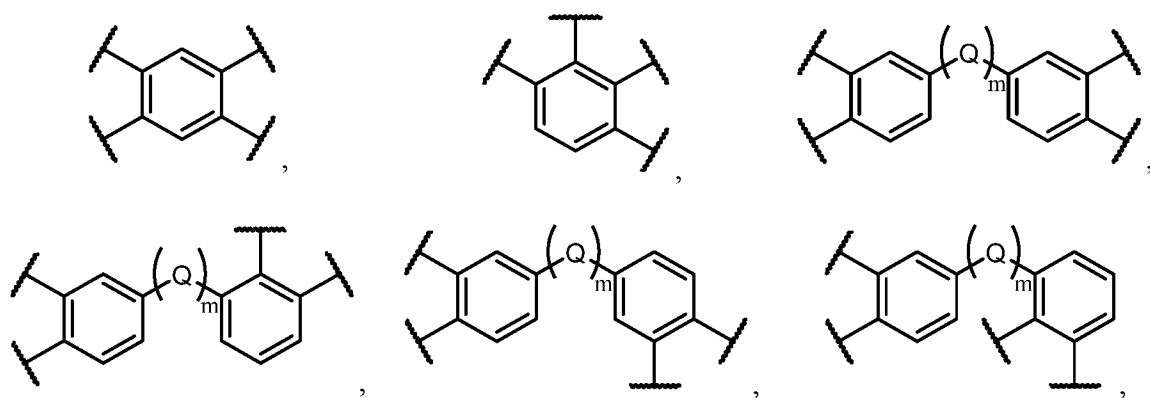


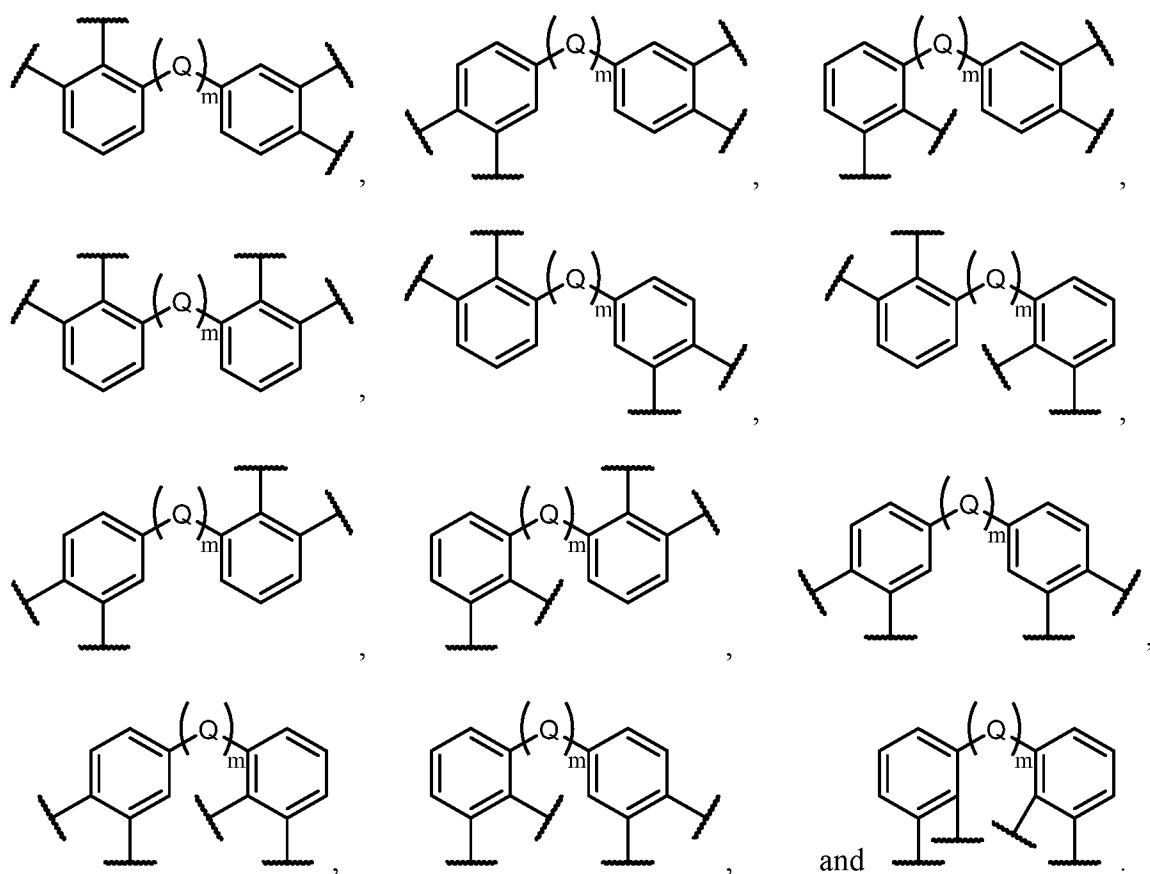


[00162] In a further aspect,
selected from:

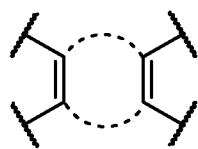


comprises a structure represented by a formula

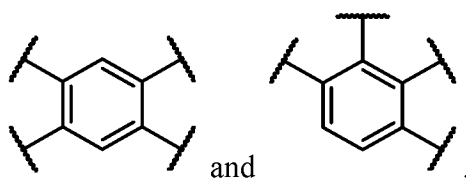




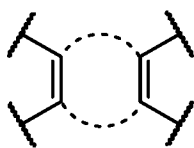
[00163] In a further aspect,
selected from:



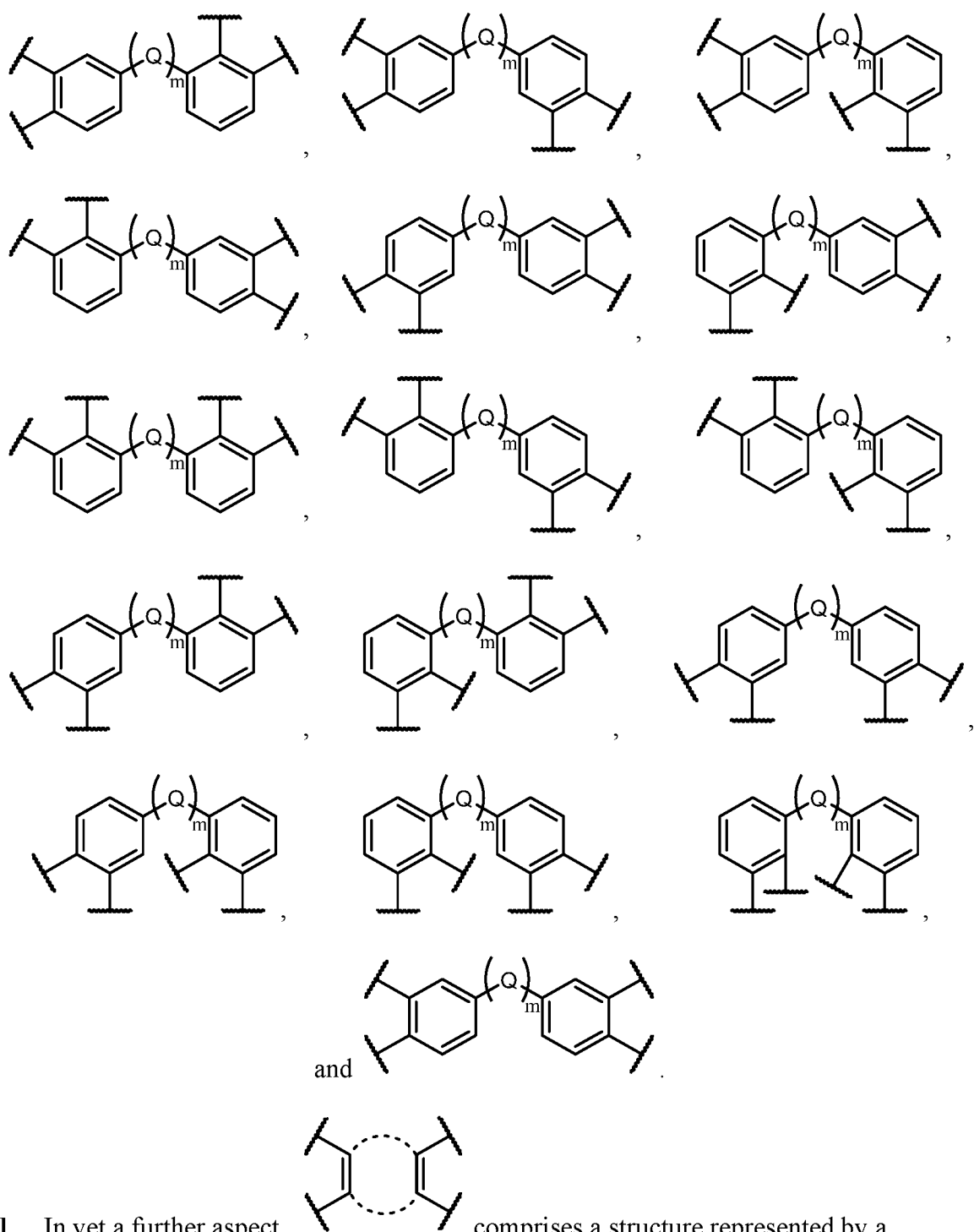
comprises a structure represented by a formula



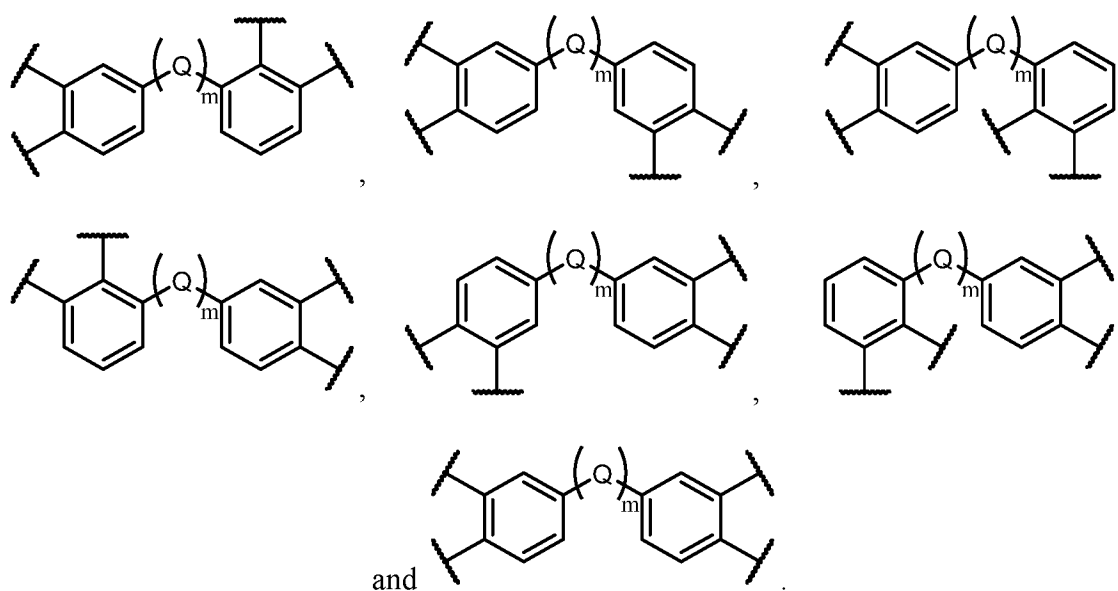
[00164] In a still further aspect,
formula selected from:



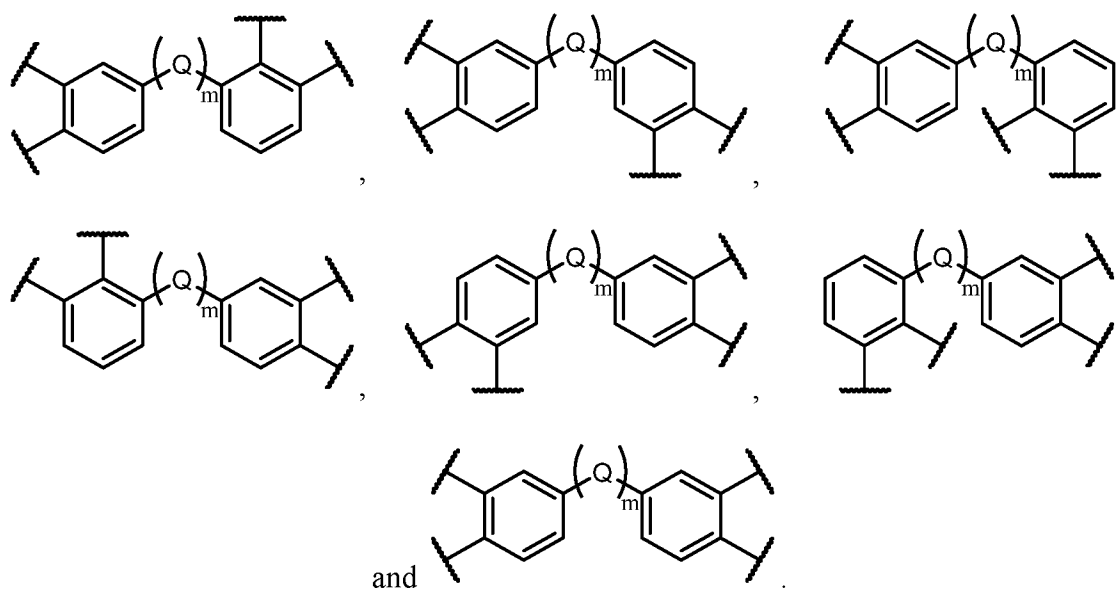
comprises a structure represented by a



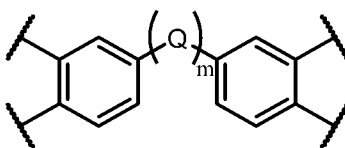
[00165] In yet a further aspect,
formula selected from:



[00166] In an even further aspect,  comprises a structure represented by a formula selected from:



[00167] In a still further aspect,  comprises a structure represented by a formula:



[00168] In one aspect, n is an integer greater than 1. In a further aspect, n is an integer greater than 10. In a still further aspect, n is an integer greater than 100. In yet a further aspect, n is an integer greater than 1000. In an even further aspect, n is an integer greater than 10,000. In a still further aspect, n is an integer greater than 100,000.

[00169] In one aspect, m is 0 or 1. In a further aspect, m is 0. In a still further aspect, m is 1.

2. PROPERTIES OF MEMBRANES

[00170] In various aspects, the disclosed ion exchange membranes can have various properties that provide the superior function of the membranes, including improved storage modulus, excellent elasticity, decreased damping, and excellent surface resistance. It is also understood that the membranes have other properties.

[00171] In various aspects, the membrane can have a storage modulus of from about 0.2 GPa to about 5.0 GPa. In a further aspect, the membrane can have a storage modulus of from about 0.2 GPa to about 4.0 GPa. In a still further aspect, the membrane can have a storage modulus of from about 0.2 GPa to about 3.0 GPa. In yet a further aspect, the membrane can have a storage modulus of from about 0.2 GPa to about 2.0 GPa. In an even further aspect, the membrane can have a storage modulus of from about 0.5 GPa to about 5.0 GPa. In a still further aspect, the membrane can have a storage modulus of from about 1.0 GPa to about 5.0 GPa. In yet a further aspect, the membrane can have a storage modulus of from about 2.0 GPa to about 5.0 GPa. In an even further aspect, the membrane can have a storage modulus of from about 3.0 GPa to about 5.0 GPa. In a still further aspect, the membrane can have a storage modulus of from about 0.5 GPa to about 4.0 GPa. In yet a further aspect, the membrane can have a storage modulus of from about 0.5 GPa to about 3.0 GPa. In an even further aspect, the membrane can have a storage modulus of from about 1.0 GPa to about 3.0 GPa.

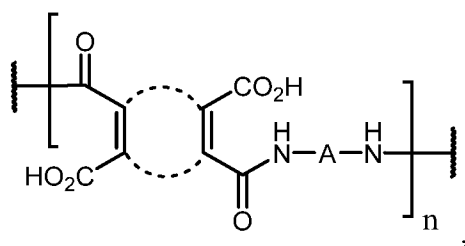
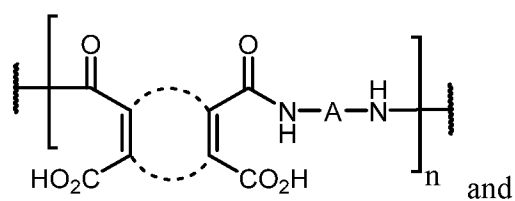
[00172] In various aspects, the membrane can have a surface resistance of from about 1.0 Ω/cm to about 20.0 Ω/cm . In a further aspect, the membrane can have a surface resistance of from about 1.0 Ω/cm to about 15.0 Ω/cm . In a still further aspect, the membrane can have a

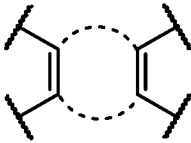
surface resistance of from about 1.0 Ω/cm to about 10.0 Ω/cm . In yet a further aspect, the membrane can have a surface resistance of from about 1.0 Ω/cm to about 5.0 Ω/cm . In a still further aspect, the membrane can have a surface resistance of from about 5.0 Ω/cm to about 20.0 Ω/cm . In yet a further aspect, the membrane can have a surface resistance of from about 10.0 Ω/cm to about 20.0 Ω/cm . In an even further aspect, the membrane can have a surface resistance of from about 15.0 Ω/cm to about 20.0 Ω/cm . In a still further aspect, the membrane can have a surface resistance of from about 5.0 Ω/cm to about 15.0 Ω/cm . In yet a further aspect, the membrane can have a surface resistance of from about 5.0 Ω/cm to about 10.0 Ω/cm .

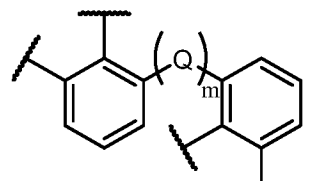
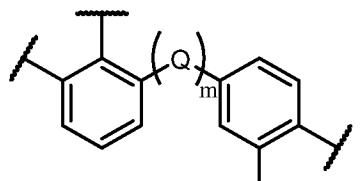
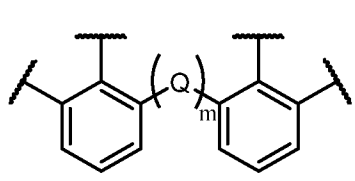
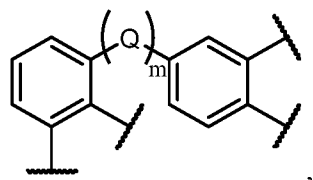
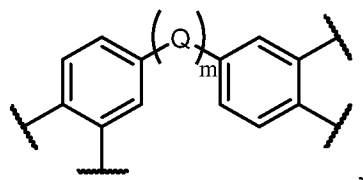
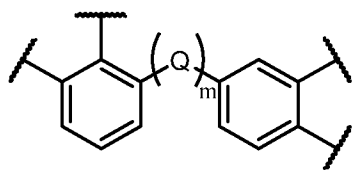
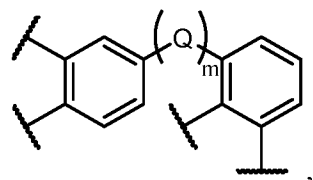
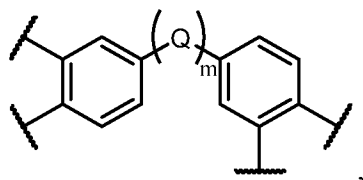
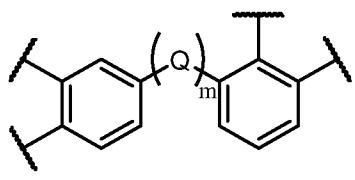
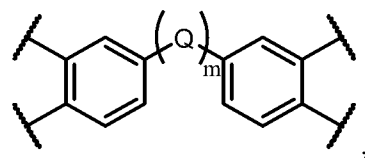
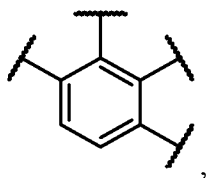
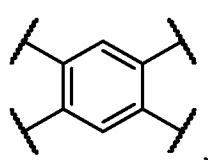
[00173] In a further aspect, the membrane exhibits an improvement in at least one property selected from elasticity, storage modulus, and surface resistance. In a still further aspect, the membrane exhibits an improvement in at least one property selected from elasticity and storage modulus. In yet a further aspect, the membrane exhibits an improvement in at least one property selected from elasticity and surface resistance. In an even further aspect, the membrane exhibits an improvement in at least one property selected from storage modulus and surface resistance. In a still further aspect, the membrane exhibits an improvement in elasticity. In yet a further aspect, the membrane exhibits an improvement in storage modulus. In an even further aspect, the membrane exhibits an improvement in surface resistance.

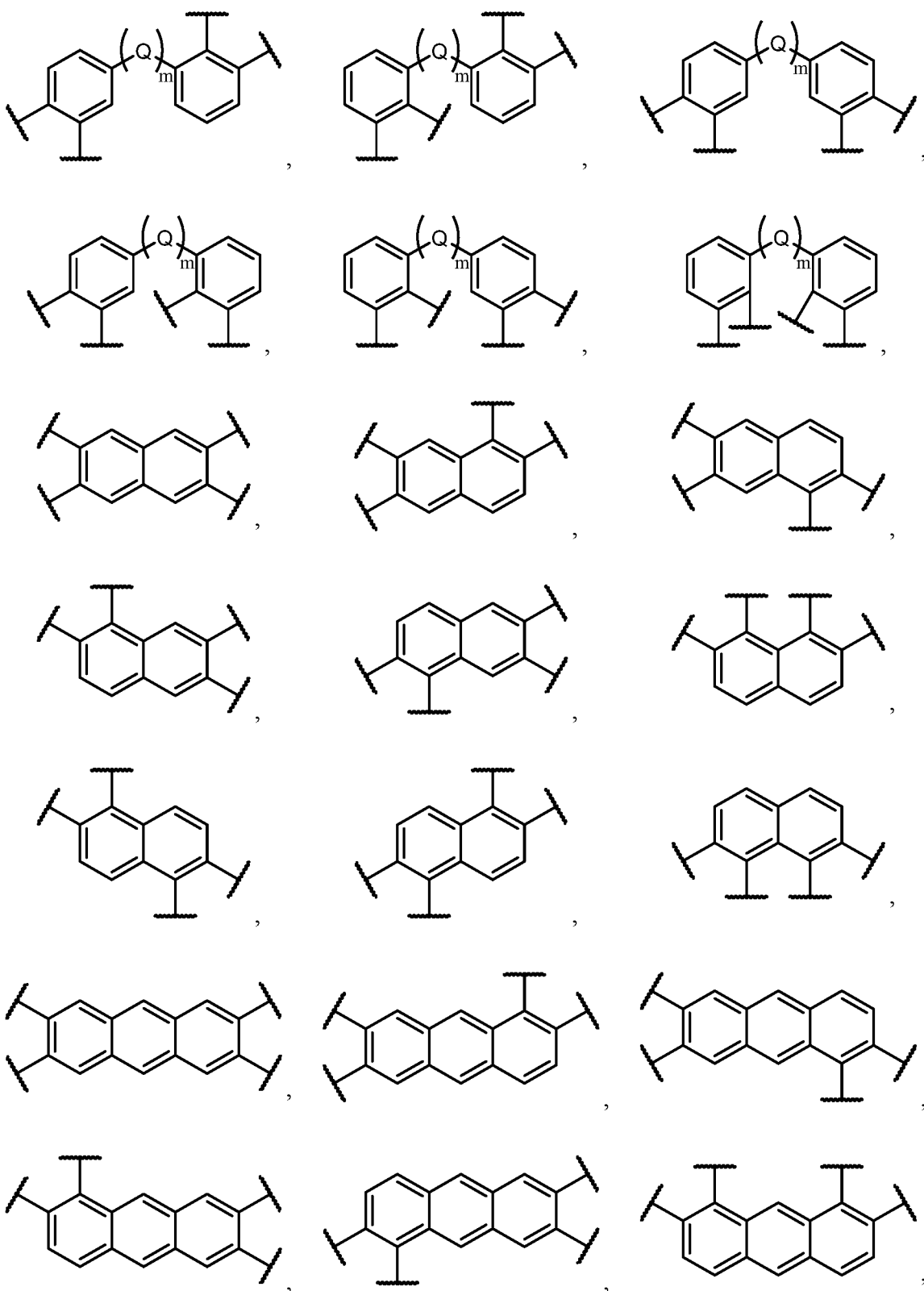
E. METHODS OF MAKING POLYIMIDE BLENDS

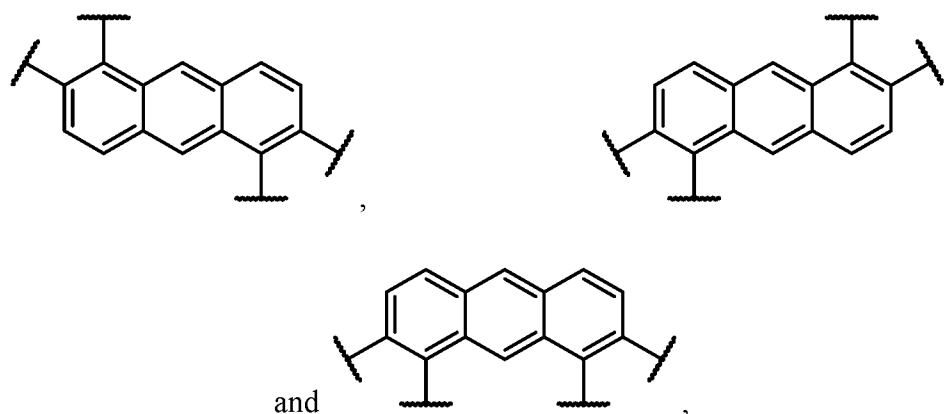
[00174] In one aspect, the invention relates to methods of making a polyimide blend, the method comprising: (a) mixing an ionic polymer selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion, and a poly(amic acid) comprising at least one residue having a structure represented by a formula selected from:



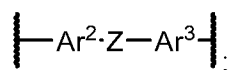
wherein  comprises a structure represented by a formula selected from:







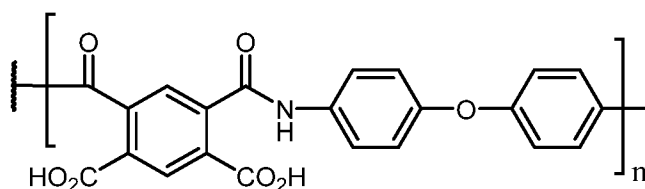
wherein n is an integer greater than 1; wherein m is 0 or 1; wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:



wherein Z , when present, is selected from O , NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO , and SO_2 ; wherein each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl; wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy; wherein Q , when present, is selected from O , NR^1 , SO , SO_2 , $\text{C}(\text{O})$, and $\text{CR}^{2a}\text{R}^{2b}$; and wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl, thereby making a poly(amic acid) blend; and (b) cyclizing the poly(amic acid) blend.

[00175] In a further aspect, the ionic polymer is Nafion.

[00176] In a further aspect, the poly(amic acid)) comprises at least one residue having a structure:



[00177] In a further aspect, the poly(amic acid) is present in solution. In a still further aspect, the poly(amic acid) solution comprises an aprotic polar solvent. In yet a further aspect, the aprotic polar solvent is selected from N,N-dimethylformamide and N-methyl-2-pyrrolidone.

[00178] In a further aspect, the aprotic polar solvent is present in an amount of from about 95 wt% to about 99 wt% of the poly(amic acid) solution. In a still further aspect, the aprotic polar solvent is present in an amount of about 95 wt% of the poly(amic acid) solution.

[00179] In a further aspect, the poly(amic acid) solution is present in an amount of from about 20 wt% to about 50 wt%.

[00180] In a further aspect, the ionic polymer is present in solution and the poly(amic acid) is present in solution, and wherein the ionic polymer and the poly(amic acid) together have a concentration of from about 0.01 g/mL to about 6 g/mL. In a still further aspect, the ionic polymer is present in solution and the poly(amic acid) is present in solution, and wherein the ionic polymer and the poly(amic acid) together have a concentration of from about 0.03 g/mL to about 6 g/mL.

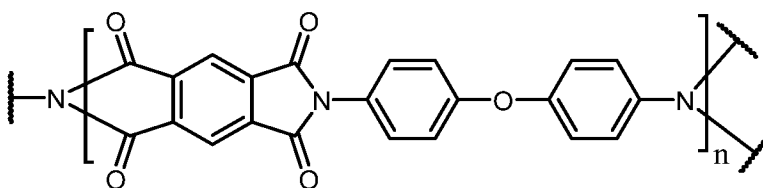
[00181] In a further aspect, mixing is blending. In a still further aspect, mixing is solution-casting. In yet a further aspect, solution-casting is performed at a temperature of from about 50 °C to about 100 °C. In an even further aspect, solution-casting is performed at a temperature of from about 40 °C to about 90 °C.

[00182] In a further aspect, cyclizing is via heat. In a still further aspect, the heat is applied at a temperature of from about 180 °C to about 250 °C.

[00183] In a further aspect, the heat is applied for from about 12 h to about 36 h.

[00184] In a further aspect, the heat is applied under vacuum, nitrogen, or helium.

[00185] In a further aspect, the polyimide comprises at least one residue having a structure:



[00186] In a further aspect, the method further comprises plating a metal electrode onto the

polyimide blend. In a still further aspect, the metal is Pt.

[00187] In a further aspect, the method further comprises modifying at least one surface of a polymeric membrane with the polyimide blend. In a still further aspect, modifying is via a bond. In yet a further aspect, modifying comprises coating the surface with the polyimide blend. In an even further aspect, modifying comprises exposing the surface to a light source.

[00188] In a further aspect, the method further comprises modifying at least one surface of a polymeric membrane with the polyimide blend. In a still further aspect, modifying is via a bond. In yet a further aspect, modifying comprises coating the surface with the polyimide blend. In an even further aspect, modifying comprises exposing the surface to a light source.

[00189] In a further aspect, the membrane exhibits an improvement in at least one property selected from elasticity, storage modulus, and surface resistance. In a still further aspect, the membrane exhibits an improvement in at least one property selected from elasticity and storage modulus. In yet a further aspect, the membrane exhibits an improvement in at least one property selected from elasticity and surface resistance. In an even further aspect, the membrane exhibits an improvement in at least one property selected from storage modulus and surface resistance. In a still further aspect, the membrane exhibits an improvement in elasticity. In yet a further aspect, the membrane exhibits an improvement in storage modulus. In an even further aspect, the membrane exhibits an improvement in surface resistance.

F. EXPERIMENTAL

[00190] The following examples are put forth so as to provide those of ordinary skill in the art with a complete disclosure and description of how the compounds, compositions, articles, devices and/or methods claimed herein are made and evaluated, and are intended to be purely exemplary of the invention and are not intended to limit the scope of what the inventors regard as their invention. Efforts have been made to ensure accuracy with respect to numbers (*e.g.*, amounts, temperature, etc.), but some errors and deviations should be accounted for. Unless indicated otherwise, parts are parts by weight, temperature is in °C or is at ambient temperature, and pressure is at or near atmospheric.

1. MATERIALS

[00191] Poly(pyromellitic dianhydride-co-4,4'-oxydianiline), amic acid solution (11 wt% \pm 5 wt% in NMP/aromatic hydrocarbons (80 % / 20 % solvent ratio)) was purchased from Sigma-Aldrich. Alcohol-based Nafion dispersion (5 wt%) and NMP were purchased from DuPontTM and TCI, respectively and were used for preparation of the blend membranes. Tetraammineplatinum (II) chloride hydrate ($\text{Pt}(\text{NH}_3)_4\text{Cl}_2 \cdot x\text{H}_2\text{O}$), ammonium hydroxide (NH_4OH), and sodium borohydride (NaBH_4) were purchased from Sigma-Aldrich and used for platinum plating. Hydrazine monohydrate ($\text{H}_2\text{NNH}_2 \cdot \text{H}_2\text{O}$) and hydroxylamine hydrochloride ($\text{H}_2\text{NOH} \cdot \text{HCl}$) were purchased from Sigma-Aldrich and used as the reducing agents. Lithium chloride (LiCl) was purchased from Sigma-Aldrich. Deionized (D.I.) water was used to clean the membrane and to prepare IPMCs.

2. MEMBRANE PREPARATION

[00192] The membrane of Nafion was provided by solution casting of 30 mL of Nafion dispersion (5 wt%, d: 0.87 g/mL) in a polystyrene mold ($r = 3.0$ cm, 1.9 depth) at 50 °C overnight. PI membrane was provided by solution casting of 12 mL of poly(pyromellitic dianhydride-co-4,4'-oxydianiline), amic acid solution (11 wt% \pm 5 wt% in NMP/aromatic hydrocarbons (80 % / 20 % solvent ratio), d : 1.066 g/mL) in aluminum foil mold ($r = 2.3$ cm, 1.27 cm depth) at 85 °C overnight.

[00193] Blend membranes of Nafion and PAA were prepared by solution casting of 21 mL of mixed Nafion solution (5 wt%) with PAA / NMP solution (1.26 wt%) through the following procedures. At first, 11 wt% PAA solution (5.33 g, 5 mL) and NMP (41.36 g, 40 mL) were added in a 100-mL beaker and stirred at room temperature for 1 hour. This 1.26 wt% PAA solution (amount of PAA solution used for samples, NPI-6: 3.7 mL, 0.044 g, NPI-12: 6.6 mL, 0.086 g, NPI-18: 8.8 mL, 0.115 g, and NPI-30: 4.3 mL, 3.9 g) was mixed with 5 wt% Nafion (amount of Nafion solution used for samples, NPI-6: 17.3 mL, 15.05 g, NPI-12: 14.4 mL, 12.53 g, NPI-18: 12.2 mL, 10.61 g, and NPI-30: 10.5 mL, 9.1 g) and the mixtures were stirred at 70 °C for NPI-6 (due to small amount of NMP) and room temperature for NPI-12, NPI-18, and NPI-30 for 1 hour. NPI-6, NPI-12, and NPI-18 were stirred at 60 °C overnight to evaporate solvent in a 50 mL beaker covered with Kimwipes[®]. In the case of NPI-30, temperature was set to 50 °C

since less solvent needed to be evaporated. The solutions were cooled to room temperature. None of the solutions precipitated, so each solution was poured into an aluminum foil mold ($r = 2.3$ cm, 1.27 cm in depth). As shown in **FIG. 1A**, the mold was placed in a desiccator connected to house vacuum and bubbles are removed for 10-20 minutes before casting. For samples NPI-6, NPI-12, and NPI-18, the mold was placed on a hot plate and was heated at 85 °C overnight. For NPI-30, the mold was placed in an oven at 70 °C for 2 days, since the same condition as other blends produced very brittle film. The cast membranes were taken out of the molds and placed in vacuum oven at 180 °C for 12 hours for thermal imidization to obtain Nafion/PI blend membranes. The photographs of prepared membranes are shown in **FIG. 1B** and the detailed composition of materials is summarized in Table 1.

[00194] As shown in Table 1, NPI-6, NPI-12, NPI-18, and NPI-30 were named based on the weight ratio of PI to Nafion after drying solvents. The total amount of PI and Nafion in unit area respectively were calculated in mg/cm^2 and the weight ratio of the two components.

TABLE 1.

Samples	Wt% ratio (PI : Nafion)	Total amount of PI (mg/cm^2)	Total amount of Nafion (mg/cm^2)	Casting condition	Thickness (μm)
Nafion	0 : 100	-	46.3	50 °C, 5 hrs	340
NPI-6	6 : 94	3.01	45.2	85 °C, overnight	278
NPI-12	12 : 88	5.42	38		285
NPI-18	18 : 82	7.22	31.9		290
NPI-30	30 : 70	11.7	27.4	70 °C, 2 days	310
PI	100 : 0	38.6	-	85 °C, overnight	350

3. FABRICATION OF IPMCs

[00195] The membranes were sanded with sandpaper (800 / 1000 counts) in order to deposit more platinum particles onto the inner surface by increasing the surface area. It also helps increase the contact area of polymer and electrode. Sanding needs to be done in the direction perpendicular to the bending direction of the IPMC. After sanding, all membranes were cleaned to remove impurities before progressing to the primary plating process. Membranes were cleaned in 3 wt% H_2O_2 solution at 70 °C for 40 minutes, 1 M H_2SO_4 aqueous solution at 60 °C for 40 minutes, D.I. water at 70 °C for 40 minutes, 1 M H_2SO_4 aqueous solution at 60 °C for 40 minutes, followed by cleaning in D.I. water at 40 °C for 40 minutes.

[00196] The next step, primary plating is an impregnation-reduction process on the roughened inner surface of the membranes. Membranes were soaked in 0.02M Pt (II) salt solution (tetraammineplatinum (II) chloride hydrate, $\text{Pt}(\text{NH}_3)_4\text{Cl}_2 \cdot x\text{H}_2\text{O}$) for 3.5 h and rinsed with D.I. water several times. To metalize the surface of the membranes, they were immersed in 350 mL aqueous solution containing NH_4OH (0.3 mL) and NaBH_4 (0.2 g) at 60 °C for 2 h. 0.2 g of NaBH_4 was added every 0.5 h. Membranes were cleaned in 1 M H_2SO_4 aqueous solution at 60 °C for 40 minutes, D.I. water at 70 °C for 40 minutes, 1 M H_2SO_4 aqueous solution at 60 °C for 40 minutes, followed by cleaning in D.I. water at 40 °C for 40 minutes. The primary plating procedure was repeated three times.

[00197] The secondary plating was processed to develop platinum on the outer surface of the membrane, on top of the inner platinum layer, to reduce the surface resistance of the electrode. The membranes were soaked in 350 mL of aqueous solution containing Pt (II) salt (0.2 g) and two reducing agents, 20 wt% $\text{H}_2\text{NNH}_2 \cdot \text{H}_2\text{O}$ solution (1 mL) and 5 wt% $\text{H}_2\text{NOH} \cdot \text{HCl}$ solution (2 mL) at 50 °C for 1 h and then 60 °C for 3 h. The reducing agents were added every 30 minutes for 4 h. Then, the composites were cleaned in 1 M H_2SO_4 aqueous solution at 60 °C for 40 minutes, D.I. water at 70 °C for 40 minutes, 1 M H_2SO_4 aqueous solution at 60 °C for 40 minutes, followed by cleaning in D.I. water at 40 °C for 40 minutes. If the resistance is greater than 10-15 Ω/cm , the entire procedure should be done up to two times. After all the process was done, the membranes were placed in 1 M LiCl solution overnight in order to replace protons with lithium ions. The platinum layers were successfully plated on to the surfaces of the membranes without cracks.

[00198] The obtained IPMCs were cut into 0.5×2.5 cm rectangular shapes for further characterizations. The measured electrode surface resistance of the prepared IPMCs after each plating step is summarized in Table 2. As mentioned earlier, solution casted Nafion, NPI-6, and NPI-12 show relatively high surface resistance that ranges 4.7-20.2 Ω /cm while NPI-18, NPI-30, and Nafion 117 show values less than 2 Ω /cm, which are reasonable compared to previous work (Palmre et al. (2014) *Scientific Reports* 4: 6176). The photographic images of NPI-18 (**2A**), NPI-30 (**2B**), and Nafion 117 (**2C**) IPMCs are shown in **FIG. 2A-C**.

TABLE 2.

Samples	1 st Primary plating (Ω /cm)	2 nd Primary plating (Ω /cm)	3 rd Primary plating (Ω /cm)	Secondary plating (Ω /cm)
Nafion (solution casted)	33.8-45.7	21.0-28.0	14.1-18.8	11.1-20.2
NPI-6	11.1-14.2	10.8-13.3	8.1-9.2	4.7-7.7
NPI-12	13.2-15.1	11.1-12.9	8.8-9.4	5.6-8.2
NPI-18	3.3-5.1	2.2-2.5	1.6-1.9	1.1-1.5
NPI-30	3.3-5.2	2.2-2.6	1.5-1.8	0.9-1.6
Nafion 117	4.2-5.3	2.8-3.1	1.6-1.9	1.3-1.7

4. FT-IR SPECTRA

[00199] FT-IR spectra were obtained using IRTracer-100 (Shimadzu) equipped with an attenuated total reflectance (ATR) accessory (MIRacle™, PIKE Technologies) to characterize the chemical structures of membranes.

[00200] The samples were characterized by Fourier Transform Infrared Spectroscopy (FT-IR) after the imidization at 180 °C for 12 h in vacuum to confirm that they were successfully imidized and both PI and Nafion components are in the blend membranes. **FIG. 3A** and **FIG. 3B**

show spectra of PAA membrane and PI membrane before and after thermal imidization, which were compared as reference. Untreated PAA membrane showed peaks at 1714 cm^{-1} (C=O stretching, carboxylic), 1657 cm^{-1} (C=O stretching, amide), and 1540 cm^{-1} (N-H bending) (Kumar et al. (2016) *Data in Brief* 7: 123-128). After thermal imidization, 1714 cm^{-1} (C=O stretching, carboxylic) and 1657 cm^{-1} (C=O stretching, amide) were replaced with 1774 cm^{-1} (C=O stretching, asymmetric) and 1712 cm^{-1} (C=O stretching, symmetric) which are characteristic to PI. Moreover, other peaks at 1453 cm^{-1} (C=C stretching), 1367 cm^{-1} (C-N stretching, imide), and 1163 cm^{-1} (imide ring deformation) appeared, which indicated the successful thermal imidization (Kumar et al. (2016) *Data in Brief* 7: 123-128).

[00201] As shown in **FIG. 4A** and **FIG. 4B**, the blend membranes NPI-6, NPI-12, NPI-18, and NPI-30 showed peaks at 1780 cm^{-1} (C=O stretching, asymmetric), 1730 cm^{-1} (C=O stretching, symmetric), 1502 cm^{-1} (C=C stretching), and 1383 cm^{-1} (C-N stretching, imide). These peaks are characteristic to PI, confirming that the thermal imidization was successful and that PI is present in the blend membranes. Also, peaks at 1205 cm^{-1} (C-F stretching, asymmetric) and 1144 cm^{-1} (C-F stretching, symmetric) which are characteristic to Nafion were shown in NPI-6, NPI-12, NPI-18, and NPI-30, confirming the presence of Nafion in the blend membranes (Laporta et al. (1999) *Physical Chemistry Chemical Physics* 1: 4619-4628). From FT-IR results, we confirmed the success of thermal imidization as well as incorporation of both polymers, PI and Nafion, in the blend membranes.

5. THERMAL PROPERTIES

[00202] Thermal properties were investigated by TGA (Q500, TA instruments). The characterization was done at room temperature under nitrogen atmosphere, heating rate of $10\text{ }^{\circ}\text{C}/\text{min}$. As shown in **FIG. 5A** and **FIG. 5B**, PI membrane is stable at temperatures up to $550\text{ }^{\circ}\text{C}$. It shows a distinguishable thermal degradation around $550 - 600\text{ }^{\circ}\text{C}$. Also, the TGA derivative curve shows a broad transition peak at $315\text{ }^{\circ}\text{C}$ and a sharp transition peak at $572\text{ }^{\circ}\text{C}$, with a total weight loss of 38 % after decomposition. Nafion membrane shows major weight loss stages around $325-380\text{ }^{\circ}\text{C}$ and $420-570\text{ }^{\circ}\text{C}$. The TGA derivative curve shows two sharp transition peaks at 360 and $462\text{ }^{\circ}\text{C}$, with a total weight loss of 92% after decomposition.

[00203] Blend membranes NPI-6, NPI-12, NPI-18, and NPI-30 show two major weight loss stages around $325-380$, $380-420$, and a small third decomposition around $420-570\text{ }^{\circ}\text{C}$. The third

decomposition increases as the content of PI increases. Differences in transition points compared to Nafion are not observable for TGA curve. In addition to sharp transition peaks at 360 and 462 °C, which are characteristic to Nafion, TGA derivative curve of blend membranes show broad transition peak at 315 °C and decomposition of PI as a shoulder at 565 °C. The total weight loss is 81 % for NPI-6 and NPI-12, and 77 % for NPI-18 and NPI-30. The TGA and TGA derivative curve of blend samples confirms the presence of both components, Nafion and PI, in the blends.

6. MECHANICAL PROPERTIES OF PREPARED MEMBRANES

[00204] A dynamic mechanical analysis using the Pyris Diamond DMA was conducted on Nafion 117, NPI-6, NPI-12, and PI membranes. DMA was not measured on NPI-18 and NPI-30 due to the stiffness of the membranes. DMA is important to understand the viscoelastic properties of the materials. The samples were cut into 0.5 cm × 2.5 cm. DMA was setup in tension, and they were oscillated at different frequencies (0.01, 0.02, 0.05, 0.1, 0.2, 0.5, 1, 2, 5, 10, 20 Hz). Measured storage modulus, loss modulus, and tangent delta are shown in **FIG. 6A-C**, respectively. To clearly show the increasing and decreasing trends, storage modulus, loss modulus, and $\tan \delta$ of samples at 10 Hz are shown in **FIG. 6D**. At 10 Hz, as the content of PI in the membrane increased, the storage modulus (E') increased from 0.1563 (Nafion) to 0.5723 (NPI-6) to 1.619 (NPI-12) to 2.430 GPa (PI) (**FIG. 6A**). In the case of loss modulus (E''), there were only minor changes: 0.0432 (Nafion), 0.1252 (NPI-6), 0.2343 (NPI-12), and 0.1366 GPa (PI) (**FIG. 6B**). Therefore, damping properties ($\tan \delta = E''/E'$) (Chen et al. (2005) *Journal of Biomechanics* **38**: 959-963; Bashaiwoldu et al. (2004) *International Journal of Pharmaceutics* **269**: 329-342; Xie et al. (2004) *Journal of Macromolecular Science B* **43**: 805-817) decreased from 0.2799 (Nafion) to 0.2191 (NPI-6) to 0.1448 (NPI-12) to 0.0562 (PI) as the content of PI increased (**FIG. 6C**). The trends in E' , E'' , and $\tan \delta$ as a function of PI content were clearly shown in **FIG. 6D**. Without wishing to be bound by theory, the storage modulus, which represents the elastic property of the material, can be increased by increasing the content of PI. Meanwhile, loss modulus, which represents the viscous property, was not affected significantly up to 12% of PI, which result in the decrease in damping property. Although limited, selective tuning in the mechanical properties can be achieved by this simple physical blending. It should be noted that the DMA analysis of the blends with higher PI contents was not conducted due the brittleness of the samples.

7. CROSS-SECTION MORPHOLOGY AND MEMBRANE THICKNESS

[00205] The cross-section morphology and thickness of the IPMCs were measured using SEM (TM3030, Hitachi) at 15 kV as shown in **FIG. 7A-D**. The samples were molded with epoxy and carefully polished, and then sputter-coated with Pt. After fabricating IPMCs based on solution casted Nafion, NPI-6, NPI-12, NPI-18, and NPI-30, surface electrode resistance was measured using two-point probe method. As shown in Table 2, solution casted Nafion, NPI-6, and NPI-12 showed high surface electrode resistance (4.7-20.2 Ω/cm). Since higher surface electrode resistance generates lower actuation capability in the IPMCs which was experimentally demonstrated (Shahinpoor and Kim (2000) *Smart Mater. Struct.* **9**: 543-551), actuation testing was only done on NPI-18 and NPI-30 IPMC actuators which resulted in surface resistance (1.1-1.5 Ω/cm) less than 2.0 Ω/cm after secondary electroless plating, which is appropriate value compared to our previous work. Since the surface resistance of solution casted Nafion – based IPMC was too high, we prepared Nafion-117 – based IPMC that resulted in surface resistance (1.3-1.7 Ω/cm) less than 2.0 Ω/cm to compare actuation performance of Nafion 117 and NPI-18 – based IPMCs.

[00206] The cross-sectional morphology of NPI-18 – based IPMC actuator was characterized with SEM image as shown in **FIG. 7D**. The platinum electrode is successfully plated onto the surface of the membrane evenly, without any defects like cracks or delamination. The thickness of the electrode is consistent throughout the surface of the electrode with a value of 10 μm . For NPI-30, SEM image was not taken since the surface electrode resistance was similar to NPI-18, which was lower than 2.0 Ω/cm .

8. VOLTAGE, CURRENT, DISPLACEMENT RESPONSES, AND BENDING STRAIN OF IPMCs

[00207] The electromechanical responses including displacement and blocking force of the prepared IPMCs were measured by a laser displacement sensor (optoNCDT-1401, Micro-Epsilon) and a load cell (GSO-30, Transducer Techniques) with a sample size of 0.5×2.5 cm in the test setup composed of a signal generator (FG-7002C, EZ digital), a power amplifier (LVC-608, AE Techtron), a DC power supply (CPS250, Tektronix), and a DAQ (SCB-68, National Instruments). IPMC was clamped in a cantilever configuration in water with a free-length of 2.2

cm. The displacement was monitored at a position of 2.0 cm away from the clamp contacts. The voltage, current and displacement (or blocking force) responses were recorded using data acquisition system (LabView 8, National Instruments).

[00208] Displacement responses of Nafion 117, NPI-18, NPI-30 IPMC actuators were measured at 0.1, 0.5, and 1 Hz. A displacement laser sensor kept track of the displacement at the tip while the voltage at the clamp was sensed by the circuit. Measured voltage, current, corresponding displacement responses, and bending strain of Nafion 117, NPI-18, and NPI-30 – based IPMC at $\pm 3\text{V AC}$ (square wave input) at frequencies 0.1, 0.5, and 1 Hz are shown in **FIG. 8A-D**. The bending strain (ϵ) was converted from displacement (δ) using the relation of

$\epsilon \cong \frac{\delta t}{L^2 + \delta^2}$, where t is the thickness of the IPMC and L is the free length.

[00209] For **FIG. 8A**, only the results of Nafion 117 and NPI-18 actuators were shown. In the case of NPI-30, due to the experimental error, number of cycles of 0.1 Hz were not the same as Nafion 117 and NPI-18. The displacements of Nafion 117 and NPI-18 actuators at 0.1 Hz were 5.3 and 5.9 mm, and strains were 0.21 and 0.28 %, respectively. Superimposed image of video captures of NPI-18 actuator at 0.1 Hz is also included. The actuators show similar displacement performances up to 2.8 s. While NPI-18 shows a bounce-back effect, which does not maintain the maximum displacement but bounces back before bending to the opposite direction, from 2.8 to 4.7 s where displacement changes by 1.3 mm, which is not the case with the pristine Nafion 117. This result is in accordance with the DMA analysis. Without wishing to be bound by theory, the increased elasticity may be responsible for the bounce-back effect. The displacement was found to be 1.6 mm, which was lower than Nafion 117 and NPI-18, due to the stiffness of the blend and that the bounce-back effect was only observed at low frequency (0.1 Hz) but not at high frequencies (0.5 and 1 Hz).

[00210] At 0.5 Hz, as shown in **FIG. 8B**, the displacement of Nafion 117 and NPI-18 actuators were almost same (3.8 mm), and strains were 0.17 and 0.28 %, respectively. The displacement of NPI-30 actuator was 1.1 mm and the strain was 0.06 %, which were lowest among the actuators due to the stiffness of the actuator. At 1.0 Hz, as shown in **FIG. 8C**, the displacement of Nafion 117 and NPI-18 actuators were 1.3 and 2.0 mm, and strains were 0.07 and 0.14 %, respectively. The displacement of NPI-30 actuator was 1.1 mm and the strain was 0.06 %, which were lowest among actuators.

[00211] The displacement decreases at 1.0 Hz compared to 0.5 Hz and the displacement responses are slower compared to 0.5 Hz. These effects are thought to be due to the limited charging time at higher frequency (Palmre et al. (2014) *Scientific Reports* 4: 6176). As the actuating frequency increases, the charging time for the hydrated cations to move toward the anode becomes shorter, resulting in the decrease of both displacement and strain. From the displacement results, we could see comparable electromechanical performance even with significant amount of 18 wt% of PI in the actuator.

[00212] The photographic images of prepared IPMC actuators at maximum displacement with/without applying voltage (± 3 V, AC) under varied frequency (0.1, 0.5, and 1.0 Hz) are shown in **FIG. 9A-C**. It shows that the NPI-18 IPMC actuator demonstrated the similar displacement range compared to Nafion 117 IPMC actuator. NPI-30 IPMC actuator showed lowest degree of deformation among the actuators. The photographic images correspond with the displacement performances.

9. BLOCKING FORCES OF IPMCs

[00213] The blocking force, which represents the electromechanical force formed at the tip of IPMC at zero displacement, was measured under driving voltage of 3V, DC. **FIG. 10** shows the typical blocking force responses measured in time for Nafion 117 and NPI-18 actuators. The highest blocking forces of Nafion 117 and NPI-18 were measured to 6.86 mN at 1.84 s and 5.93 mN at 1.47 s. The blocking for decrease of NPI-18 is likely to come from the increased stiffness of PI incorporated in Nafion. The blocking force is decreased by less than 15 % and the response time is also decreased by 20 %. While obtaining faster response time of actuators by blending PI is important, the decrease in blocking force that accompanies should also be considered in the fabrication of IPMC actuators.

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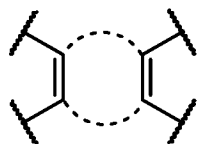
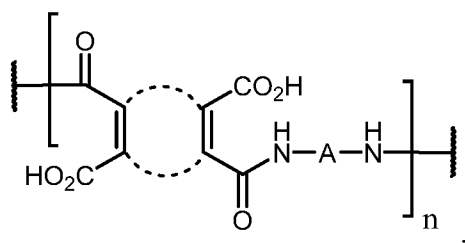
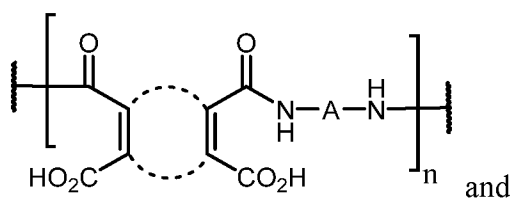
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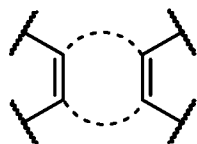
[00251] It will be apparent to those skilled in the art that various modifications and variations can be made in the present invention without departing from the scope or spirit of the invention. Other embodiments of the invention will be apparent to those skilled in the art from consideration of the specification and practice of the invention disclosed herein. It is intended that the specification and examples be considered as exemplary only, with a true scope and spirit of the invention being indicated by the following claims.

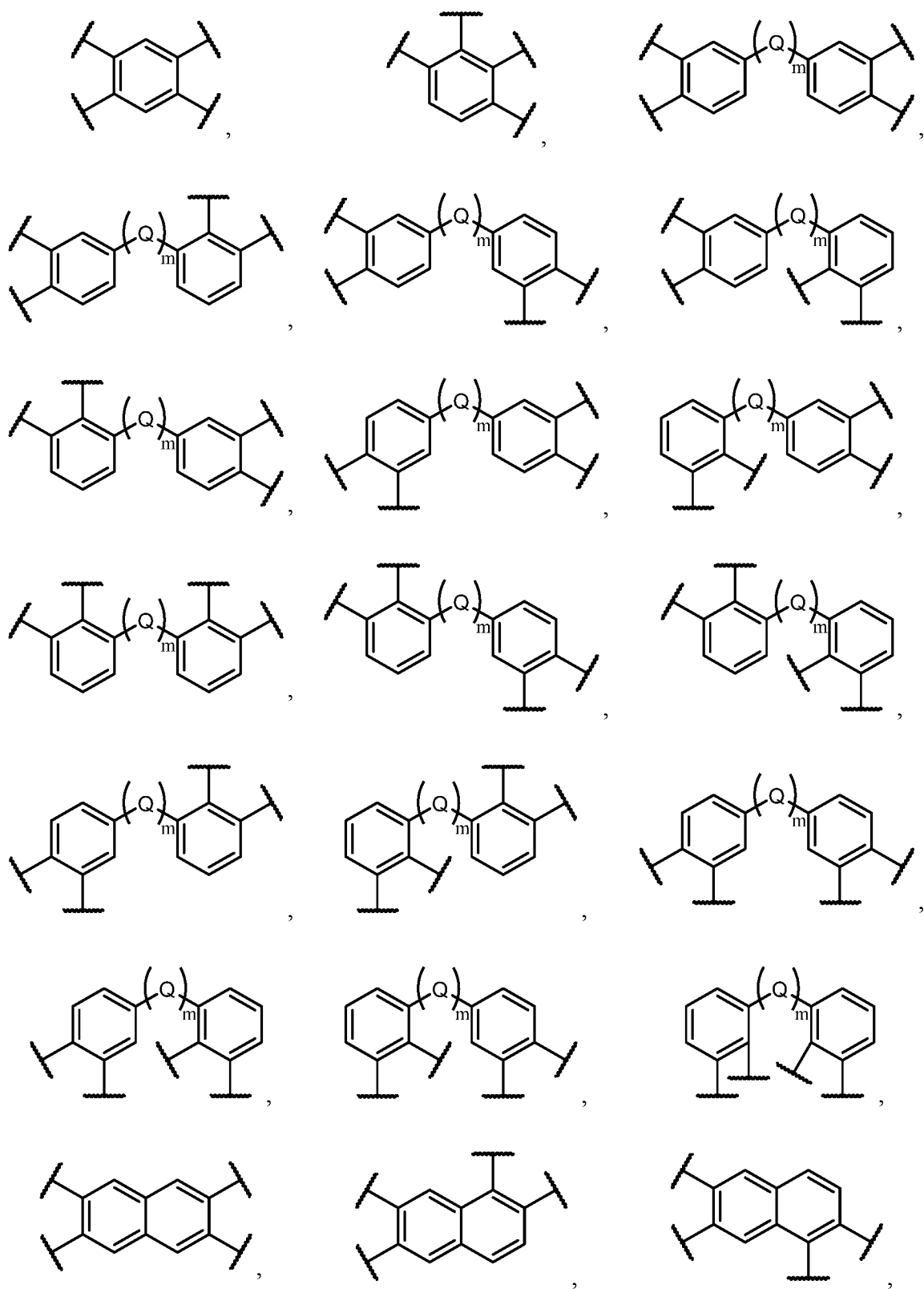
CLAIMS

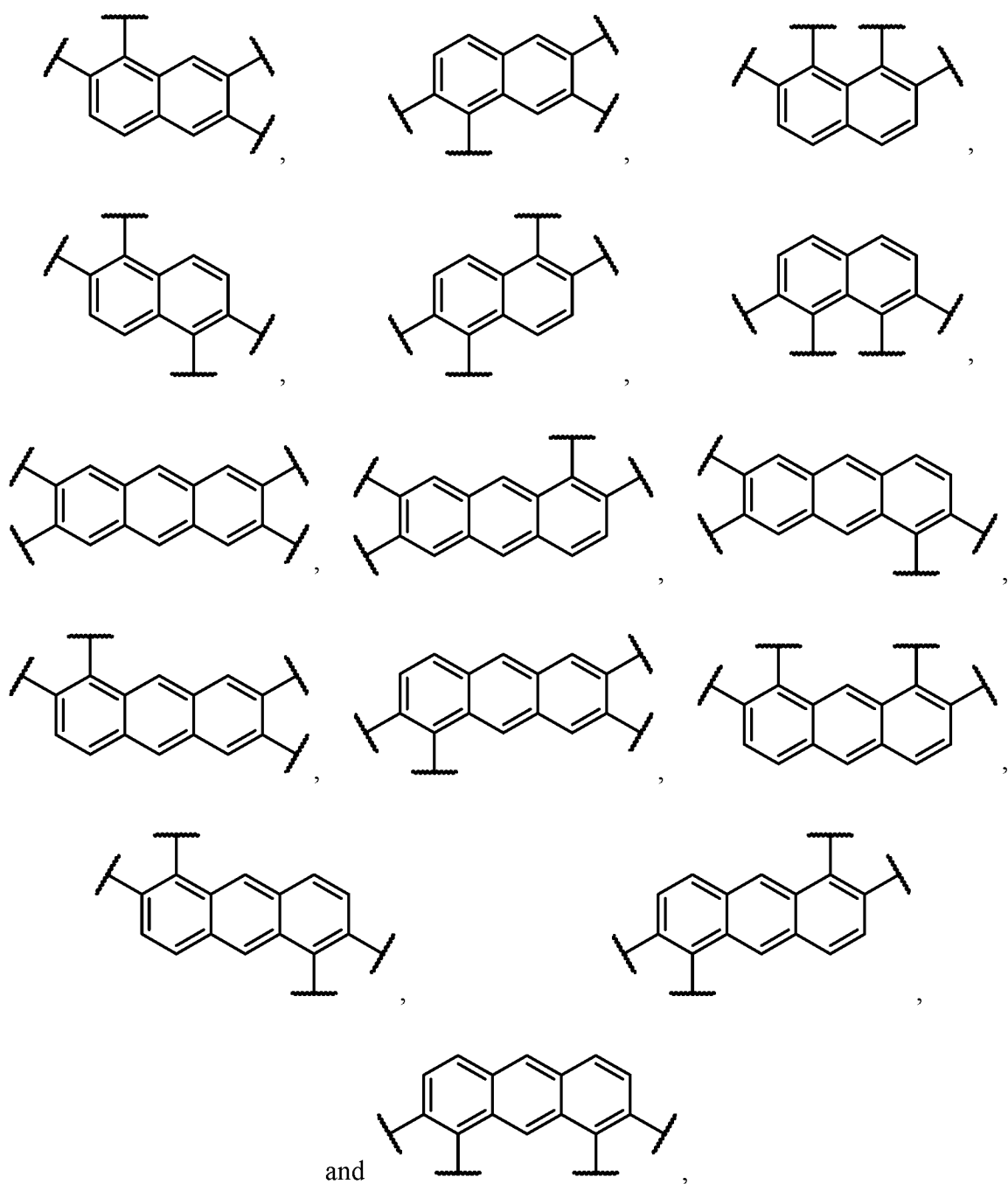
What is claimed is:

1. A method of making a polyimide blend, the method comprising:
 - a) mixing an ionic polymer selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion, and a poly(amic acid) comprising at least one residue having a structure represented by a formula selected from:



wherein  comprises a structure represented by a formula selected from:

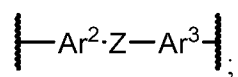




wherein n is an integer greater than 1;

wherein m is 0 or 1;

wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:



wherein Z, when present, is selected from O, NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO, and SO_2 ;

wherein each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl;

wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy;

wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy;

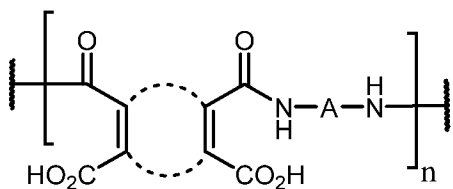
wherein Q, when present, is selected from O, NR^1 , SO, SO_2 , $\text{C}(\text{O})$, and $\text{CR}^{2a}\text{R}^{2b}$; and

wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl,

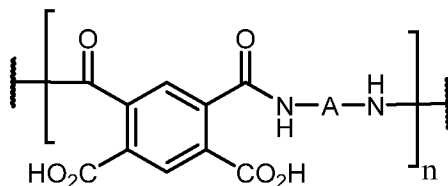
thereby making a poly(amic acid) blend; and

b) cyclizing the poly(amic acid) blend.

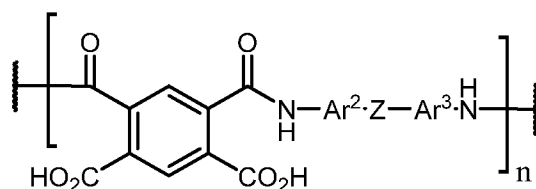
2. The method of claim 1, wherein the ionic polymer is Nafion.
3. The method of claim 1, wherein n is greater than 10,000.
4. The method of claim 1, wherein the poly(amic acid) comprises at least one residue having a structure represented by a formula:



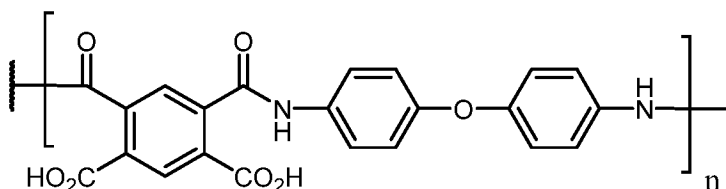
5. The method of claim 1, wherein the poly(amic acid) comprises at least one residue having a structure represented by a formula:



6. The method of claim 1, wherein the poly(amic acid) comprises at least one residue having a structure:

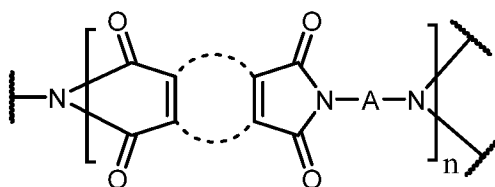


7. The method of claim 1, wherein the poly(amic acid) comprises at least one residue having a structure:

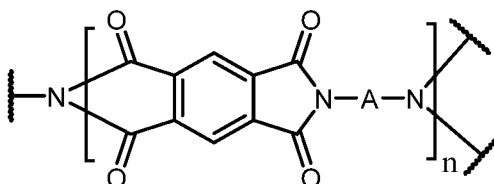


8. The method of claim 1, wherein the poly(amic acid) is present in solution.
9. The method of claim 7, wherein the poly(amic acid) solution is present in an amount of from about 20 wt% to about 50 wt%.
10. The method of claim 7, wherein the poly(amic acid) solution comprises an aprotic polar solvent.
11. The method of claim 10, wherein the aprotic polar solvent is selected from N,N-dimethylformamide and N-methyl-2-pyrrolidone.

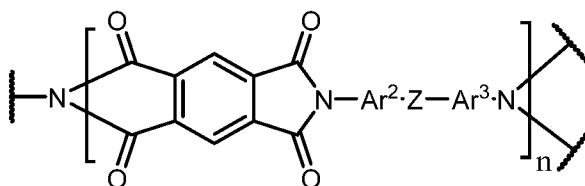
12. The method of claim 10, wherein the aprotic polar solvent is present in an amount of from about 95 wt% to about 99 wt% of the poly(amic acid) solution.
13. The method of claim 10, wherein the aprotic polar solvent is present in an amount of about 95 wt% of the poly(amic acid) solution.
14. The method of claim 1, wherein the ionic polymer is present in solution and the poly(amic acid) is present in solution, and wherein the ionic polymer and the poly(amic acid) together have a concentration of from about 0.01 g/mL to about 6 g/mL.
15. The method of claim 1, wherein the ionic polymer is present in solution and the poly(amic acid) is present in solution, and wherein the ionic polymer and the poly(amic acid) together have a concentration of from about 0.03 g/mL to about 6 g/mL.
16. The method of claim 1, wherein mixing is blending.
17. The method of claim 1, wherein mixing is solution-casting.
18. The method of claim 17, wherein solution-casting is performed at a temperature of from about 50 °C to about 100 °C.
19. The method of claim 17, wherein solution-casting is performed at a temperature of from about 40 °C to about 90 °C.
20. The method of claim 1, wherein cyclizing is via heat.
21. The method of claim 20, wherein the heat is applied at a temperature of from about 180 °C to about 250 °C.
22. The method of claim 20, wherein the heat is applied for from about 12 h to about 36 h.
23. The method of claim 20, wherein the heat is applied under vacuum, nitrogen, or helium.
24. The method of claim 1, wherein the polyimide blend comprises a polyimide comprising at least one residue having a structure represented by a formula:



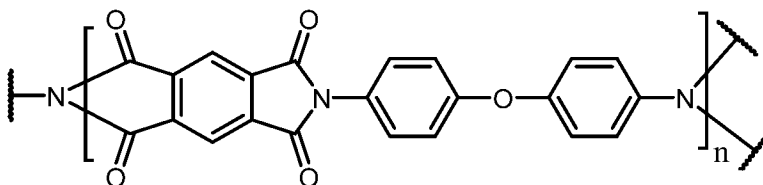
25. The method of claim 24, wherein the polyimide comprises at least one residue having a structure represented by a formula:



26. The method of claim 24, wherein the polyimide comprises at least one residue having a structure represented by a formula:



27. The method of claim 24, wherein the polyimide comprises at least one residue having a structure:

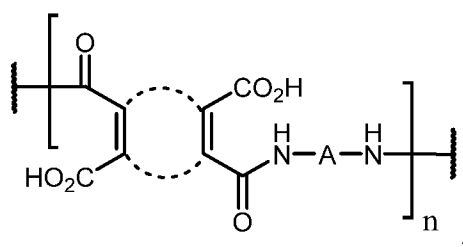
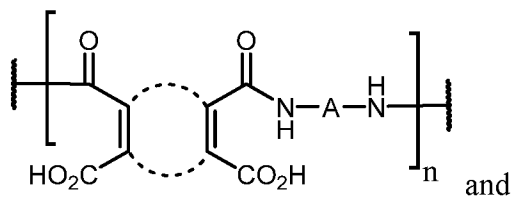


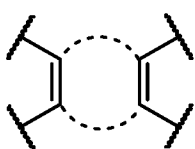
28. The method of claim 24, wherein the polyimide is present in an amount of from about 6 wt% to about 30 wt%.
29. The method of claim 24, wherein the polyimide is present in an amount of from about 18 wt% to about 20 wt%.

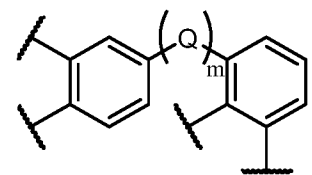
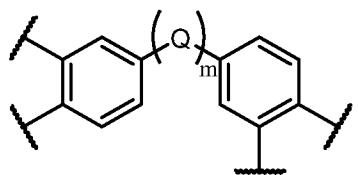
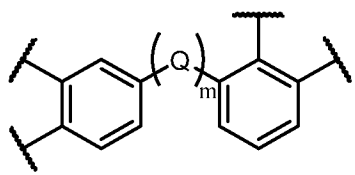
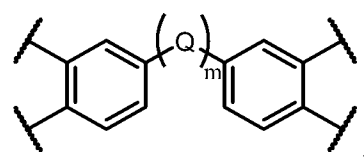
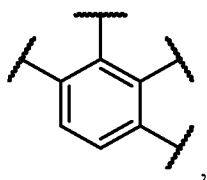
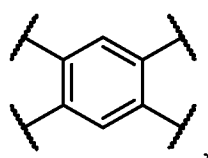
30. The method of claim 1, further comprising plating a metal electrode onto the polyimide blend.
31. The method of claim 30, wherein the metal is Pt.
32. The method of claim 30, further comprising modifying at least one surface of a polymeric membrane with the polyimide blend.
33. The method of claim 32, wherein modifying is via a bond.
34. The method of claim 32, wherein modifying comprises coating the surface with the polyimide blend.
35. The method of claim 32, wherein modifying comprises exposing the surface to a light source.
36. The method of claim 1, further comprising modifying at least one surface of a polymeric membrane with the polyimide blend.
37. The method of claim 36, wherein modifying is via covalent bonding.
38. The method of claim 36, wherein modifying comprises coating the surface with the polyimide blend.
39. The method of claim 36, wherein modifying comprises exposing the surface to a light source.
40. A poly(amic acid) blend comprising:
 - a) an ionic polymer selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-

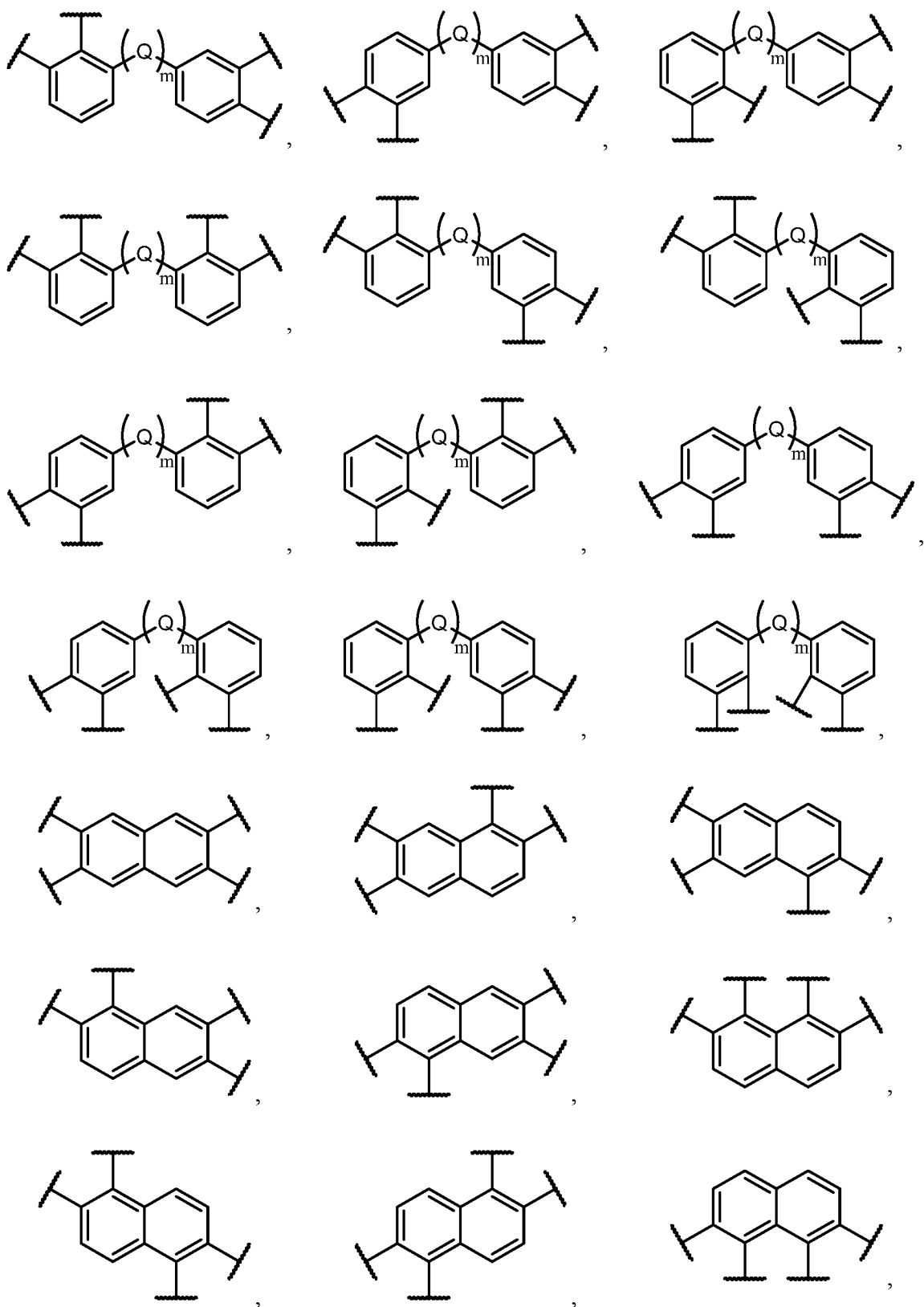
hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion; and

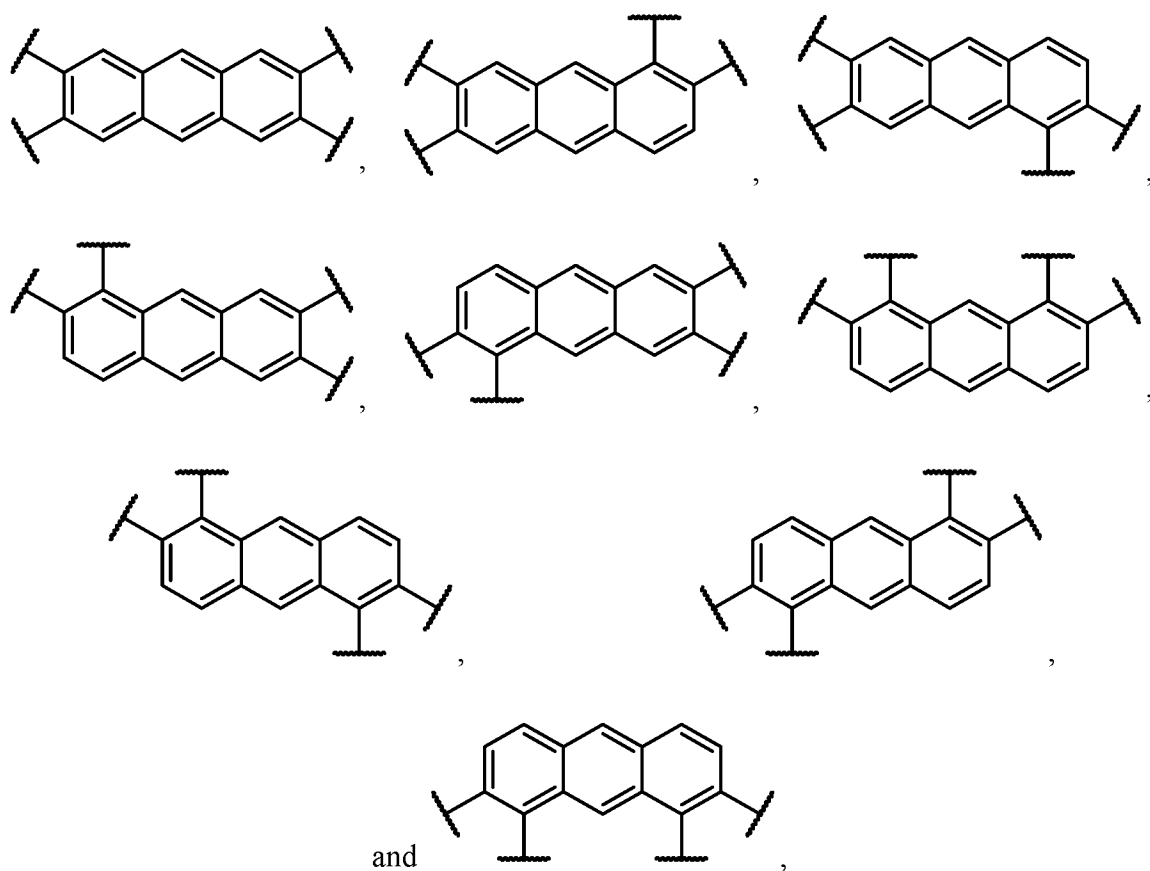
- b) a poly(amic acid) comprising at least one residue having a structure represented by a formula selected from:



wherein  comprises a structure represented by a formula selected from:



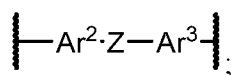




wherein n is an integer greater than 1;

wherein m is 0 or 1;

wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:



wherein Z , when present, is selected from O , NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO , and SO_2 ;

wherein each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl;

wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups

independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy;

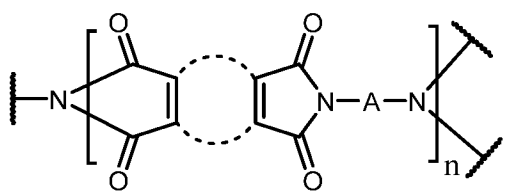
wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy;

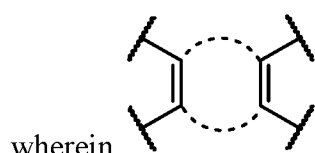
wherein Q, when present, is selected from O, NR^1 , SO, SO_2 , $\text{C}(\text{O})$, and $\text{CR}^{2a}\text{R}^{2b}$; and

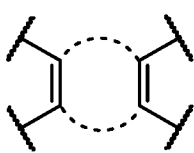
wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl.

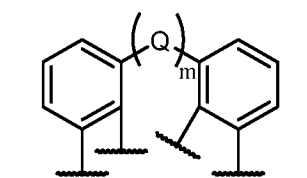
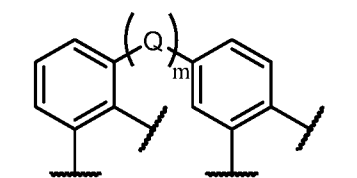
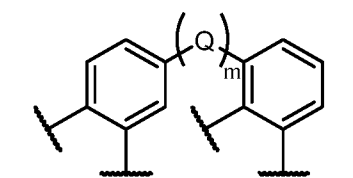
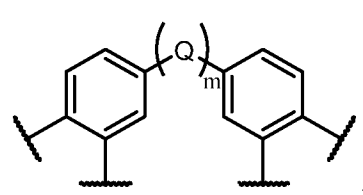
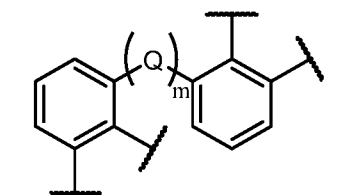
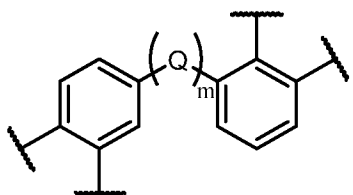
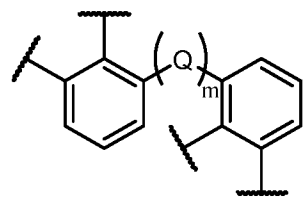
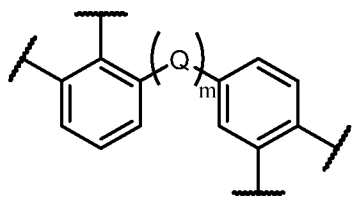
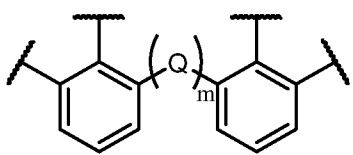
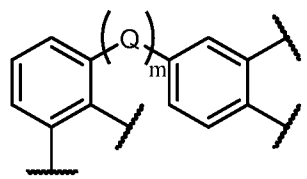
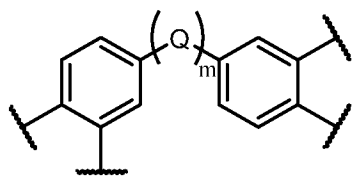
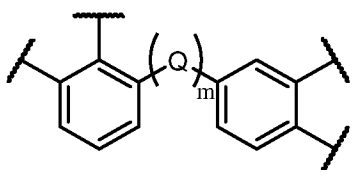
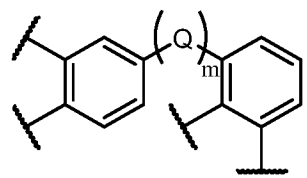
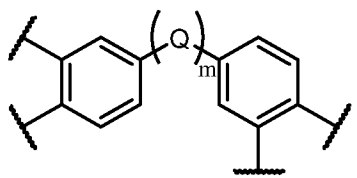
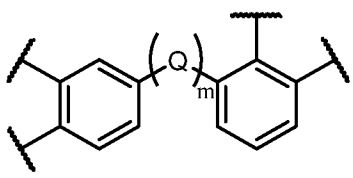
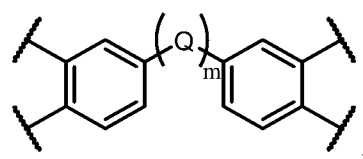
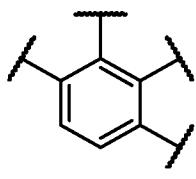
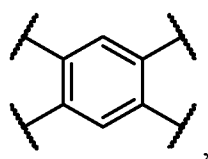
41. A polyimide blend comprising:

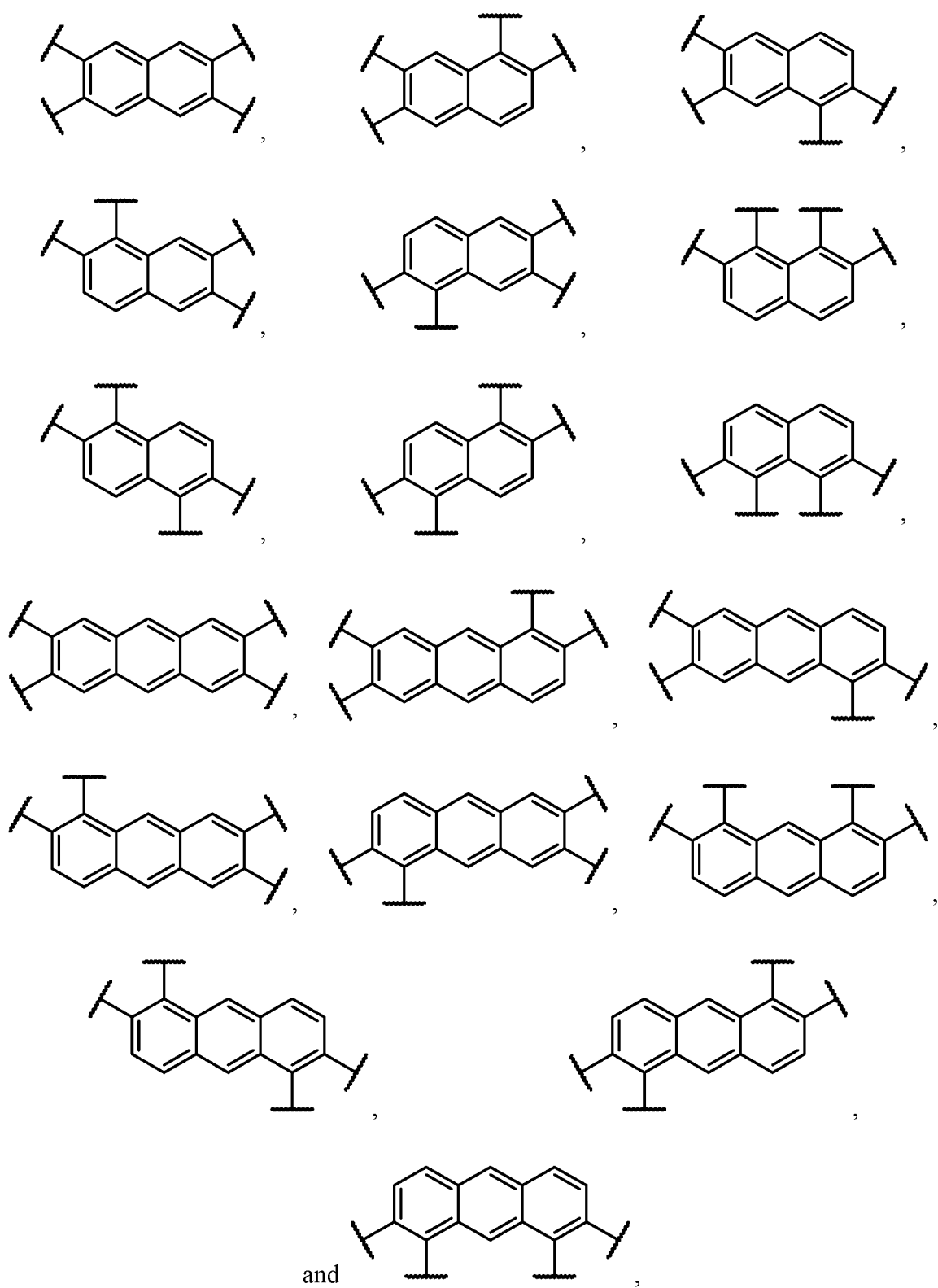
- a) an ionic polymer selected from a perfluorinated ionomer membrane, a poly(acrylic acid) salt, sulfonated polystyrene, sulfonated poly(arylene ether sulfone), sulfonated poly(arylene thioether sulfone), cross-linked poly(styrene-*ran*-ethylene), sulfonated poly(styrene-*b*-ethylene-*co*-butylene-*b*-styrene), poly(fluoroalkyl methacrylate-*co*-acrylic acid), poly(fluoroalkyl methacrylate-*co*-2-acylamido-2-methyl-1-propanesulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid), poly(fluoroalkyl methacrylate-*co*-sulfonic acid-*co*-2-hydroxyethyl methacrylate), poly(vinylidene-*g*-sulfonated N-ethylenecarbazole), poly(vinylidene fluoride-*co*-hexafluoropropylene), poly(ethylene-*co*-tetrafluoroethylene), and Nafion; and
- b) a polyimide comprising at least one residue having a structure represented by a formula:





wherein  comprises a structure represented by a formula selected from:

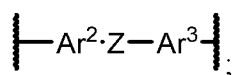




wherein n is an integer greater than 1;

wherein m is 0 or 1;

wherein A is selected from $-\text{Ar}^1-$ and a structure represented by a formula:



wherein Z, when present, is selected from O, NR^3 , $\text{CR}^{4a}\text{R}^{4b}$, CO, and SO_2 ;

wherein each of R^3 , R^{4a} , and R^{4b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl;

wherein Ar^1 , when present, is selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy;

wherein each of Ar^2 and Ar^3 , when present, is independently selected from aryl, 5-membered heteroaryl, and 6-membered heteroaryl and substituted with 0, 1, 2, or 3 groups independently selected from halogen, $-\text{OH}$, $-\text{CN}$, $-\text{NH}_2$, C1-C4 alkyl, C1-C4 haloalkyl, and C1-C4 alkoxy;

wherein Q, when present, is selected from O, NR^1 , SO, SO_2 , $\text{C}(\text{O})$, and $\text{CR}^{2a}\text{R}^{2b}$;
and

wherein each of R^1 , R^{2a} , and R^{2b} , when present, is independently selected from hydrogen, C1-C4 alkyl, and C1-C4 haloalkyl.

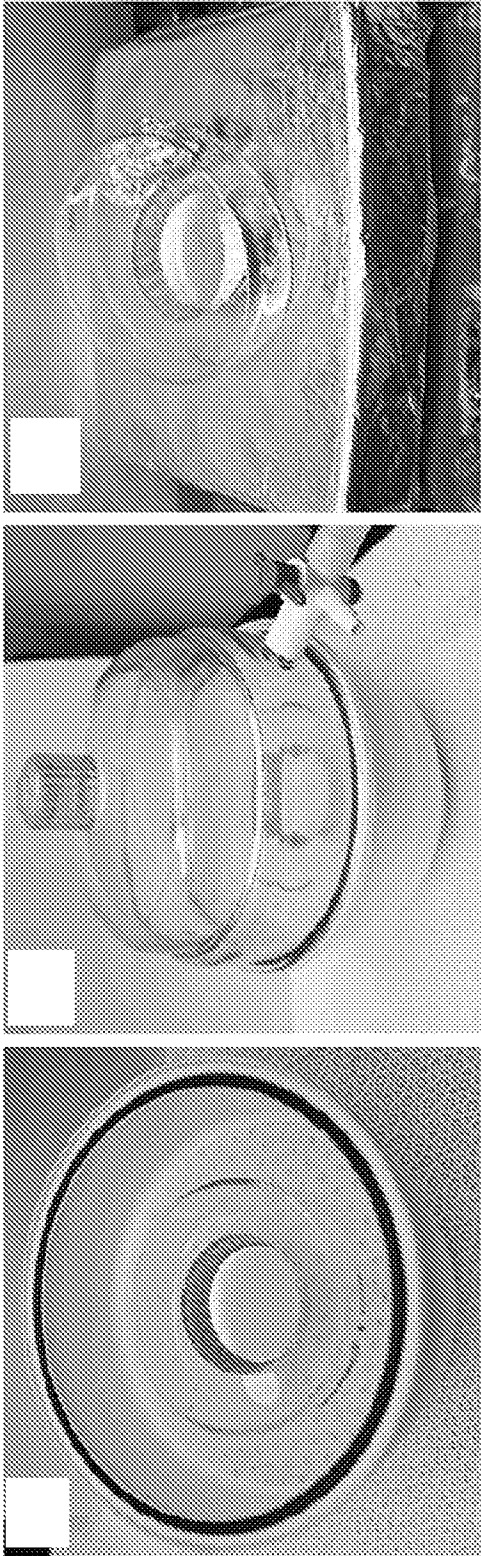


FIG. 1A

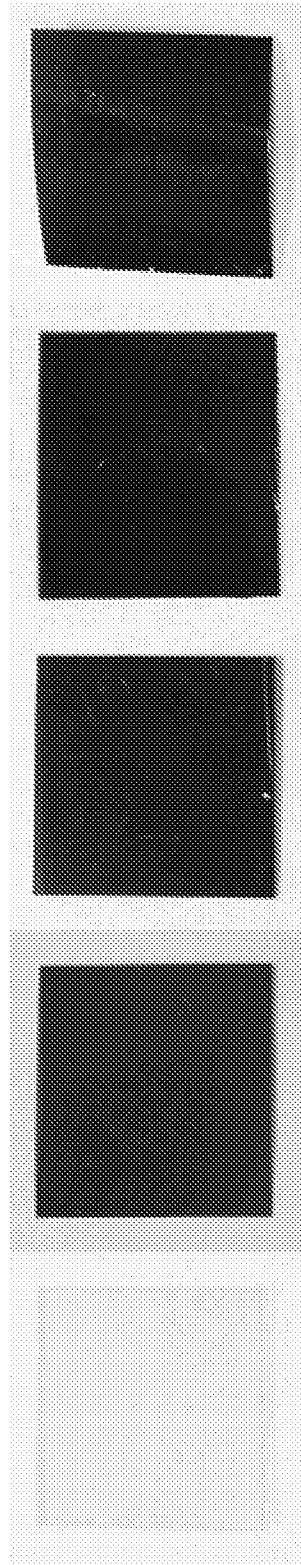


FIG. 1B

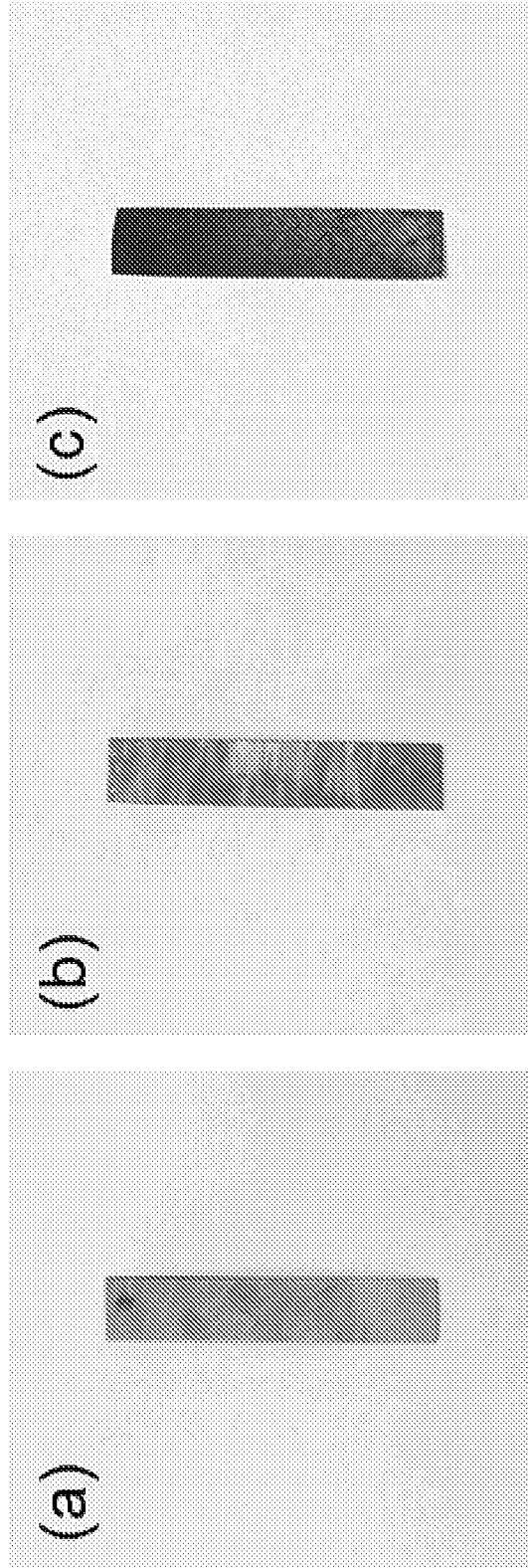


FIG. 2C

FIG. 2B

FIG. 2A

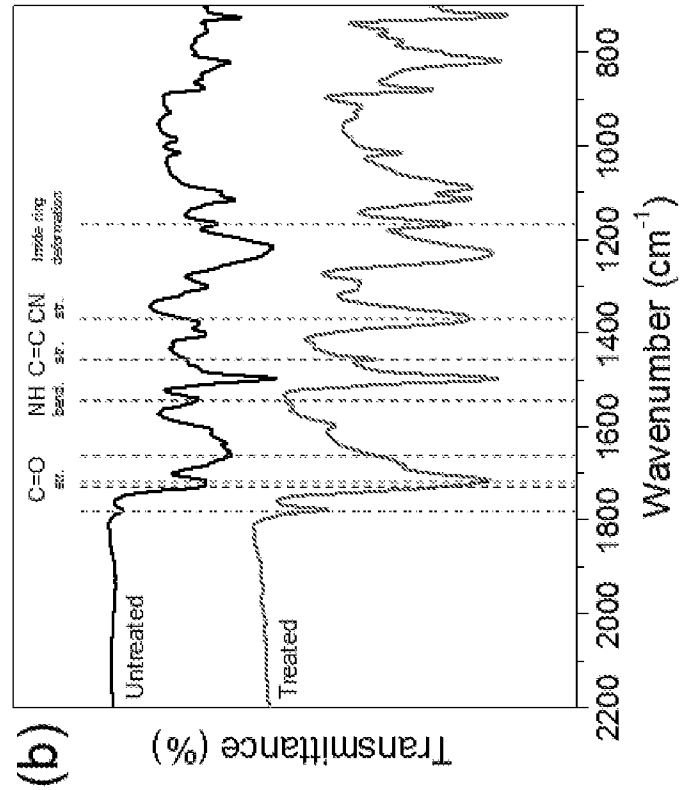


FIG. 3B

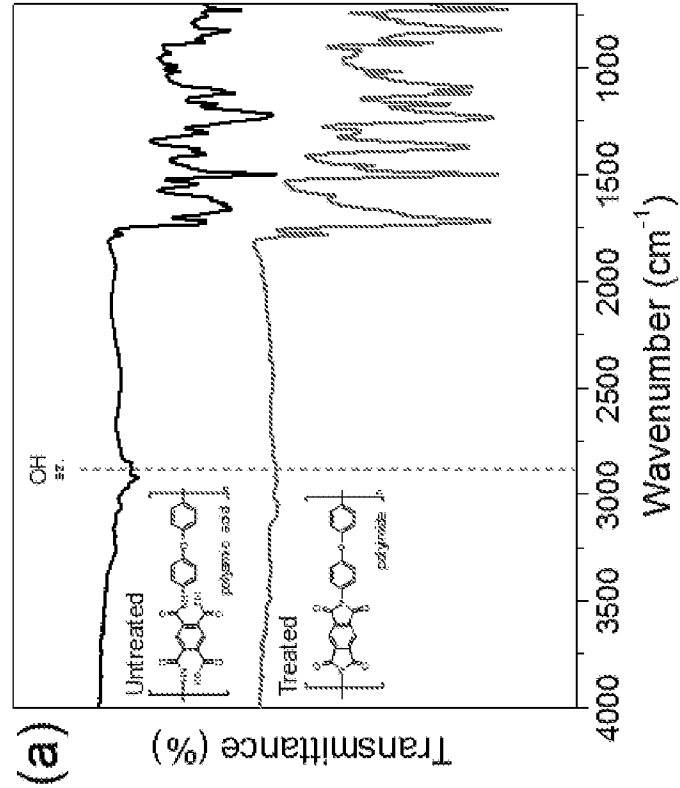


FIG. 3A

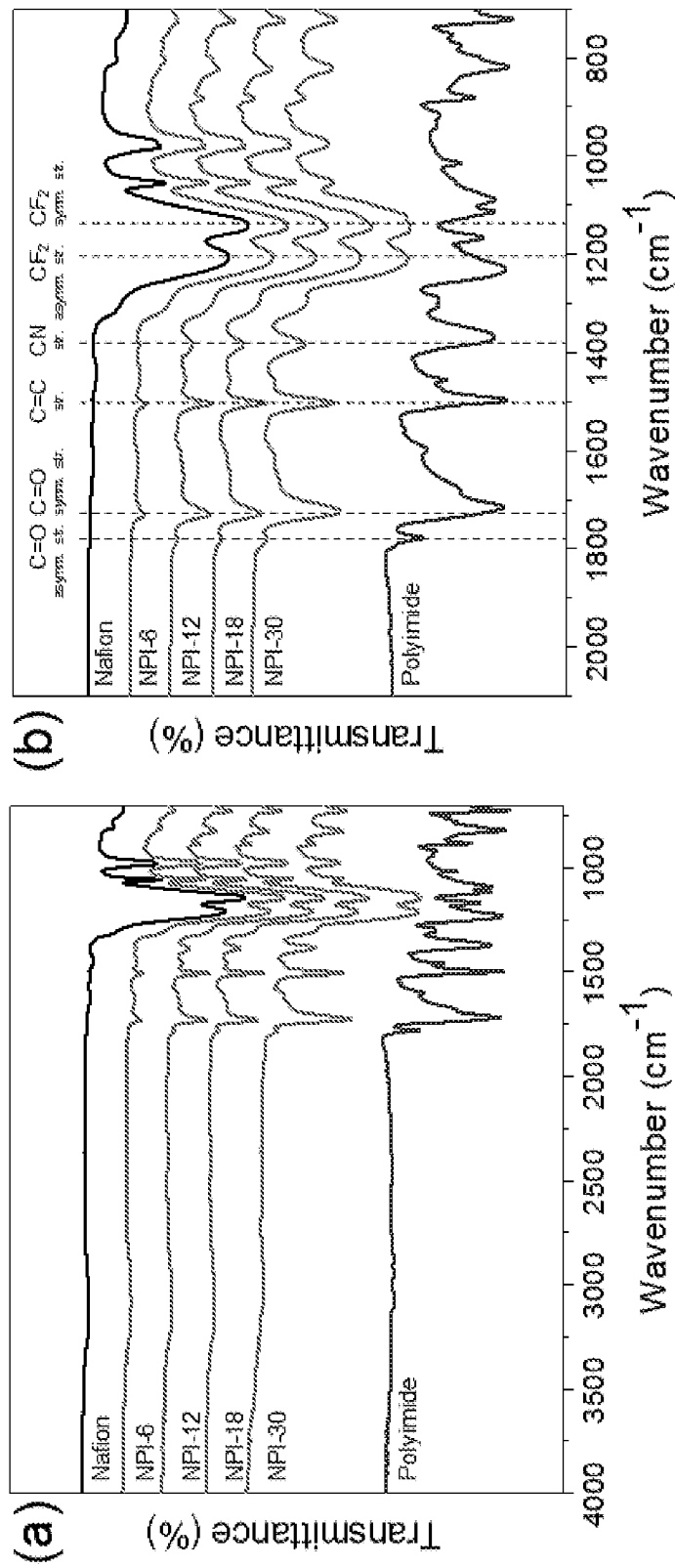


FIG. 4A

FIG. 4B

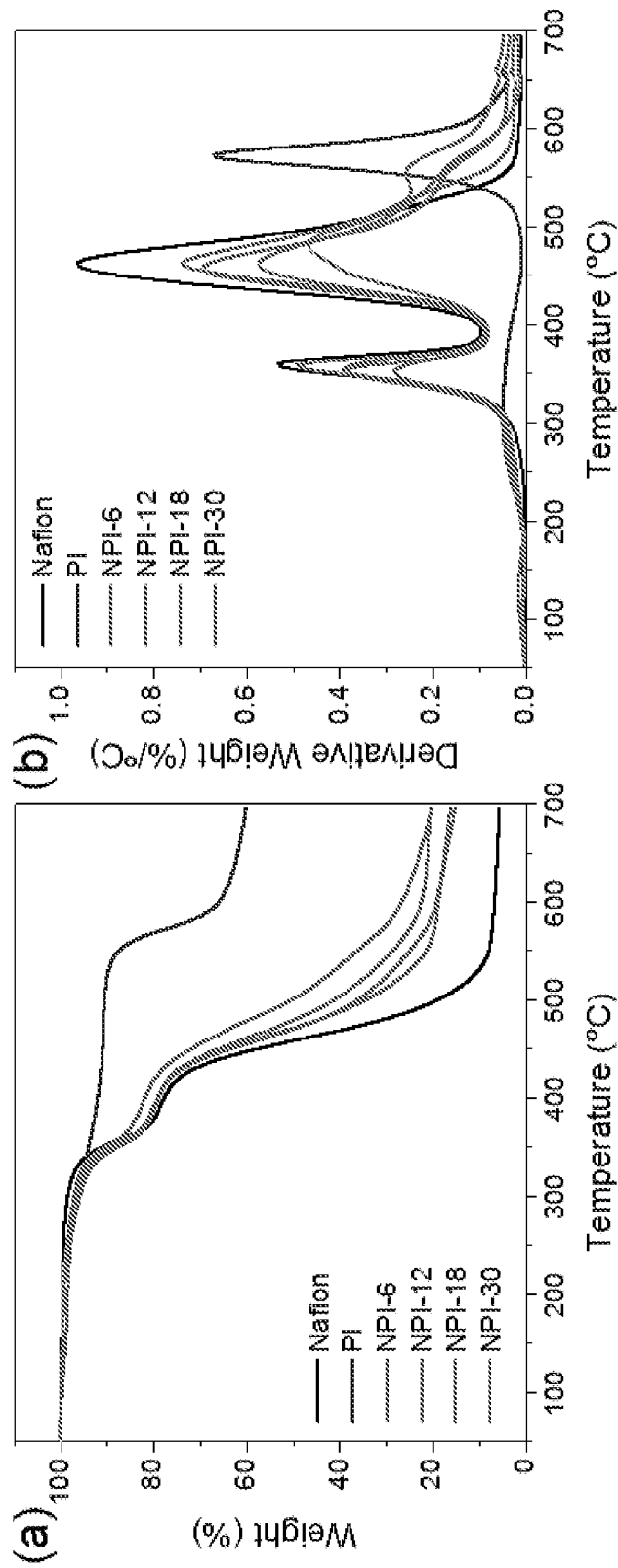


FIG. 5B

FIG. 5A

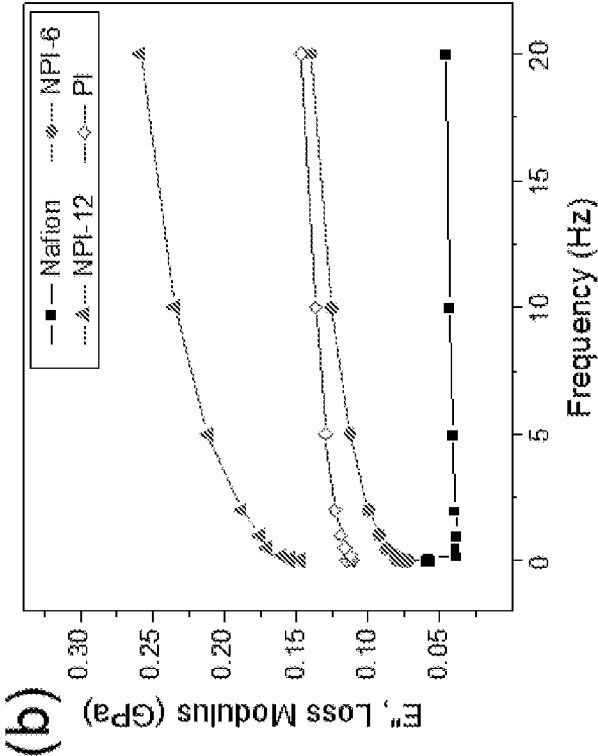


FIG. 6A

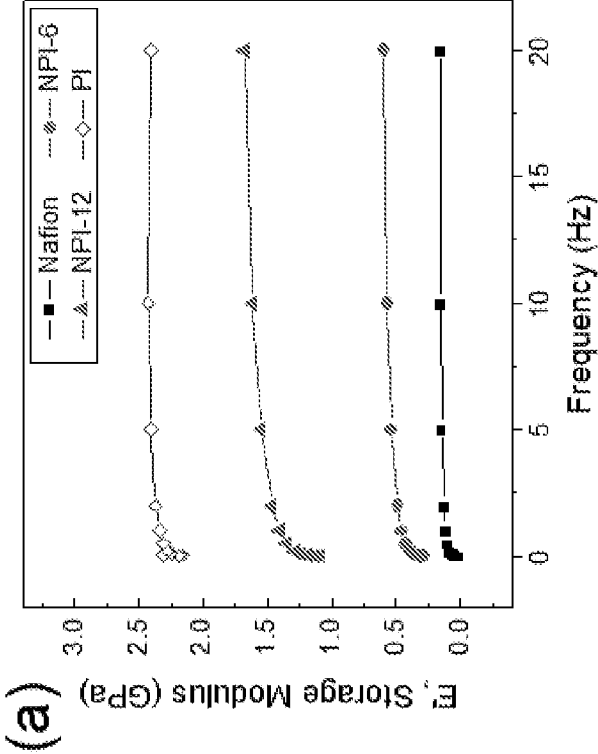


FIG. 6B

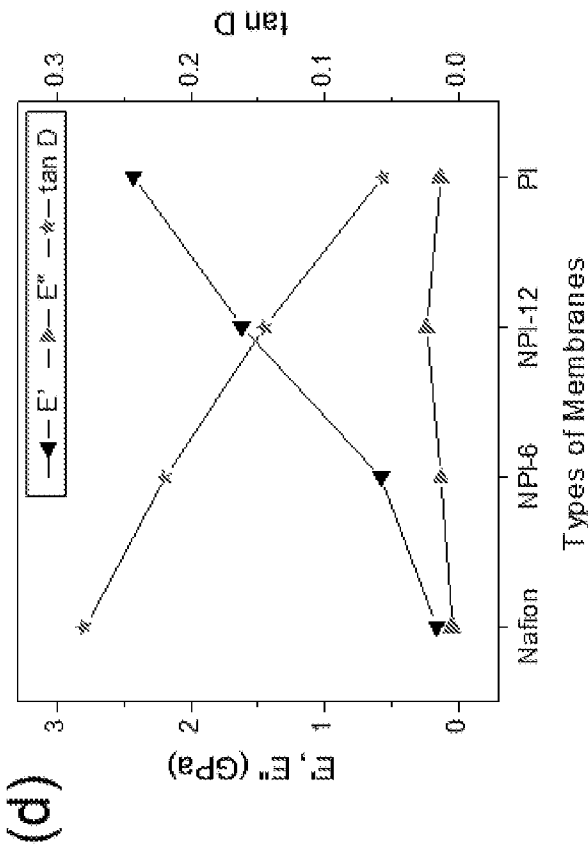


FIG. 6D

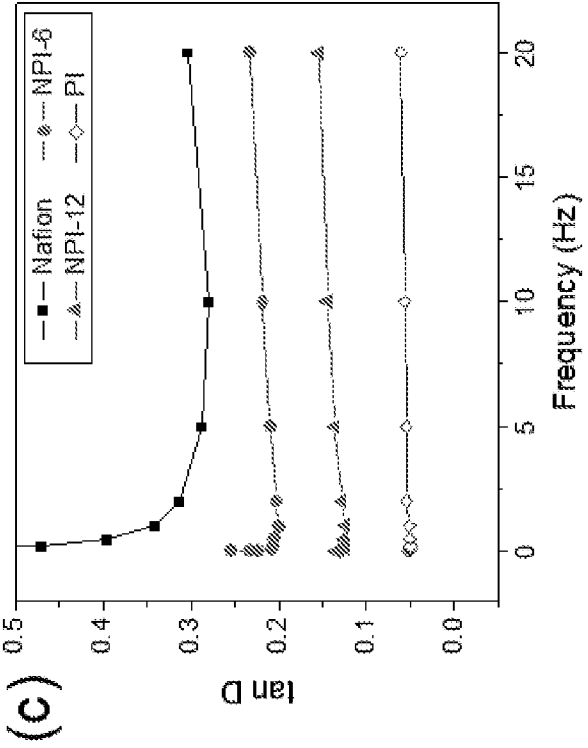


FIG. 6C

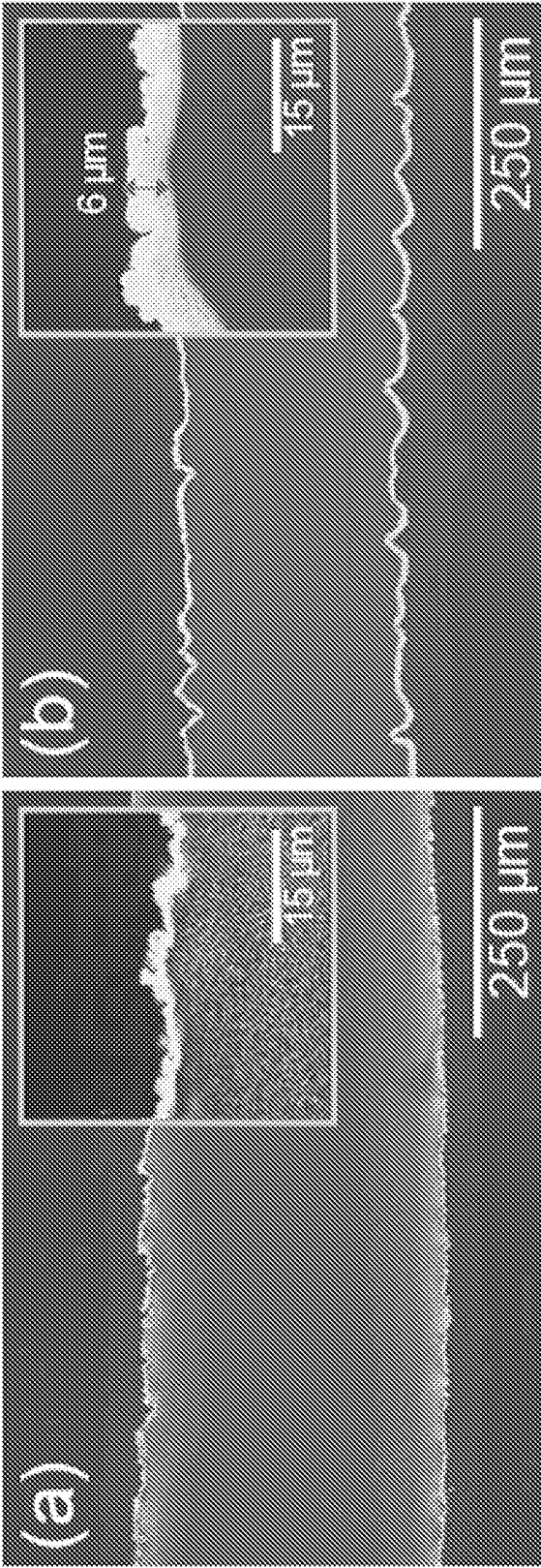


FIG. 7B

FIG. 7A

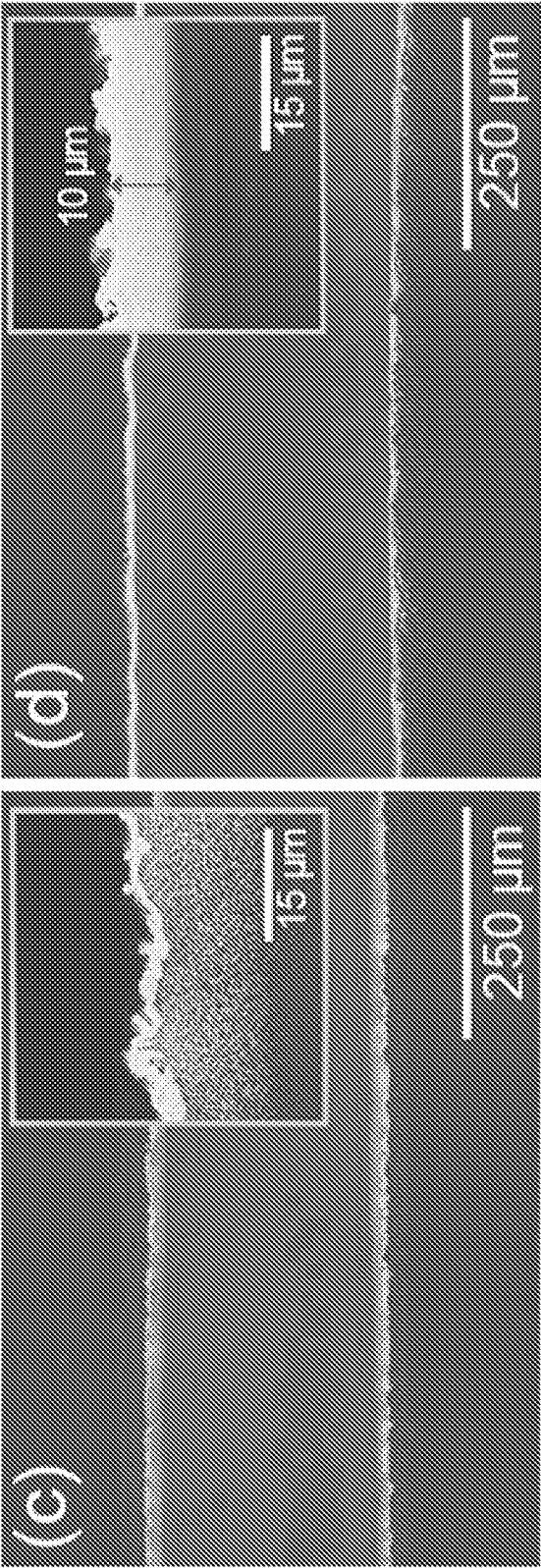


FIG. 7D

FIG. 7C

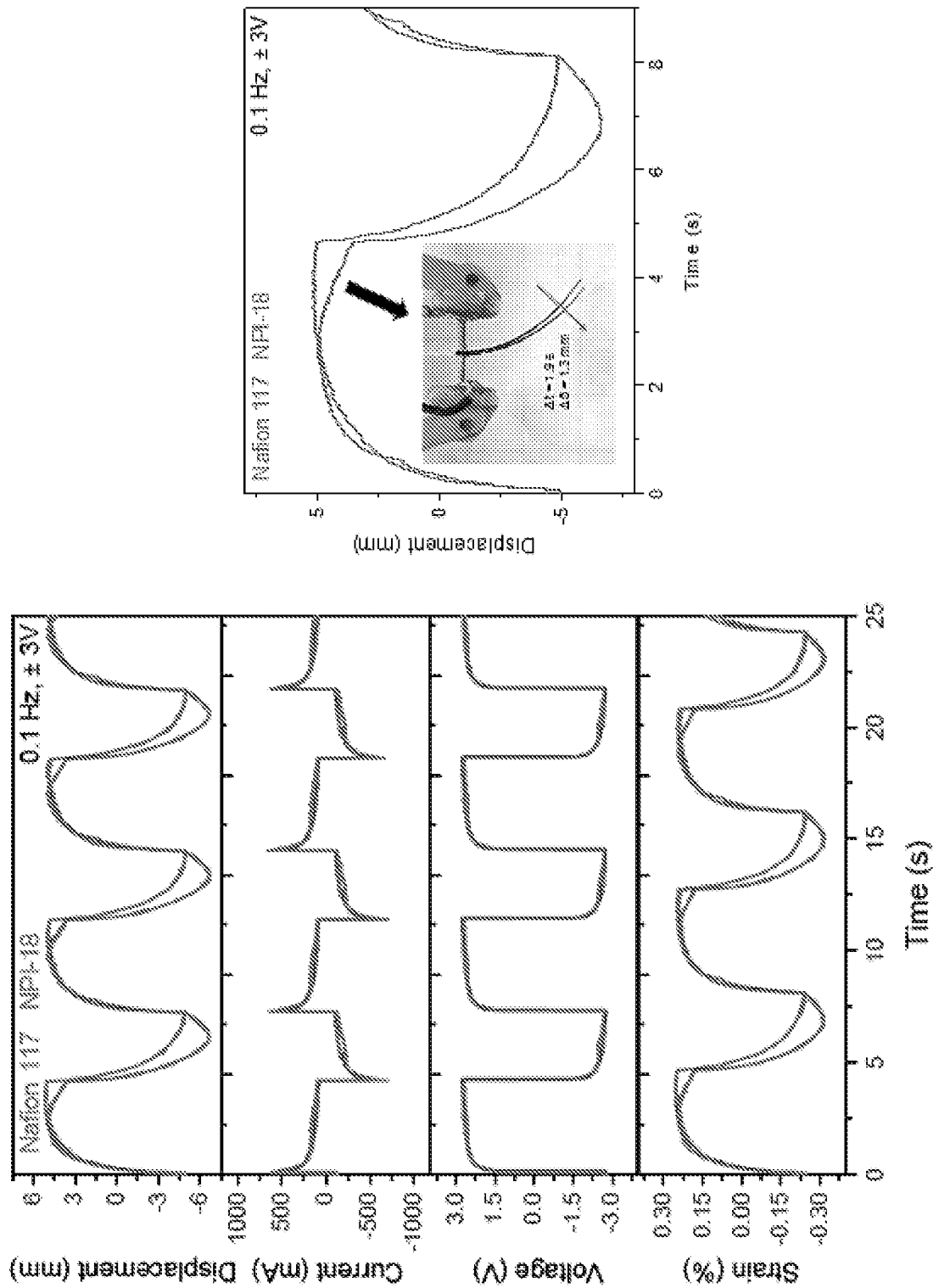


FIG. 8A

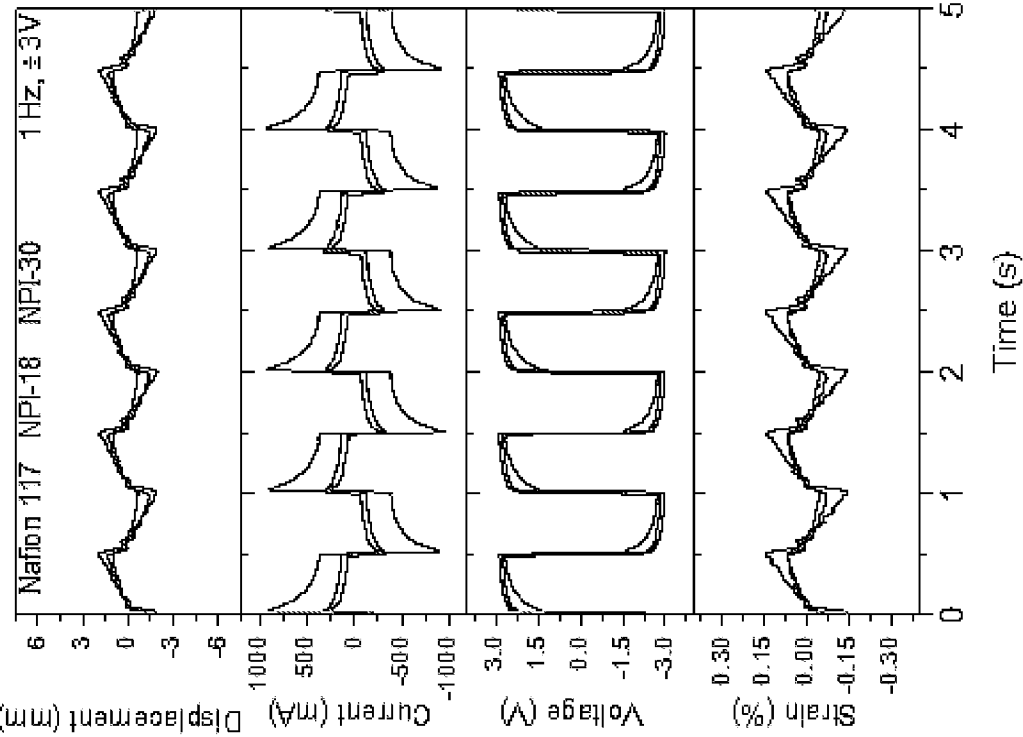


FIG. 8B

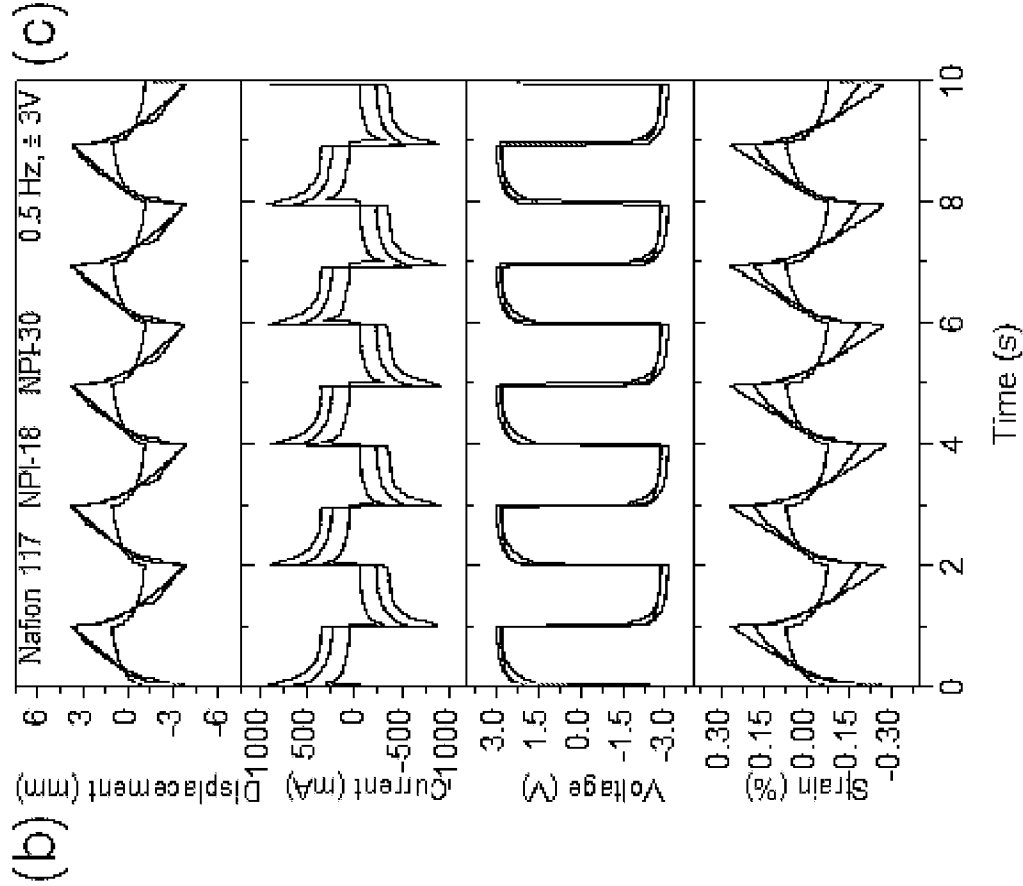


FIG. 8C

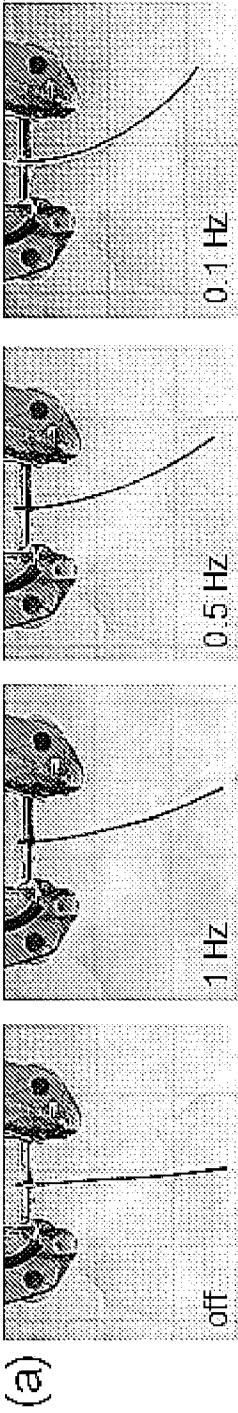


FIG. 9A

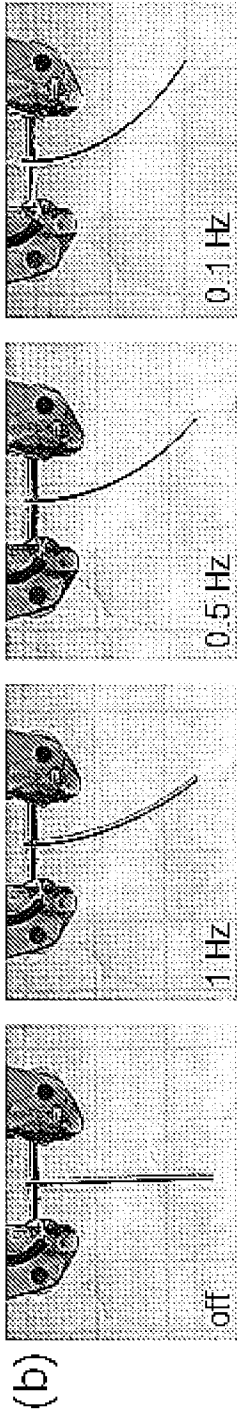


FIG. 9B

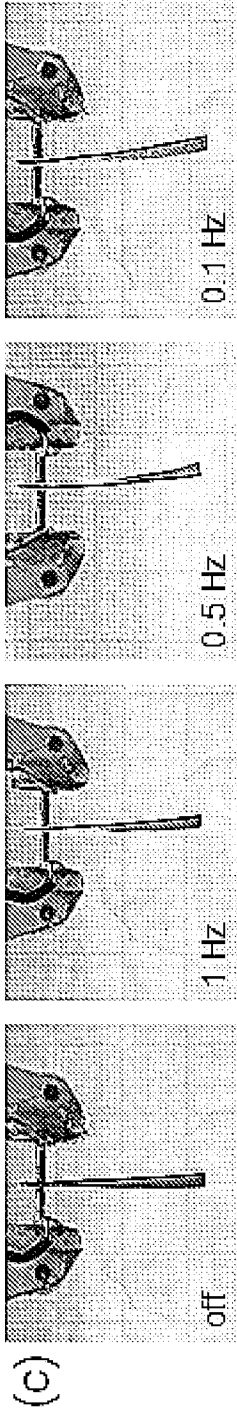


FIG. 9C

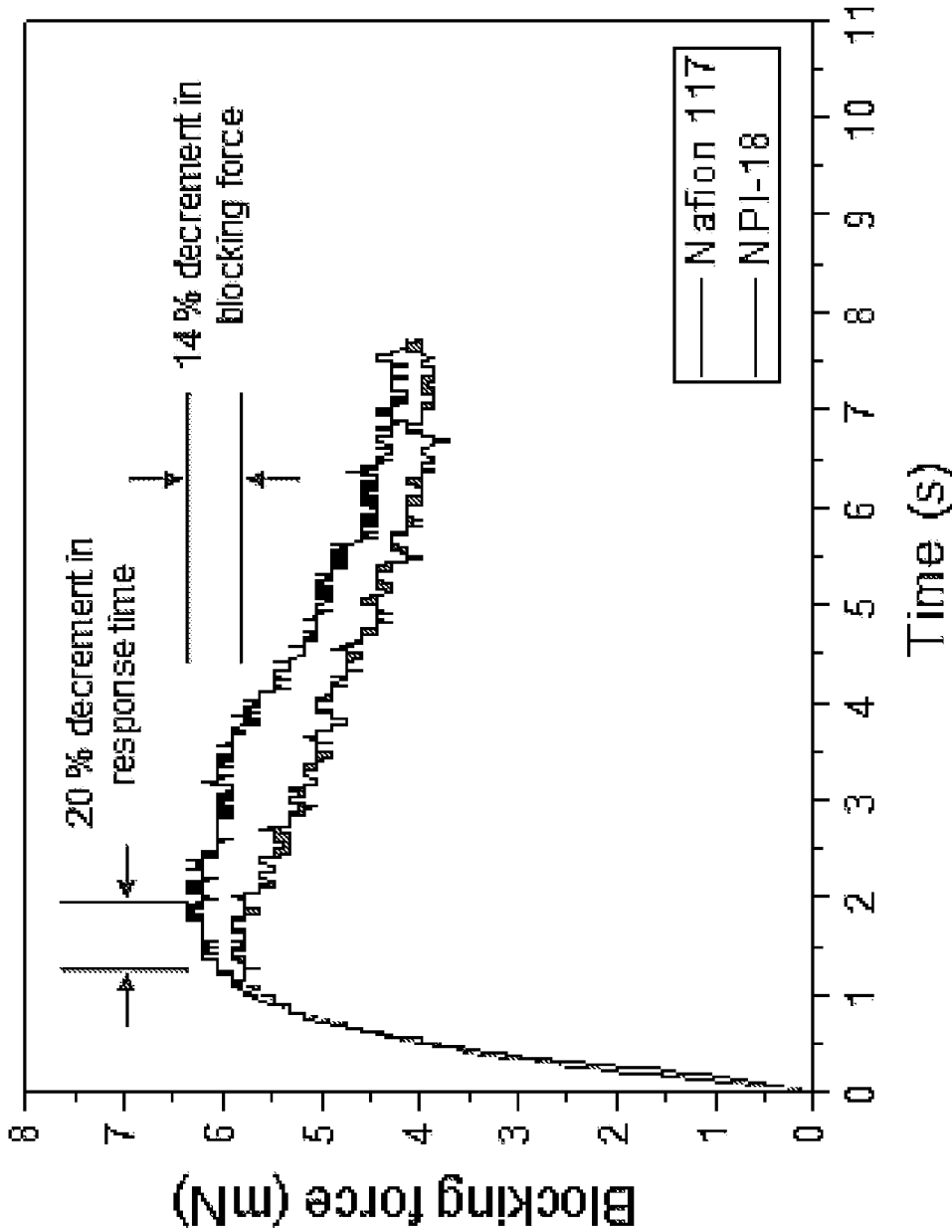


FIG. 10

INTERNATIONAL SEARCH REPORT

International application No.

PCT/US 17/44667

A. CLASSIFICATION OF SUBJECT MATTER
 IPC(8) - B01D 71/64, B01D 53/22, C08L 79/08 (2017.01)
 CPC - C08L 79/08, B01D 53/228, C08L 2205/02

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

See Search History Document

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

See Search History Document

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)

See Search History Document

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	US 2005/031925 A1 (OFER et al.) 10 February 2005 (10.02.2005), entire document, especially: abstract; para [0038]; para [0060]; para [0061]; para [0065]; para [0084]; para [0119], Formula II; para [0125]; para [0147]; para [0148]; para [0150]; para [0156]; para [0224]; para [0237]; para [0307]; pg 12, Table 1, Nafion; pg 12, Table 1, PAR; pg 13, Table 3, PI.	41
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Y		1-40
Y	WOO et al. "Synthesis and characterization of sulfonated polyimide membranes for direct methanol fuel cell", Journal of Membrane Science. 2003. Vol. 220, pp 31-45, entire document, especially: abstract; pg 34, Fig 1, SPAA-Et3N-theta.	1-40
A	US 2014/0120431 A1 (ROELOFS et al.) 1 May 2014 (01.05.2014), entire document.	1-41
A	US 2007/0231588 A1 (KANAKARAJAN et al.) 4 October 2007 (04.10.2007), entire document.	1-41

☐ Further documents are listed in the continuation of Box C.

☐ See patent family annex.

* Special categories of cited documents:

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"E" earlier application or patent but published on or after the international filing date

"L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified)

"O" document referring to an oral disclosure, use, exhibition or other means

"P" document published prior to the international filing date but later than the priority date claimed

"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention

"X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone

"Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art

"&" document member of the same patent family

Date of the actual completion of the international search

26 September 2017 (26.09.2017)

Date of mailing of the international search report

18 OCT 2017

Name and mailing address of the ISA/US

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 Facsimile No. 571-273-8300

Authorized officer:

Lee W. Young

PCT Helpdesk: 571-272-4300
 PCT OSP: 571-272-7774